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Preface

This manual is a language reference for users of the Cadence[®] Library Exchange Format (LEF) and Design Exchange Format (DEF) integrated circuit (IC) description languages.

LEF defines the elements of an IC process technology and associated library of cell models. DEF defines the elements of an IC design relevant to physical layout, including the netlist and design constraints. LEF and DEF inputs are in ASCII form.

This manual assumes that you are familiar with the development and design of integrated circuits.

This preface provides the following information:

- What's New on page 9
- Related Documents on page 9
- <u>Typographic and Syntax Conventions</u> on page 10
- Character Information on page 11

What's New

For information on what is new or changed in LEF and DEF for version 5.5, see <u>What's New in LEF/DEF.</u>

Related Documents

The following Cadence tools read LEF and DEF files and write layout data in DEF. For information about these tools, see the related documents in the Cadence online documentation system (CDSDoc).

- Silicon Ensemble[®] Place-and-Route
- Cadence Ultra Placer
- Cadence Ultra Router
- Cadence Clock Tree Generator

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■ Pearl[®] Timing Analyzer

Note: References in this manual to specific place-and-route tools are meant to note how those tools must use the LEF or DEF syntax. They do not refer to using LEF or DEF syntax in general. Other place-and-route tools might also have limitations when using LEF and DEF syntax. For information on any limitations, see the documentation for the specific tool.

Typographic and Syntax Conventions

This list describes the conventions used in this manual.

text	Words in monospace type indicate keywords that you must enter literally. These keywords represent language tokens.
variable	Words in $italics$ indicate user-defined information for which you must substitute a name or a value.
objRegExpr	An object name with the identifier $objRegExpr$ represents a regular expression for the object name.
pt	Represents a point in the design. This value corresponds to a coordinate pair, such as x y. You must enclose a point within parentheses, with space between the parentheses and the coordinates. For example,
	RECT (1000 2000) (1500 400).
	Vertical bars separate possible choices for a single argument. They take precedence over any other character.
[]	Brackets denote optional arguments. When used with vertical bars, they enclose a list of choices from which you can choose one.
{ }	Braces followed by three dots indicate that you must specify the argument at least once, but you can specify it multiple times.
{ }	Braces used with vertical bars enclose a list of choices from which you must choose one.
	Three dots indicate that you can repeat the previous argument. If they are used with brackets, you can specify zero or more

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	_	ey are used with braces, you must specify at ent, but you can specify more.
,		ree dots together indicate that if you specify rgument, you must separate those arguments
н н		enclose string values. Write quotation marks \ \ ". Write a backslash within a string as \\.
Any characters not incentered literally.	cluded in the list above	are required by the language and must be
Character Info	ormation	
LEF and DEF suppor	t the following characte	rs:
!		< and >
\$. (period)
&		?
		{ }
:		′ (single quotation mark)
1		" (double quotation mark)
@		_ (underbar)
~		^
=		, (comma)
Uppercase and lower characters	case alphabet	Numbers
DEF reserves the follo	owing characters for sp	ecial functions:
+ Start of new	keyword	

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Default special characters for bus bits unless overridden by BUSBITCHARS

Default special character for hierarchy unless overridden by DIVIDERCHAR

Coordinates and start of new keyword

[]

Preface

LEF and DEF names cannot contain the following ASCII characters:

\n Newline

Space

; Semicolon

Note: LEF and DEF names also cannot contain the ASCII character used by the place-androute tool for comments. For example, if the tool uses the pound sign (#) for comments, it cannot be used in a LEF or DEF name.

LEF and DEF interpret the following characters as regular expressions. Use these characters in LEF and DEF names only when you intend a regular expression.

* Asterisk Matches any sequence of characters

Percent Matches any single character

Note: Pattern matching only works in a few areas of the DEF file, such as component name matching in the SPECIALNET section, and component name matching in GROUP definitions.

You can use the backslash (\) as an escape character. When the backslash precedes a character that has special meaning in LEF or DEF, the special meaning of the character is ignored. The following characters have special meanings that can be escaped:

BUSBITCHARS delimiterPair The characters you specify to enclose bus

bits

DIVIDERCHAR character The character you specify to express

hierarchy

\ The backslash character

Note: You cannot use the escape character with the pound sign (#).

LEF Syntax

This chapter contains information about the following topics:

- About Library Exchange Format Files on page 14
 - General Rules on page 14
 - □ Managing LEF Files on page 15
 - Order of LEF Statements on page 16
- <u>LEF Statement Definitions</u> on page 16
 - □ Bus Bit Characters on page 16
 - □ <u>Clearance Measure</u> on page 17
 - □ <u>Divider Character</u> on page 17
 - □ Extensions on page 18
 - □ Layer (Cut) on page 18
 - □ <u>Layer (Implant)</u> on page 25
 - □ <u>Layer (Masterslice or Overlap)</u> on page 27
 - □ <u>Layer (Routing)</u> on page 28
 - □ Macro on page 56

Layer Geometries on page 69

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- □ Manufacturing Grid on page 82
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LEF Syntax

- □ Nondefault Rule on page 84
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- Property Definitions on page 88
- □ Same-Net Spacing on page 89
- □ Site on page 91
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- Version on page 95
- □ <u>Via</u> on page 95
- □ <u>Via Rule</u> on page 100
- □ Via Rule Generate on page 102

About Library Exchange Format Files

A Library Exchange Format (LEF) file contains library information for a class of designs. Library data includes layer, via, placement site type, and macro cell definitions. The LEF file is an ASCII representation using the syntax conventions described in Typographic and Syntax Conventions on page 10.

General Rules

Note the following information about creating LEF files:

- Lines in the LEF file are limited to 2,048 characters (extra characters are truncated).
- Distance is specified in microns.
- Distance precision is controlled by the UNITS statement.
- LEF statements end with a semicolon (;). You must leave a space between the last character in the statement and the semicolon.

LEF Syntax

Managing LEF Files

You can define all of your library information in a single LEF file; however this creates a large file that can be complex and hard to manage. Instead, you can divide the information into two files, a "technology" LEF file and a "cell library" LEF file.

A technology LEF file contains all of the LEF technology information for a design, such as placement and routing design rules, and process information for layers. A technology LEF file can include all of the following LEF statements:

```
VERSION statement
NAMESCASESENSITIVE statement
BUSBITCHARS statement
DIVIDERCHAR statement
[ UNITS statement ]
[ MANUFACTURINGGRID statement ]
[ NOWIREEXTENSIONATPIN statement ]
[ USEMINSPACING statement ]
[ CLEARANCEMEASURE statement ]
[ PROPERTYDEFINITIONS statement ]
{ LAYER (Nonrouting) statement
  | LAYER (Routing) statement } ...
[ MAXVIASTACK statement ]
{ VIA statement } ...
{ VIARULE statement
  | VIARULE GENERATE statement } ...
[ NONDEFAULTRULE statement ] ...
[ SPACING statement ]
{ SITE statement} ...
[ BEGINEXT statement ] ...
```

A cell library LEF file contains the macro and standard cell information for a design. A library LEF file can include the following statements:

```
VERSION statement
NAMESCASESENSITIVE statement
BUSBITCHARS statement
DIVIDERCHAR statement
[ SITE statement ]
{ MACRO statement
      [ PIN statement ] ...
      [ OBS statement ] ...
[ BEGINEXT statement ] ...
```

When reading in the LEF files, always read in the technology LEF file first.

LEF Syntax

Order of LEF Statements

LEF files can contain the following statements. You must specify the statements in the following order:

```
VERSION statement
NAMESCASESENSITIVE statement
BUSBITCHARS statement
DIVIDERCHAR statement
[ UNITS statement ]
[ MANUFACTURINGGRID statement ]
[ NOWIREEXTENSIONATPIN statement ]
[ USEMINSPACING statement ]
[ CLEARANCEMEASURE statement ]
[ PROPERTYDEFINITIONS statement ]
{ LAYER (Nonrouting) statement
  | LAYER (Routing) statement } ...
[ MAXVIASTACK statement ]
{ VIA statement } ...
{ VIARULE statement
  | VIARULE GENERATE statement } ...
[ NONDEFAULTRULE statement ] ...
[ SPACING statement ]
{ SITE statement} ...
{ MACRO statement
   [PIN statement ] ...
   [OBS statement ...]} ...
[ BEGINEXT statement ] ...
END LIBRARY
```

Note: If the statements are not defined in the LEF file, many applications assume default values for the header section (VERSION, NAMESCASESENSITIVE, BUSBITCHARS and DIVIDERCHAR). However, the default values are not formally part of the language definition; therefore, you cannot be sure that the same assumptions are used in all applications. You should always explicitly define these values.

LEF Statement Definitions

The following definitions describe the syntax arguments for the statements that make up a LEF file. Statements are listed in alphabetical order, *not* in the order they must appear in a LEF file. For the correct order, see "Order of LEF Statements" on page 16.

Bus Bit Characters

```
BUSBITCHARS "delimiterPair";
```

LEF Syntax

Specifies the pair of characters used to specify bus bits when LEF names are mapped to or from other databases. The characters must be enclosed in double quotation marks. For example:

```
BUSBITCHARS "[]";
```

If one of the bus bit characters appears in a LEF name as a regular character, you must use a backslash (\) before the character to prevent the LEF reader from interpreting the character as a bus bit delimiter.

Note: If you do not specify the BUSBITCHARS statement in your LEF file, many applications assume a default value of "[]". However, this default is not formally part of the language definition; therefore, you cannot be sure that the same assumptions are used in all applications. You should always explicitly define this value.

Clearance Measure

```
[CLEARANCEMEASURE {MAXXY | EUCLIDEAN} ;]
```

Defines the clearance spacing requirement that will be applied to pins and obstructions (blockages) in cells. If you do not specify a CLEARANCEMEASURE statement, euclidean distance is used by default.

MAXXY Uses the largest x or y distances for spacing between objects.

EUCLIDEAN Uses the euclidean distance for spacing between objects. That

is, the square root of $x^2 + y^2$.

Divider Character

```
DIVIDERCHAR "character";
```

Specifies the character used to express hierarchy when LEF names are mapped to or from other databases. The character must be enclosed in double quotation marks. For example:

```
DIVIDERCHAR "/" ;
```

If the divider character appears in a LEF name as a regular character, you must use a backslash (\) before the character to prevent the LEF reader from interpreting the character as a hierarchy delimiter.

Note: If you do not specify the DIVIDERCHAR statement in your LEF file, many applications assume a default value of "/". However, this default is not formally part of the language definition; therefore, you cannot be sure that the same assumptions are used in all applications. You should always explicitly define this value.

LEF Syntax

Extensions

```
[BEGINEXT "tag" extension
ENDEXT]
```

Adds customized syntax to the LEF file that can be ignored by tools that do not use that syntax. You can also use extensions to add new syntax not yet supported by your version of LEF/DEF, if you are using version 5.1 or later.

extension

Specifies the contents of the extension.

"tag"

Identifies the extension block. You must enclose tag in double quotation marks.

Example 1-1 Extension Statement

```
BEGINEXT "1VSI Signature 1.0"

CREATOR "company name"

DATE "timestamp"

REVISION "revision number"

ENDEXT
```

Layer (Cut)

```
LAYER layerName
    TYPE CUT ;
     [SPACING minSpacing
        [ LAYER 2ndLayerName
        | ADJACENTCUTS {3 | 4} WITHIN distance]
     [PROPERTY propName propVal ;] ...
     [ACCURRENTDENSITY { PEAK | AVERAGE | RMS}
       { value
        FREQUENCY freq_1 freq_2 ...;
           [CUTAREA cutArea_1 cutArea_2 ... ;]
           TABLEENTRIES
            v_freq_1_cutArea_1 v_freq_1_cutArea_2 ...
            v_freq_2_cutArea_1 v_freq_2_cutArea_2 ...
       } ;]
     [DCCURRENTDENSITY AVERAGE
       { value
        CUTAREA cutArea_1 cutArea_2 ... ;
           TABLEENTRIES value 1 value 2 ...
     [ANTENNAMODEL {OXIDE1 | OXIDE2 | OXIDE3 | OXIDE4} ;] ...
     [ANTENNAAREARATIO value ;] ...
```

LEF Syntax

```
[ANTENNADIFFAREARATIO \{value \mid PWL \ (\ d1\ r1\ )\ (\ d2\ r2\ )\ \ldots)\};]... [ANTENNACUMAREARATIO value;]... [ANTENNACUMDIFFAREARATIO \{value \mid PWL \ (\ d1\ r1\ )\ (\ d2\ r2\ )\ \ldots)\};]... [ANTENNAAREAFACTOR value;]...
```

END layerName

Defines cut layers in the design. Each cut layer is defined by assigning it a name and design rules. You must define cut layers separately, with their own layer statements.

You must define layers in process order from bottom to top. For example:

poly	masterslice
cut01	cut
metal1	routing
cut12	cut
metal2	routing
cut23	cut
metal3	routing

ACCURRENTDENSITY

Specifies how much AC current a cut of a certain area can handle at a certain frequency. For an example using the ACCURRENTDENSITY syntax, see Example 1-4 on page 32.

The ACCURRENTDENSITY syntax is defined as follows:

```
{PEAK | AVERAGE | RMS}
{ value
  FREQUENCY freq_1 freq_2 ...;
    [CUTAREA cutArea_1 cutArea_2 ... ;]
    TABLEENTRIES
    v_freq_1_cutArea_1 v_freq_1_cutArea_2 ...
    v_freq_2_cutArea_1 v_freq_2_cutArea_2 ...
} ;:
PEAK
                  Specifies the peak limit of the layer.
                  Specifies the average limit of the layer.
AVERAGE
                  Specifies the root mean square limit of the
RMS
                  layer.
                  Specifies a maximum current limit for the
value
                  layer in milliamps per square micron
                  (mA/\mu m^2).
                  Type: Float
```

LEF Syntax

FREOUENCY

Specifies frequency values, in megahertz. You can specify more than one frequency. If you specify multiple frequency values, the values must be specified in ascending order.

If you specify only one frequency value, there is no frequency dependency, and the table entries are assumed to apply to all frequencies.

Type: Float

CUTAREA

Specifies cut area values, in square microns (μm^2). You can specify more than one cut area. If you specify multiple cut area values, the values must be specified in ascending order.

If you specify only one cut area value, there is no cut area dependency, and the table entries are assumed to apply to all cut areas.

Type: Float

TABLEENTRIES

Defines the maximum current for each frequency and cut area pair specified in the FREQUENCY and CUTAREA statements, in mA/µm².

The pairings define each cut area for the first frequency in the FREQUENCY statement, then the cut areas for the second frequency, and so on. The final value for a given cut area and frequency is computed from a linear interpolation of the table values.

Type: Float

ANTENNAAREAFACTOR value

Specifies the multiply factor for the antenna metal area calculation.

Default: 1.0 Type: Float

LEF Syntax

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

Note: If you specify a value that is greater than 1.0, the computed areas will be larger, and violations will occur more frequently.

ANTENNAAREARATIO value

Specifies the maximum legal antenna ratio, using the area of the metal wire that is not connected to the diffusion diode. For more information on process antenna calculation, see <u>Appendix D</u>, <u>"Calculating and Fixing Process Antenna Violations,"</u>

Type: Integer

ANTENNACUMAREARATIO value

Specifies the cumulative antenna ratio, using the area of the metal wire that is not connected to the diffusion diode. For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations",

Type: Integer

ANTENNACUMDIFFAREARATIO $\{value \mid PWL \ (\ d1 \ r1\)\ (\ d2 \ r2\)...)\}$

Specifies the cumulative antenna ratio, using the area of the metal wire that is connected to the diffusion diode. You can supply an explicit ratio value or specify piece-wise linear format (PWL), in which case the cumulative ratio is calculated using linear interpolation of the diffusion area and ratio input values. The diffusion input values must be specified in ascending order. *Type:* Integer

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

ANTENNADIFFAREARATIO $\{value \mid PWL ((d1 r1)(d2 r2)...)\}$

Specifies the antenna ratio, using the area of the metal wire connected to the diffusion diode. You can supply an explicit ratio value or specify piece-wise linear format (PWL), in which case the ratio is calculated using linear interpolation of the diffusion area and ratio input values. The diffusion input values must be specified in ascending order.

Type: Integer

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LEF Syntax

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations."

```
ANTENNAMODEL {OXIDE1 | OXIDE2 | OXIDE3 | OXIDE4}
```

Specifies the oxide model for the layer. If you specify an ANTENNAMODEL statement, that value affects all ANTENNA* statements for the layer that follow it until you specify another ANTENNAMODEL statement.

Default: OXIDE1, for a new LAYER statement

Value: OXIDE1 or OXIDE2

Note: OXIDE1 and OXIDE2 are currently supported. If you specify OXIDE3 or OXIDE4, current tools parse and ignore them.

Because LEF is sometimes used incrementally, if an ANTENNA statement occurs twice for the same oxide model, the last value specified is used. For any given ANTENNA keyword, only one value or PWL table is stored for each oxide metal on a given layer.

For an example using the ANTENNAMODEL syntax, see Example 1-5 on page 36.

DCCURRENTDENSITY

Specifies how much DC current a via cut of a certain area can handle in units of milliamps per square micron (mA/μm²). For an example using the DCCURRENTDENSITY syntax, see Example 1-6 on page 38.

The DCCURRENTDENSITY syntax is defined as follows:

```
AVERAGE
{ value
CUTAREA cutArea_1 cutArea_2 ...;
    TABLEENTRIES value_1 value_2 ...
};
AVERAGE
                Specifies the average limit for the layer.
                Specifies a current limit for the layer in
value
                mA/\mu m^2.
                 Type: Float
```

LEF Syntax

CUTAREA Specifies cut area values, in square microns.

You can specify more than one cut area value. If you specify multiple cut area values, the values must be specified in ascending

order. *Type:* Float

TABLEENTRIES Specifies the maximum current density for

each specified cut area, in mA/ μ m². The final value for a specific cut area is computed from a linear interpolation of the table values.

Type: Float

LAYER LayerName

Specifies the name for the layer. This name is used in later references to the layer.

PROPERTY propName propVal

Specifies a numerical or string value for a layer property defined in the PROPERTYDEFINITIONS statement. The propName you specify must match the propName listed in the

PROPERTYDEFINITIONS statement.

SPACING

Specifies the minimum spacing allowed between via cuts on the same net or different nets. This value can be overridden by the SAMENET SPACING statement. For an example using the SPACING syntax, see Example 1-2 on page 24.

The SPACING syntax is defined as follows:

minSpacing Specifies the default minimum spacing

between via cuts, in microns.

Type: Float

LAYER 2ndLayerName

Applies the spacing rule between objects on the cut layer and objects on <code>2ndLayerName</code>. The second cut layer must already be defined in the LEF file.

LEF Syntax

ADJACENTCUTS {3 | 4} WITHIN distance

Applies the spacing rule only when the cut has at least three or four via cuts that are less than <code>distance</code>, in microns, from each other. You can specify only one ADJACENTCUTS statement per cut layer. For more information, see "Adjacent Via Cuts" on page 24.

Type: Float (distance)

TYPE CUT

Specifies that the layer is for contact-cuts. The type is later referenced in vias and in rules for generating vias.

Example 1-2 Spacing Statement

The following SPACING rule specifies that extra space is needed for any via with more than than three adjacent cuts, which happens if one via has more than 2x2 cuts. A cut that is within .25 μ m of three other cuts requires spacing that is greater than or equal to 0.22μ m.

```
LAYER CUT12

SPACING 0.20; #default cut spacing

SPACING 0.22 ADJACENTCUTS 3 WITHIN 0.25;

...

END CUT12
```

The following SPACING rule specifies that extra space is required for any via with 3x3 cuts or more (that is, a cut with four or more adjacent cuts). A cut that is within .25 μ m of to four other cuts requires spacing that is greater than or equal to 0.22 μ m.

```
LAYER CUT12

SPACING 0.20; #default cut spacing
SPACING 0.22 ADJACENTCUTS 4 WITHIN 0.25;
...
END CUT12
```

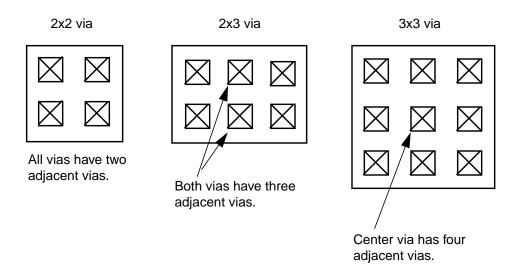
Adjacent Via Cuts

A cut is considered adjacent if it is within distance of another cut in any direction (including a 45-degree angle). Figure 1-1 on page 25 illustrates adjacent via cuts for 2x2, 2x3, and 3x3 vias, for typical spacing values (that is, the diagonal spacing is greater than the ADJACENTCUTS distance value). For three adjacent cuts, the ADJACENTCUTS rule allows tight cut spacing on 1xn vias and 2x2 vias, but requires larger cut spacing on 2x3, 2x4 and 3xn vias. For four adjacent cuts, the rule allows tight cut spacing on 2xn vias, but it requires larger cut spacing on 3xn vias.

LEF Syntax

The ADJACENTCUTS rule overrides the cut-to-cut spacing used in VIARULE GENERATE statements for large vias if the ADJACENTCUTS spacing value is larger that the VIARULE spacing value.

Figure 1-1



Layer (Implant)

```
LAYER layerName

TYPE IMPLANT;

[WIDTH minWidth;]

[SPACING minSpacing [LAYER layerName2];]...

[PROPERTY propName propVal;]...

END layerName
```

Defines implant layers in the design. Each layer is defined by assigning it a name and simple spacing and width rules. These spacing and width rules only affect the legal cell placements. These rules interact with the library methodology, detailed placement, and filler cell support. You must define implant layers separately, with their own layer statements.

LAYER 1	ayerName	Specifies the name for the layer. This name is used in later references to the layer.
LAYER 1	-	Specifies the name of another implant layer that requires extra spacing that is greater than or equal to minspacing from this implant layer.

LEF Syntax

PROPERTY propName propVal

Specifies a numerical or string value for a layer property defined in the PROPERTYDEFINITIONS statement. The propName you

specify must match the propName listed in the

PROPERTYDEFINITIONS statement.

SPACING minSpacing Specifies the minimum spacing for the layer, in microns. This

value affects the legal cell placement.

Type: Float

TYPE IMPLANT Identifies the layer as an implant layer.

WIDTH minWidth Specifies the minimum width for this layer, in microns. This value

affects the legal cell placement.

Type: Float

Example 1-3 Implant Layer

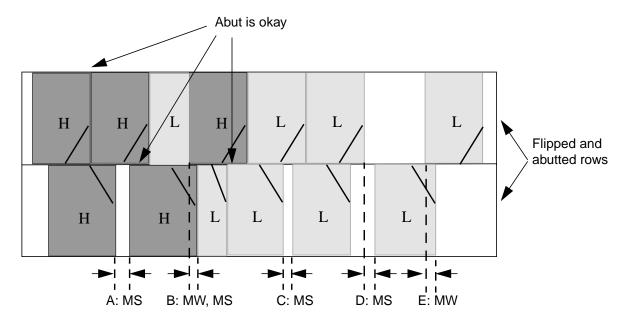
Typically, you define high-drive cells on one implant layer and low-drive cells on another implant layer. The following example defines high-drive cells on *implant1* and low-drive cells on *implant2*. Both implant layers cover the entire cell. The placers and filler cell creation attempt to legalize the cell overlaps in abutting rows to ensure that the minimum width and spacing values are met.

```
#high-drive implant layer
LAYER implant1
   TYPE IMPLANT;
                     \#implant rectangles must be >=0.50 microns wide
   WIDTH 0.50;
   SPACING 0.50;
                     #implant rectangles must be >=0.50 microns apart
END implant1
LAYER implant2
                     #low-drive imlpant layer
   TYPE IMPLANT ;
   WIDTH 0.50;
                     #implant rectangles must be >=0.50 microns wide
   SPACING 0.50;
                     #implant rectangles must be >=0.50 microns apart
END implant2
```

Assume that the high-drive cells and low-drive cells are completely covered by their respective implant layers. Because there is no spacing between *implant1* and *implant2* specified, you might see a placement like that illustrated in Figure 1-2 on page 27.

LEF Syntax

Figure 1-2



MS = Minimum spacing error MW = Minimum width error

Note that you can correct A, C, D, and E by putting in filler cells with the apropriate implant type. However, B cannot be corrected by a filler cell—either the placer must avoid it, or you must allow the filler cell or post-process command to move cells or modify the implant layer to correct the error.

Layer (Masterslice or Overlap)

```
LAYER layerName

TYPE {MASTERSLICE | OVERLAP};

[PROPERTY propName propVal;]...

END layerName
```

Defines masterslice (nonrouting) or overlap layers in the design. Masterslice layers are typically polysilicon layers and are only needed if the cell MACROS have pins on the polysilicon layer.

The overlap layer should normally be named OVERLAP. It can be used in MACRO definitions to form rectilinear-shaped cells and blocks (that is, an "L"-shaped block).

Each layer is defined by assigning it a name and design rules. You must define masterslice or overlap layers separately, with their own layer statements.

LEF Syntax

You must define layers in process order from bottom to top. For example:

poly masterslice
cut01 cut
metal1 routing
cut12 cut
metal2 routing
cut23 cut
metal3 routing

LAYER layerName

Specifies the name for the layer. This name is used in later

references to the layer.

TYPE

Specifies the purpose of the layer.

MASTERSLICE Layer is fixed in the base array. If pins

appear in the masterslice layers, you must define vias to permit the routers to connect those pins and the first routing layer. Wires are not allowed on masterslice layers.

Routing tools can use only one masterslice layer. If a masterslice layer is defined, exactly one cut layer must be defined between the masterslice layer and the

adjacent routing layers.

OVERLAP Layer used for overlap checking for

rectilinear blocks. Obstruction descriptions in the macro obstruction statements refer

to the overlap layer.

PROPERTY propName propVal

Specifies a numerical or string value for a layer property defined in the PROPERTYDEFINITIONS statement. The propName you specify must match the propName listed in the

PROPERTYDEFINITIONS statement.

Layer (Routing)

```
LAYER layerName

TYPE ROUTING;

DIRECTION {HORIZONTAL | VERTICAL};

PITCH distance;

WIDTH defWidth;

[OFFSET distance;]

[AREA minArea;]
```

LEF Syntax

```
[ [SPACING minSpacing
    [ RANGE minWidth maxWidth
       [ USELENGTHTHRESHOLD
       | INFLUENCE value [RANGE stubMinWidth stubMaxWidth]
       RANGE minWidth maxWidth]
    | LENGTHTHRESHOLD maxLength [RANGE minWidth maxWidth]
 ;] ...
| [SPACINGTABLE
   PARALLELRUNLENGTH {length} ...
        {WIDTH width {spacing} ...} ...;
    [SPACINGTABLE
     INFLUENCE {WIDTH width WITHIN distance SPACING spacing} ...;
  ] ]
[WIREEXTENSION value ; ]
[MINIMUMCUT numCuts WIDTH width
   [FROMABOVE | FROMBELOW]
   [LENGTH length WITHIN distance];] ...
[MAXWIDTH width ;]
[MINWIDTH width ;]
[MINSTEP distance ;]
[MINENCLOSEDAREA area [WIDTH width];]...
[PROTRUSIONWIDTH width1 LENGTH length WIDTH width2 ;]
[RESISTANCE RPERSQ value ;]
[CAPACITANCE CPERSODIST value ;]
[HEIGHT distance ;]
[THICKNESS distance ;]
[SHRINKAGE distance ;]
[CAPMULTIPLIER value ;]
[EDGECAPACITANCE value ;]
[SLOTWIREWIDTH minWidth ;]
[SLOTWIRELENGTH minLength ;]
[SLOTWIDTH minWidth ;]
[SLOTLENGTH minLength ;]
[MAXADJACENTSLOTSPACING spacing ;]
[MAXCOAXIALSLOTSPACING spacing ;]
[MAXEDGESLOTSPACING spacing ;]
[SPLITWIREWIDTH minWidth ;]
[MINIMUMDENSITY minDensity;]
[MAXIMUMDENSITY maxDensity ;]
[DENSITYCHECKWINDOW windowLength windowWidth ;]
[DENSITYCHECKSTEP stepValue ;]
[FILLACTIVESPACING spacing ;]
[ANTENNAMODEL {OXIDE1 | OXIDE2 | OXIDE3 | OXIDE4} ;] ...
[ANTENNAAREARATIO value ;] ...
[ANTENNADIFFAREARATIO \{value \mid PWL ((d1 r1)(d2 r2)...)\};]...
[ANTENNACUMAREARATIO value ;] ...
[ANTENNACUMDIFFAREARATIO \{value \mid PWL ((d1 r1)(d2 r2)...)\};]...
[ANTENNAAREAFACTOR value [DIFFUSEONLY] ;] ...
[ANTENNASIDEAREARATIO value ;] ...
```

LEF Syntax

```
[ANTENNADIFFSIDEAREARATIO \{value \mid PWL ((d1 r1) (d2 r2) ...)\};] ...
    [ANTENNACUMSIDEAREARATIO value ;] ...
    [ANTENNACUMDIFFSIDEAREARATIO \{value \mid PWL ((d1r1)(d2r2)...)\};]...
    [ANTENNASIDEAREAFACTOR value [DIFFUSEONLY];] ...
    [PROPERTY propName propVal ;] ...
    [ACCURRENTDENSITY {PEAK | AVERAGE | RMS}
        { value
        FREQUENCY freq_1 freq_2 ...;
           [WIDTH width_1 width_2 ...;]
           TABLEENTRIES
             v_freq_1_width_1 v_freq_1_width_2 ...
             v_freq_2_width_1 v_freq_2_width_2 ...
        } ;]
    [DCCURRENTDENSITY AVERAGE
        { value
        | WIDTH width 1 width 2 ...;
           TABLEENTRIES value 1 value 2 ...
END layerName
```

Defines routing layers in the design. Each layer is defined by assigning it a name and design rules. You must define routing layers separately, with their own layer statements.

You must define layers in process order from bottom to top. For example:

```
poly masterslice
cut01 cut
metal1 routing
cut12 cut
metal2 routing
cut23 cut
metal3 routing
```

ACCURRENTDENSITY

Specifies how much AC current a wire on this layer of a certain width can handle at a certain frequency in units of milliamps per micron (mA/µm).

Note: The true meaning of current density would have units of milliamps per square micron (mA/ μ m²); however, the thickness of the metal layer is implicitly included, so the units in this table are milliamps per micron, where only the wire width varies.

The ACCURRENTDENSITY syntax is defined as follows:

```
{PEAK | AVERAGE | RMS}
{ value
| FREQUENCY freq_1 freq_2 ...;
```

LEF Syntax

```
[WIDTH width_1 width_2 ...;]
    TABLEENTRIES
      v_freq_1_width_1 v_freq_1_width_2 ...
      v_freq_2_width_1 v_freq_2_width_2 ...
} ;
PEAK
                   Specifies the peak current limit of the layer.
AVERAGE
                   Specifies the average current limit of the
                   layer.
                   Specifies the root mean square current
RMS
                   limit of the layer.
                   Specifies a maximum current for the layer
value
                   in mA/μm.
                   Type: Float
                   Specifies frequency values, in megahertz.
FREQUENCY
                   You can specify more than one frequency.
                   If you specify multiple frequency values,
                   the values must be specified in ascending
                   order.
                   If you specify only one frequency value,
                   there is no frequency dependency, and the
                   table entries are assumed to apply to all
                   frequencies.
                   Type: Float
WIDTH
                   Specifies wire width values, in microns.
                   You can specify more than one wire width.
                   If you specify multiple width values, the
                   values must be specified in ascending
                   order.
                   If you specify only one width value, there is
                   no width dependency, and the table entries
                   are assumed to apply to all widths.
                    Type: Float
```

LEF Syntax

TABLEENTRIES

Defines the maximum current for each of the frequency and width pairs specified in the FREQUENCY and WIDTH statements, in mA/ μ m.

The pairings define each width for the first frequency in the FREQUENCY statement, then the widths for the second frequency, and so on.

The final value for a given wire width and frequency is computed from a linear interpolation of the table values. the widths are not adjusted for any process shrinkage, so the should be correct for the "drawn width".

Type: Float

Example 1-4 AC Current Density Statements

The following examples define AC current density tables:

```
LAYER met1
     . . .
     ACCURRENTDENSITY PEAK
                                       #peak AC current limit for met1
     FREQUENCY 100 400;
                                       #2 freq values in MHz
     WIDTH
      0.4 0.8 1.6 5.0 10.0 ;
                                       #5 width values in microns
     TABLEENTRIES
     9.0 7.5 6.5 5.4 4.7
                                       \#mA/\mu m for 5 widths and freq_1 (100 Mhz)
     7.5 6.8 6.0 4.8 4.0
                                       \#mA/\mu m for 5 widths and freq 2 (400 Mhz)
     ACCURRENTDENSITY AVERAGE
                                       #avg. AC current limit for met1
     50.0;
                                       \#mA/\mu m for any width at any frequency
     ACCURRENTDENSITY RMS
                                       #RMS AC current limit for met1
     FREOUENCY 1;
                                       #1 freq (required by syntax; not really used)
     WIDTH
      0.4 0.8 1.6 5.0 20.0 ;
                                       #5 width values in microns
     TABLEENTRIES
     7.5 6.8 6.0 4.8 4.0 ;
                                       \#mA/\mu m for 5 widths
END met1 ;
```

The PEAK current density at .4 μ m, 100 MHz is 9.0 OmA/ μ m. Therefore, a 0.4 μ m wide wire can carry 9.0 x .4 = 3.6 mA of PEAK current.

LEF Syntax

The RMS current density at .4 μ m is 7.5 mA/ μ m. Therefore, a 0.4 μ m wide wire can carry 7.5 x .4 = 3.0 mA of RMS current.

```
LAYER cut12
     . . .
                                  #peak AC current limit for one cut
     ACCURRENTDENSITY PEAK
                                  #2 freq values in MHz
     FREQUENCY 10 200;
       CUTAREA 0.16 0.32
                                 \#2 cut areas in \mu\text{m}^2
     TABLEENTRIES
                                  \#mA/\mu m^2 for 2 cut areas at freq_1 (10 Mhz)
     0.5 0.4 ;
                                  \#mA/\mu m^2 for 2 cut areas at freq_2 (200 Mhz)
     0.4 0.35 ;
     ACCURRENTDENSITY AVERAGE
                                  #average AC current limit for via cut12
                                  \#mA/\mu m^2 for any cut area at any frequency
     ACCURRENTDENSITY RMS
                                  #RMS AC current limit for via cut12
     FREQUENCY 1 ;
                                  #1 freq (required by syntax; not really used)
                                  #2 cut areas in um^2
       CUTAREA 0.16 1.6;
     TABLEENTRIES
                                  \#mA/\mu m^2 for 2 cut areas at any frequency
     10.0 9.0 ;
     . . . .
END cut12 ;
```

ANTENNAAREAFACTOR value [DIFFUSEONLY]

Specifies the multiply factor for the antenna metal area calculation. DIFFUSEONLY specifies that the current antenna factor should only be used when the corresponding layer is connected to the diffusion.

Default: 1.0 Type: Float

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

Note: If you specify a value that is greater than 1.0, the computed areas will be larger, and violations will occur more frequently.

ANTENNAAREARATIO value

Specifies the maximum legal antenna ratio, using the area of the metal wire that is not connected to the diffusion diode. For more information on process antenna calculation, see <u>Appendix D</u>, "Calculating and Fixing Process Antenna Violations,"

Type: Integer

LEF Syntax

ANTENNACUMAREARATIO value

Specifies the cumulative antenna ratio, using the area of the wire that is not connected to the diffusion diode. For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

Type: Integer

ANTENNACUMDIFFAREARATIO $\{value \mid PWL ((d1 r1)(d2 r2)...)\}$

Specifies the cumulative antenna ratio, using the area of the metal wire that is connected to the diffusion diode. You can supply and explicit ratio value or specify piece-wise linear format (PWL), in which case the cumulative ratio value is calculated using linear interpolation of the diffusion area and ratio input values. The diffusion input values must be specified in ascending order.

Type: Integer

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations."

ANTENNACUMDIFFSIDEAREARATIO $\{value \mid PWL \ (\ d1\ r1\)\ (\ d2\ r2\)\dots)\}$

Specifies the cumulative antenna ratio, using the side wall area of the metal wire that is connected to the diffusion diode. You can supply and explicit ratio value or specify piece-wise linear format (PWL), in which case the cumulative ratio value is calculated using linear interpolation of the diffusion area and ratio input values. The diffusion input values must be specified in ascending order.

Type: Integer

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

ANTENNACUMSIDEAREARATIO value

Specifies the cumulative antenna ratio, using the side wall area of the metal wire that is not connected to the diffusion diode. For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations."

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LEF Syntax

ANTENNADIFFAREARATIO $\{value \mid PWL ((d1 r1)(d2 r2)...)\}$

Specifies the antenna ratio, using the area of the metal wire that is connected to the diffusion diode. You can supply and explicit ratio value or specify piece-wise linear format (PWL), in which case the ratio value is calculated using linear interpolation of the diffusion area and ratio input values. The diffusion input values must be specified in ascending order.

Type: Integer

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

ANTENNADIFFSIDEAREARATIO $\{value \mid PWL ((d1 r1)(d2 r2)...)\}$

Specifies the antenna ratio, using the side wall area of the metal wire that is connected to the diffusion diode. You can supply and explicit ratio value or specify piece-wise linear format (PWL), in which case the ratio value is calculated using linear interpolation of the diffusion area and ratio input values. The diffusion input values must be specified in ascending order.

Type: Integer

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations."

ANTENNAMODEL {OXIDE1 | OXIDE2 | OXIDE3 | OXIDE4}

Specifies the oxide model for the layer. If you specify an ANTENNAMODEL statement, that value affects all ANTENNA* statements for the layer that follow it until you specify another ANTENNAMODEL statement.

Default: OXIDE1, for a new LAYER statement

Value: OXIDE1 or OXIDE2

Note: OXIDE1 and OXIDE2 are currently supported. If you specify OXIDE3 or OXIDE4, current tools parse and ignore them.

Because LEF is sometimes used incrementally, if an ANTENNA statement occurs twice for the same oxide model, the last value specified is used. For any given ANTENNA keyword, only one value or PWL table is stored for each oxide metal on a given layer.

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LEF Syntax

Example 1-5 Antenna Model Statement

The following example describes antenna information for oxide models on layer m1.

```
LAYER m1
                                  #OXIDE1 not required, but good practice
   ANTENNAMODEL OXIDE1 ;
   ANTENNACUMAREARATIO 5000;
                                  #OXIDE1 values
   ANTENNACUMDIFFAREARATIO 8000;
                                  #OXIDE2 model starts here
   ANTENNAMODEL OXIDE2 ;
   ANTENNACUMAREARATIO 500;
                                  #OXIDE2 values
  ANTENNACUMDIFFAREARATIO 800;
   ANTENNAMODEL OXIDE3 ;
                                  #OXIDE3 model currently ignored
   ANTENNACUMAREARATIO 300;
   ANTENNACUMDIFFAREARATIO 600;
END m1
```

ANTENNASIDEAREAFACTOR value [DIFFUSEONLY]

Specifies the multiply factor for the antenna metal side wall area calculation. DIFFUSEONLY specifies that the current antenna factor should only be used when the corresponding layer is connected to the diffusion.

Default: 1.0 Type: Float

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations."

ANTENNASIDEAREARATIO value

Specifies the antenna ratio, using the side wall area of the metal wire that is not connected to the diffusion diode. For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

Type: Integer

AREA minArea

Specifies the minimum metal area required for polygons on the layer, in distance units squared. minArea is the smallest allowed area of a single shape on a layer.

Type: Float

LEF Syntax

CAPACITANCE CPERSQDIST value

Specifies the capacitance for each square unit, in picofarads per square micron. This is used to model wire-to-ground capacitance.

CAPMULTIPLIER value Specifies the multiplier for interconnect capacitance to account for increases in capacitance caused by nearby wires.

> Default: 1 *Type:* Integer

DCCURRENTDENSITY

Specifies how much DC current a wire on this layer of a given width can handle in units of milliamps per micron (mA/µm).

Note: The true meaning of current density would have units of milliamps per square micron (mA/µm²); however, the thickness of the metal layer is implicitly included, so the units in this table are milliamps per micron, where only the wire width varies.

The DCCURRENTDENSITY syntax is defined as follows:

```
AVERAGE
{ value
 WIDTH width_1 width_2 ...;
    TABLEENTRIES value_1 value_2 ...
} ;
```

Specifies the average current limit of the **AVERAGE**

layer.

Specifies the current limit for the layer, in value

mA/μm.

Specifies wire width values, in microns. WIDTH

> You can specify more than one wire width. If you specify multiple width values, the values must be specified in ascending

order.

Type: Float

LEF Syntax

TABLEENTRIES

Specifies the value of current density for each specified width, in mA/μm.

The final value for a given wire width is computed from a linear interpolation of the table values. The widths are not adjusted for any process shrinkage, so they should be correct for the "drawn width".

Type: Float

Example 1-6 DC Current Density Statements

The following examples define DC current density tables:

```
LAYER met1
...

DCCURRENTDENSITY AVERAGE #avg. DC current limit for met1
50.0; #mA/\mum for any width

(or)

DCCURRENTDENSITY AVERAGE #avg. DC current limit for met1
WIDTH
0.4 0.8 1.6 5.0 20.0 #5 width values in microns
TABLEENTRIES
7.5 6.8 6.0 4.8 4.0; #mA/\mum for 5 widths
...
END met1;
```

The AVERAGE current density at 0.4 μm is 7.5 mA/ μm . Therefore, a 0.4 μm wide wire can carry 7.5 x .4 = 3.0 mA of AVERAGE DC current.

```
LAYER cut12
...

DCCURRENTDENSITY AVERAGE #avg. DC current limit for via cut12 10.0; #mA/\mu^2 for any cut area

(or)

DCCURRENTDENSITY AVERAGE #avg. DC current limit for via cut12 CUTAREA 0.16 0.32 #2 cut areas in \mu^2

TABLEENTRIES
10.0 9.0; #mA/\mu^2 for 2 cut areas
...

END cut12;
```

LEF Syntax

DENSITYCHECKSTEP stepValue

Specifies the stepping distance for metal density checks, in distance units.

Type: Float

DENSITYCHECKWINDOW windowLength windowWidth

Specifies the dimensions of the check window, in distance units. *Type:* Float

DIRECTION {HORIZONTAL | VERTICAL}

Specifies the preferred routing direction. The automatic routing tools attempt to route in the preferred direction on a layer. A typical case is to route horizontally on layers 1 and 3, and vertically on layer 2.

EDGECAPACITANCE value

Specifies a floating-point value of peripheral capacitance, in picofarads per micron. The place-and-route tool uses this value in two situations:

- Estimating capacitance before routing
- Calculating segment capacitance after routing

For the second calculation, the tool uses value only if you set layer thickness, or layer height, to 0. In this situation, the peripheral capacitance is used in the following formula: segment capacitance = (layer capacitance per square x segment width x segment length) + (peripheral capacitance x 2 (segment width + segment length)).

For Silicon Ensemble, if you do not specify a value for EDGECAPACITANCE, the values of the Timing.Fringcap.layernum environmental variables are used instead.

FILLACTIVESPACING spacing

Specifies the spacing between metal fills and active geometries.

Type: Float

HEIGHT distance

Specifies the distance from the top of the ground plane to the bottom of the interconnect.

Type: Float

LEF Syntax

LAYER layerName

Specifies the name for the layer. This name is used in later references to the layer.

MAXADJACENTSLOTSPACING spacing

Specifies the maximum spacing, in distance units, allowed between two adjacent slot sections.

Type: Float

MAXCOAXIALSLOTSPACING spacing

Specifies the maximum spacing, in distance units, allowed between two slots in the same slot section.

Type: Float

MAXEDGESLOTSPACING spacing

Specifies the maximum spacing, in distance units, allowed between slot edges.

Type: Float

MAXIMUMDENSITY maxDensity

Specifies the maximum metal density allowed for the layer, as a percentage. The *minDensity* and *maxDensity* values represent the metal density range within which all areas of the design must fall. The metal density must be greater than or equal to *minDensity* and less than or equal to *maxDensity*.

Type: Float

Example 1-7 Minimum and Maximum Density Statements

The following example specifies a metal density range in which the minimum metal density must be greater than or equal to 20 percent and the maximum metal density must be less than or equal to 70 percent.

MINIMUMDENSITY 20.0; MAXIMUMDENSITY 70.0;

MAXWIDTH width

Specifies the maximum wire width, in microns, allowed on the layer. For example, MAXWIDTH 10.0 specifies that the width of every wire on the layer must be less than or equal to 10.0 μ m.

Type: Float

LEF Syntax

MINENCLOSEDAREA area [WIDTH width]

Specifies the minimum area size limit for an empty area that is enclosed by metal (that is, a donut hole formed by the metal).

area Specifies the minimum area size of the

hole, in microns squared.

Type: Float

width Applies the minimum area size limit only

when a hole is created from a wire that has a width that is greater than width, in microns. If any of the wires that

surround the donut hole are larger than

this value, the rule applies.

Type: Float

Example 1-8 Min Enclosed Area Statement

The following MINENCLOSEDAREA example specifies that a hole area must be greater than or equal to $0.40 \ \mu m^2$.

```
LAYER m1
...
MINENCLOSEDAREA 0.40;
```

The following MINENCLOSEDAREA example specifies that a hole area must be greater than or equal to $0.30~\mu m^2$. However, if any of the wires enclosing the hole have a width that is greater than $0.15~\mu m$, then the hole area must be greater than or equal to $0.40~\mu m^2$. If any of the wires enclosing the hole are larger than $0.50~\mu m$, then the hole area must be greater than or equal to $0.80~\mu m^2$.

```
LAYER m1
...
MINENCLOSEDAREA 0.30;
MINENCLOSEDAREA 0.40 WIDTH 0.15;
MINENCLOSEDAREA 0.80 WIDTH 0.50;
```

MINIMUMCUT

Specifies the number of cuts a via must have when it is on a wide wire or pin whose width is greater than width. The MINIMUMCUT rule applies to all vias touching this particular metal layer. You can specify more than one MINIMUMCUT rule per layer.

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LEF Syntax

For an example using the MINMUMCUT syntax, see Example 1-9 on page 43.

The MINIMUMCUT syntax is defined as follows:

[MINIMUMCUT numCuts WIDTH width

[FROMABOVE | FROMBELOW]

[LENGTH length WITHIN distance]] ...

numCuts Specifies the number of cuts a via must

have when it is on a wire or pin whose

width is greater than width.

Type: Integer

WIDTH width Specifies the width of the wire or pin, in

microns. *Type:* Float

FROMABOVE | FROMBELOW

Indicates whether the rule applies only to connections from above this layer or from

below.

Default: The rule applies to connections

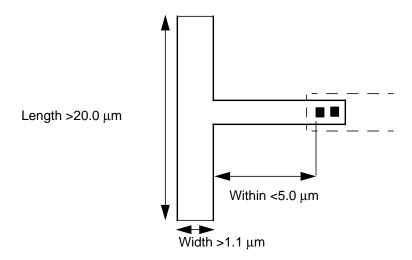
from above and below.

LENGTH length WITHIN distance

Indicates that the rule applies for thin wires directly connected to wide wires, if the wide wire has a width that is greater than width and a length that is greater than length, and the vias on the thin wire are less than distance from the wide wire (see Figure 1-3 on page 43).

Type: Floats, specified in microns

Figure 1-3



Example 1-9 Minimum Cut Statement

The following MINIMUMCUT example shows different ways to specify the MINIMUMCUT rule.

The following syntax specifies that two via cuts are required for m4 wires that are greater than 0.5 μ m when connecting from m3 or m5.

```
LAYER m4
MINIMUMCUT 2 WIDTH 0.5;
```

The following syntax specifies that four via cuts are required for m4 wires that are greater than 0.7 μ m, when connecting from m3.

```
LAYER m4
MINIMUMCUT 4 WIDTH 0.7 FROMBELOW;
```

The following syntax specifies that four via cuts are required for m4 wires that are greater than 1.0 μ m, when connecting from m5.

```
LAYER m4
MINIMUMCUT 4 WIDTH 1.0 FROMABOVE ;
```

The following syntax specifies that two via cuts are required for m4 wires that are greater than 1.1 μ m wide and greater than 20.0 μ m long, and the via cut is less than 5.0 μ m from the wide wire. Figure 1-3 on page 43 illustrates this example.

```
MINIMUMCUT 2 WIDTH 1.1 LENGTH 20.0 WITHIN 5.0;
```

LEF Syntax

MINIMUMDENSITY minDensity

Specifies the minimum metal density allowed for the layer, as a percentage. The minDensity and maxDensity values represent the metal density range within which all areas of the design must fall. The metal density must be greater than or equal to minDensity and less than or equal to maxDensity. For an example of this statement, see Example 1-7 on page 40.

Type: Float

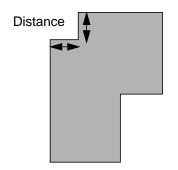
MINSTEP distance

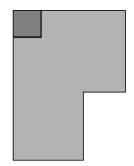
Specifies the minimum "inside" step size, or shortest edge length, for a shape, in microns. Step size is required if you want to use Optical Pattern Correction on a shape. If both edges of an inside step are less than <code>distance</code>, the step should be filled in. See Figure 1-4 on page 44 for an illustration of this rule.

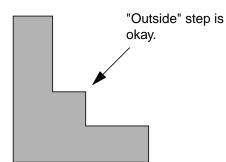
Type: Float

Figure 1-4

If both "inside" edges are less than specified distance, fill it in.







MINWIDTH width

Specifies the minimum legal object width on the routing layer, in microns. For example, MINWIDTH 0.15 specifies that the width of every object must be greater than or equal to 0.15 μm . This value is used for verification purposes, and does not affect the routing width. The WIDTH statement defines the default routing width on the layer.

Default: The value of the WIDTH statement

Type: Float

OFFSET distance

Specifies the offset, in distance units, from the placement grid to the routing grid for the layer.

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LEF Syntax

Default: Half the routing pitch for the layer

Type: Float

PITCH distance

Specifies the routing pitch for the layer. Pitch is used to generate the routing grid. For more information, see <u>"Routing Pitch"</u> on page 51.

Type: Float

PROPERTY propName propVal

Specifies a numerical or string value for a layer property defined in the PROPERTYDEFINITIONS statement. The *propName* you specify must match the *propName* listed in the

PROPERTYDEFINITIONS statement.

PROTRUSIONWIDTH width1 LENGTH length WIDTH width2

Specifies that the width of a protrusion must be greater than or equal to width1 if it is shorter than length, and it connects to a wire that has a width greater than or equal to width2 (see Figure 1-5 on page 45).

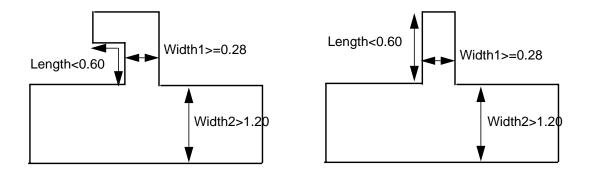
Type: Floats, specified in microns

Example 1-10 Protrusion Statement

The following example specifies that a protrusion must have a width that is greater than or equal to 0.28 μ m, if the length of the protrusion is less than 0.60 μ m and the wire it connects to has a width that is greater than 1.20 μ m.

```
LAYER m1
...
PROTRUSIONWIDTH 0.28 LENGTH 0.60 WIDTH 1.20;
```

Figure 1-5



LEF Syntax

RESISTANCE RPERSO value

Specifies the resistance for a square of wire, in ohms per square.

The resistance of a wire can be defined as

RPERSQU x wire length/wire width

SHRINKAGE distance

Specifies the value to account for shrinkage of interconnect wiring due to the etching process. Actual wire widths are determined by subtracting this constant value.

Type: Float

SLOTLENGTH minLength

Specifies the minimum slot length, in distance units, allowed in

the design.

Default: The minimum spacing for the layer

Type: Float

SLOTWIDTH minWidth

Specifies the minimum slot width, in distance units, allowed in

the design.

Default: The minimum spacing for the layer

Type: Float

SLOTWIRELENGTH minLength

Specifies the minimum wire length, in distance units, allowed for

wires that need to be slotted.

Type: Float

SLOTWIREWIDTH minWidth

Specifies the minimum wire width, in distance units, allowed for

wires that need to be slotted.

Type: Float

SPACING Specifies the spacing rules or spacing tables to use for wiring on

the layer.

Note: You cannot mix SPACING rules and SPACINGTABLE rules

in a LAYER statement. You must specify either SPACING

statements for all routing layers or SPACINGTABLE statements

for all routing layers.

LEF Syntax

You can specify more than one spacing rule for a layer. For information on and examples of using spacing rules, see <u>"Using Spacing Rules"</u> on page 51.

The syntax for describing spacing rules is defined as follows:

Specifies the default minimum spacing, in microns, allowed between two geometries on different nets.

Type: Float

The minimum spacing rule applies to objects on the layer with widths in the indicated RANGE (that is, widths that are greater than or equal to minWidth and less than or equal to maxWidth). If you do not specify a range, the rule applies to all objects.

Type: Float

USELENGTHTHRESHOLD

Specifies that the threshold spacing rule should be used if the other object meets the previous LENGTHTHRESHOLD value.

```
INFLUENCE value
  [RANGE stubMinWidth stubMaxWidth]
```

LEF Syntax

Specifies the area of the stub wire that inherits the spacing from a wider wire. *Type:* Float

The influence rule applies to stub wires on the layer with widths in the indicated RANGE (that is, widths that are greater than or equal to stubMinWidth and less than or equal to stubMaxWidth). If you do not specify a range, the rule applies to all stub wires. Type: Float

RANGE minWidth maxWidth

Specifies an optional second width range. The spacing rule applies if the widths of both objects fall in the ranges defined (each object in a different range). For an object's width to fall in a range, it must be greater than or equal to minWidth and less than or equal to maxWidth.

Type: Float

LENGTHTHRESHOLD maxLength [RANGE minWidth maxWidth]

Specifies the maximum parallel run length or projected length with an adjacent metal object.

The threshold spacing rule applies to objects with widths in the indicated RANGE (that is, widths that are greater than or equal to minWidth and less than or equal to maxWidth). If you do not specify a range, the rule applies to all objects.

Type: Float

You can specify only one parallel run length and one influence spacing table for a layer. For information on and examples of using spacing tables, see "Using Spacing Tables" on page 53.

The syntax for describing spacing tables is defined as follows:

```
[ SPACINGTABLE PARALLELRUNLENGTH {length} ...
```

LEF Syntax

```
{WIDTH width {spacing} ...} ...;
     [ SPACINGTABLE
        INFLUENCE {WIDTH width WITHIN distance
            SPACING spacing \ ... ; ]
PARALLELRUNLENGTH {length} ...
                 Specifies the maximum parallel run length
                 between two objects, in microns. You must
                 specify length values in increasing order.
                 Type: Float
WIDTH width {spacing} ...
                 width specifies the maximum width of the
                 two objects, in microns.
                 Type: Float
                 spacing specifies the spacing between the
                 two wires, in microns.
                 Type: Float
                 You must specify width and spacing
                 values in increasing order.
                 If the maximum width of the two objects is
                 greater than width, and the parrallel run
                 length is greater than length, then the
                 spacing between the objects must be greater
                 than or equal to spacing.
                 Creates a table that enforces wide wire
INFLUENCE
                 spacing rules between nearby perpendicular
                 wires. You can only specify an INFLUENCE
                 table if you specify a PARALLELRUNLENGTH
                 table first.
WIDTH width WITHIN distance SPACING spacing ...
```

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LEF Syntax

width specifies the width of the object, in

microns. *Type:* Float

distance specifies the distance between the object and two perpendicular wires, in microns.

Type: Float

spacing specifies the spacing between the two perpendicular wires, in microns.

Type: Float

You must specify width values in

increasing order.

If an object has a width that is greater than width, and is located less than distance from two perpendicular wires, then the perpendicular wires must be separated by spacing that is greater than or equal to spacing.

SPLITWIREWIDTH minWidth

Specifies the minimum wire width, in distance units, allowed for

wires that need to be split.

Type: Float

THICKNESS distance Specifies the thickness of the interconnect.

Type: Float

TYPE ROUTING Identifies the layer as a routable layer.

WIDTH defWidth Specifies the default routing width to use for all regular wiring on

the layer. *Type:* Float

WIREEXTENSION value Specifies the distance by which wires are extended at vias. You

must specify a value that is more than half of the routing width.

Default: Wires are extended half of the routing width

Type: Float

LEF Syntax

Routing Pitch

The PITCH statements define the detail routing grid generated when you initialize a floorplan. The pitch for a given routing layer defines the distance between routing tracks in the preferred direction for that layer. The complete routing grid is the union of the tracks generated for each routing layer.

The spacing of the grid should be no less than line-to-via spacing in both the horizontal and vertical directions. Grid spacing less than line-to-via spacing can result in routing problems and in a decrease in the utilization results.

The grid should normally allow for diagonal vias. Via spacing on all layers included in the via definition in LEF determines whether or not diagonal vias can be used. The router is capable of avoiding violations between diagonal vias. If you allow diagonal vias, less time is needed for routing and the layout creates a smaller design.

Using Spacing Rules

Spacing rules apply to pin-to-wire, obstruction-to-wire, via-to-wire, and wire-to-wire spacing. These requirements specify the default minimum spacing allowed between two geometries on different nets.

When defined with a RANGE argument, a spacing value applies to all objects with widths within a specified range. That is, the rule applies to objects whose widths are greater than or equal to the specified minimum width and less than or equal to the specified maximum width.

In the following example, the default minimum allowed spacing between two adjacent objects is 0.3 μ m. However, for objects between 1.01 and 2.0 μ m in width, the spacing is 0.5 μ m.

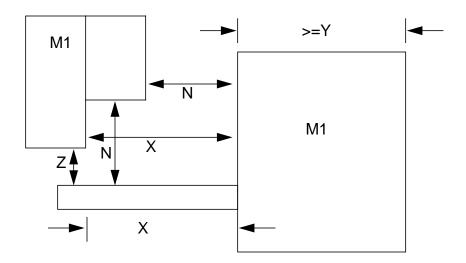
```
SPACING 0.3 ;
SPACING 0.5 RANGE 1.01 2.0 ;
```

Influence spacing rules are used to support the inheritance of wide wire spacing by nets connected to the wide wires. For example, a larger spacing is needed for stub wires attached to large objects like pre-routed power wires. A piece of metal connecting to a wider wire will inherit spacing rules for a user-defined distance from the wider wire.

In <u>Figure 1-6</u> on page 52, a minimum space of N is required between two metal lines when at least one metal line has a width that is >= Y. This spacing must be maintained for any small piece of metal (<Y) that is connected to the wide metal within X range of the wide metal. Outside of this range, normal spacing rules (Z) apply.

LEF Syntax

Figure 1-6



In the following example, the $0.5~\mu m$ spacing applies for the first $2.0~\mu m$ of the stub sticking out from the large object. This rule only applies to the stub wire; the previous rule must be included for the wide wire spacing.

```
SPACING 0.28;
SPACING 0.20 LENGTHTHRESHOLD 1.5;
SPACING 0.5
RANGE 2.01 2000.0
INFLUENCE 2.000;
```

Some processes only need the <code>INFLUENCE</code> rule for certain widths of the stub wire. In the following example, the 0.5 μ m spacing is required only for stub wires between 0.5 and 1.0 μ m in width.

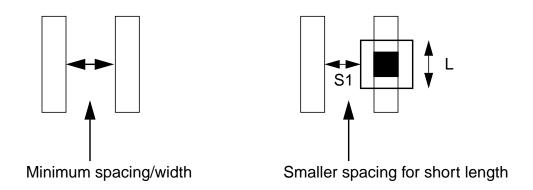
```
SPACING 0.5

RANGE 2.01 2000.0

INFLUENCE 2.00 RANGE 0.5 1.0 ;
```

LEF Syntax

Threshold spacing is a function of both the wire width and the length of the neighboring object. It is typically used when vias are wider than the wire to allow tighter wire-to-wire spacing, even when the vias are present.



In the following example, a slightly tighter spacing of .24 μm is needed if the other object is less than or equal to 1.0 μm in length.

```
SPACING 0.28 ;
SPACING 0.24 LENGTHTHRESHOLD 1.0 ;
```

The USELENGTHTHRESHOLD argument specifies that the threshold spacing rule should be applied if the other object meets the previous LENGTHTHRESHOLD value.

In the following example, a larger spacing of 0.32 μ m is needed for wire widths between 1.01 and 9.99 μ m. However, if the other object is less than or equal to 1.0 μ m in length, the smaller .0.24 μ m spacing is applied.

```
SPACING 0.28;

SPACING 0.24 LENGTHTHRESHOLD 1.0;

SPACING 0.32

RANGE 1.01 9.99 USELENGTHTHRESHOLD;
```

Using Spacing Tables

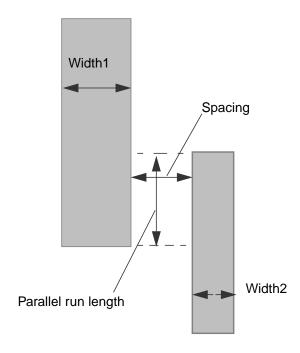
Some processes have complex width and length threshold rules. Instead of creating multiple SPACING rules with different LENGTHTHRESHOLD and RANGE statements, you can define the information in a spacing table.

LEF Syntax

For example, for <u>Figure 1-7</u> on page 54, a typical 90 nanometer DRC manual might have the following rules described:

Minimum spacing	0.15 μm spacing
Either width>0.25 μm and parallel length>0.50 μm	0.20 μm spacing
Either width>1.50 μm and parallel length>0.50 μm	0.50 μm spacing
Either width>3.00 μm and parallel length>3.00 μm	1.00 μm spacing
Either width>5.00 μm and parallel length>5.00 μm	2.00 μm spacing

Figure 1-7



These rules translate into the following SPACINGTABLE PARALLELRUNLENGTH statement:

```
LAYER m1
  SPACINGTABLE
    PARALLELRUNLENGTH 0.00 0.50 3.00 5.00
                                                 #lengths must be increasing
      WIDTH 0.00 0.15 0.15 0.15 0.15
                                                 #max width>0.00
      WIDTH 0.25
                      0.15 0.20 0.20 0.20
                                                #max width>0.25
      WIDTH 1.50
                     0.15 0.50 0.50 0.50
                                                 #max width>1.50
      WIDTH 3.00
                      0.15 0.50 1.00 1.00
                                                 #max width>3.00
      WIDTH 5.00
                      0.15 0.50 1.00 2.00 ;
                                                 #max width>5.00
END m1
```

Using the SPACINGTABLE PARALLELRUNLENGTH statement, the rules can be described in the following way:

LEF Syntax

- **1.** Find the maximum width of the two objects.
- **2.** Find the table row that matches the maximum width.
- **3.** Find the table column that matches the parallel run length. The value listed where the row and column intersect is the required spacing for that maximum width and parallel run length.

By definition, the width is the smaller dimension of the object (that is, the width of each object must be less than or equal to its length).

Processes often require a second spacing table to enforce the wide wire spacing rules between nearby perpendicular wires, even if the wires are narrow. Figure 1-8 on page 56 illustrates this situation. Use the following SPACINGTABLE INFLUENCE syntax.to describe this table:

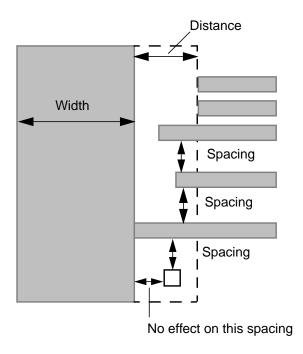
```
SPACINGTABLE INFLUENCE {WIDTH width WITHIN distance SPACING spacing} ...;
```

If a wire has a width that is greater than width, and the distance between it and two other wires is less than distance, the other wires must be separated by spacing that is greater than or equal to spacing. Typically, the distance and spacing values are the same. Note that the distance halo extends horizontally, but not into the corners.

By definition, the width is the smaller dimension of the object (that is, the width is less than or equal to the length of the large wire).

LEF Syntax

Figure 1-8



The wide wire rules often match the larger width and spacing values in the SPACINGTABLE PARALLELRUNLENGTH values. The previously described rules translate into the following SPACINGTABLE INFLUENCE statement:

```
LAYER m1
...
SPACINGTABLE INFLUENCE
WIDTH 1.50 WITHIN 0.50 SPACING 0.50 #w>1.50, dist<0.50, needs sp>=0.50
WIDTH 3.00 WITHIN 1.00 SPACING 1.00 #widths must be increasing
WIDTH 5.00 WITHIN 2.00 SPACING 2.00;
...
END m1
```

Macro

LEF Syntax

```
[ORIGIN pt ;]
[EEQ macroName ;]
[LEQ macroName ;]
[SIZE width BY height ;]
[SYMMETRY {X | Y | R90} ... ;]
[SITE siteName ;]
[PIN statement] ...
[OBS statement] ...
[PROPERTY propName propVal ;] ...
```

END macroName

Defines macros in the design.

CLASS

Specifies the macro type. If you do not specify CLASS, the macro is considered a CORE macro, and a warning prints when the LEF file is read in. You can specify macros of the following types:

COVER

Macro with data that is fixed to the floorplan and cannot change, such as power routing (ring pins) around the core. The placers understand that CLASS COVER cells have no active devices (such as diffusion or polysilicon), so the MACRO SIZE statement does not affect the placers, and you do not need an artificial OVERLAP layer. However, any pin or obstruction geometry in the COVER cells can affect the pin access checks done by the placers.

A cover macro can be of the following sub-class:

BUMP—A physical-only cell that has bump geometries and pins. Typically a bump cell has geometries only on the top-most "bump" metal layer, although it might contain a via and pin to the metal layer below. Bump cells cannot be moved; however, you can change the assignment of a bump cell pin to a driver cell.

RING

Large macro that can cut prerouted special nets and connect to these nets with ring pins.

LEF Syntax

BLOCK Predefined macro used in hierarchical design.

A block macro can have the following sub-class:

BLACKBOX—A block that sometimes only contains a SIZE statement that estimates its total area. A blackbox can optionally contain pins, but in many cases, the pin names are taken from a Verilog description and do not need to match the LEF MACRO pin names.

PAD I/O pad. A pad can be one of the following types:

INPUT, OUTPUT, INOUT, POWER, or SPACER, for I/O rows; INPUT, OUTPUT, INOUT, or POWER, for I/O corner pads; AREAIO for area I/O driver cells that are placed inside the core of the chip.

For an example of a macro pad cell, see Example 1-11 on page 59.

Example 1-11 on page 59

CORE Macro used in the core area. A core macro can

be one of the following types:

FEEDTHRU—Used for connecting to another cell.

TIEHIGH, TIELOW—Used for connecting unused I/O terminals to the power or ground bus.

SPACER—Sometimes called a filler cell, this cell is used to fill in space between regular core cells.

ANTENNACELL—Used for solving process antenna violations. This cell has a single input to a diode to bleed off charge that builds up during manufacturing.

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LEF Syntax

ENDCAP

A macro placed at the ends of core rows (to connect with power wiring).

If the library includes only one corner I/O macro, then appropriate SYMMETRY must be included in its macro description. An ENDCAP macro can be one of the following types:

PRE—A left-end macro

POST—A right-end macro

TOPLEFT—A top left I/O corner cell

TOPRIGHT—A top right I/O corner cell

BOTTOMLEFT—A bottome left I/O corner cell

BOTTOMRIGHT—A bottom right I/O corner cell

Example 1-11 Macro Pad Cell

The following example defines a power pad cell that illustrates when to use the CLASS CORE keywords on power ports. For the VDD pin, there are two ports: one to connect to the interior core power ring, and one to complete the I/O power ring. Figure 1-1 on page 6 illustrates this pad cell.

```
MACRO PAD 0
   CLASS PAD ;
   FOREIGN PAD 0 0.000 0.000;
   ORIGIN 0.000 0.000;
   SIZE 100.000 BY 300.000 ;
   SYMMETRY X Y R90 ;
   SITE PAD SITE ;
# Define pin VDD with SHAPE ABUTMENT because there are no obstructions
# to block a straight connection to the pad rings. The port without
# CLASS CORE is used for completing the I/O power ring.
   PIN VDD
     DIRECTION INOUT ;
     USE POWER ;
     SHAPE ABUTMENT ;
     PORT
       LAYER metal2 ;
         RECT 0.000 250.000 100.000 260.000 ;
       LAYER metal3 ;
         RECT 0.000 250.000 100.000 260.000;
     END
```

LEF Syntax

```
# Define VDD port with PORT CLASS CORE to indicate that the port connects
# to the core area instead of to the pad ring.
     PORT
       CLASS CORE ;
       LAYER metal2 ;
         RECT 0.000 290.000 100.000 300.000 ;
       LAYER metal3 ;
         RECT 0.000 290.000 100.000 300.000 ;
     END
   END VDD
# Define pins VCC and GND with SHAPE FEEDTHRU because these pins
# cannot make a straight connection to the pad rings due to obstructions.
   PIN VCC
     DIRECTION INOUT ;
     USE POWER ;
     SHAPE FEEDTHRU;
     PORT
       LAYER metal2 ;
         RECT 0.000 150.000 20.000 160.000 ;
         RECT 20.000 145.000 80.000 155.000 ;
         RECT 80.000 150.000 100.000 160.000 ;
       LAYER metal3 ;
         RECT 0.000 150.000 20.000 160.000 ;
         RECT 20.000 145.000 80.000 155.000 ;
         RECT 80.000 150.000 100.000 160.000 ;
     END
   END VCC
   PIN GND
     DIRECTION INOUT ;
     USE GROUND ;
     SHAPE FEEDTHRU ;
     PORT
       LAYER metal2 ;
         RECT 0.000 50.000 20.000 60.000 ;
         RECT 80.000 50.000 100.000 60.000 ;
     END
   END GND
   OBS
```

LEF Syntax

```
LAYER metal1 ;

RECT 0.000 0.000 100.000 300.000 ;

LAYER metal2 ;

RECT 25.000 50.000 75.000 60.000 ;

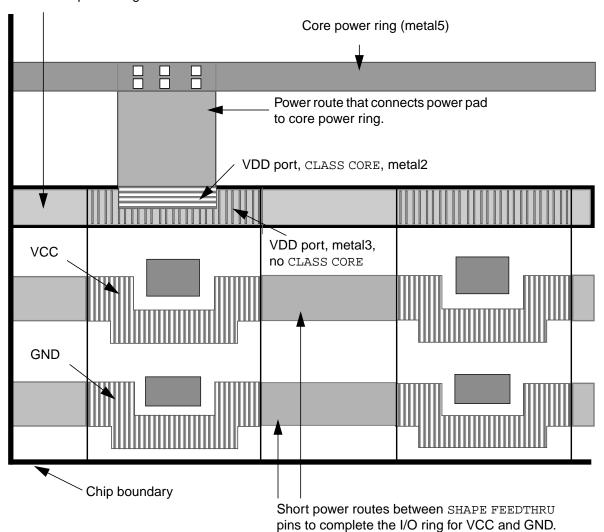
RECT 30.500 157.000 70.500167.000 ;

END

END PAD_0
```

Figure 1-9 Power Pad Cell

One long power route that completes the I/O power ring for VDD.



LEF Syntax

EEQ macroName

Specifies that the macro being defined should be electrically equivalent to the previously defined <code>macroName</code>. For Silicon Ensemble, <code>PLACE</code> automatically selects among EEQ macros to obtain the best placement. EEQ macros include devices such as OR-gates or inverters that have several implementations with different shapes, geometries, and orientations.

Electrically equivalent macros have the following requirements:

- Corresponding pins must have corresponding functionality.
- Pins must be defined in the same order.
- For each group of corresponding pins (one from each macro), pin function and electrical characteristics must be the same.
- The EEQ macroName specified must refer to a previously defined macro. If the EEQ macroName referenced is already electrically equivalent to other model macros, all referenced macros are considered electrically equivalent.

FOREIGN foreignCellName [pt [orient]]

Specifies the foreign (GDSII) structure name to use when placing an instance of the macro. The optional pt coordinate specifies the macro origin (lower left corner when the macro is in north orientation) offset from the foreign origin. The FOREIGN statement has a default offset value of 0 0, if pt is not specified.

The optional orient value specifies the orientation of the foreign cell when the macro is in north orientation. The default orient value is north.

For Silicon Ensemble, the calculation of absolute location for the foreign reference in OUTPUT GDSII is affected by component placement location and component orientation, as well as by the macro foreign coordinate offset, but not by the macro foreign orientation.

Example 1-12 Foreign Statements

The following examples show two variations of the FOREIGN statement. The negative offset specifies that the GDSII structure should be above and to the right of the macro lower left corner.

LEF Syntax

```
MACRO ABC ...
FOREIGN ABC -2 -3;
```

The positive offset specifies that the GDSII structure should be below and to the left of the macro lower left corner.

```
MACRO EFG ...
FOREIGN EFG 2 3 ;
```

LEQ macroName

Specifies that the macro being defined should be logically equivalent to the previously defined <code>macroName</code>. Unlike EEQ macros, LEQ macros can have pins in which the corresponding electrical characteristics, such as timing, resistance, and capacitance, are different.

LEQ macros can be replaced by one another without effecting an Engineering Change. Automatic layout commands do not replace a macro in the netlist with an LEQ macro.

An example of an LEQ macro is a distribution cell that has several implementations with different electrical characteristics, such as drive strengths, intrinsic delays, and so on.

The following are requirements of LEQ macros:

- As with EEQ macros, the number, specified order, and corresponding functions of the pins on LEQ macros must be the same.
- Internal nonschematic mustjoin and power pins can be different.
- Pin geometries, obstructions, size, foreign references, orientation, power/grid connections, and site requirements can be different.
- The LEQ macroName must have been previously defined. If the LEQ macroName referenced is already logically equivalent to other macros, all referenced macros are considered logically equivalent.

MACRO macroName

Specifies the name of the library macro.

LEF Syntax

OBS statement

Defines obstructions on the macro. Obstruction geometries are specified using layer geometries syntax. See <u>"Macro Obstruction Statement"</u> on page 72 for syntax information.

ORIGIN pt

Specifies how to find the origin of the macro to align with a DEF COMPONENT placement point. If there is no ORIGIN statement, the DEF placement point for a North-oriented macro is aligned with 0, 0 in the macro. If ORIGIN is given in the macro, the macro is shifted by the ORIGIN x, y values first, before aligning with the DEF placement point. For example, if the ORIGIN is 0, -1, then macro geometry at 0, 1 are shifted to 0, 0, and then aligned to the DEF placement point.

PIN statement

Defines pins for the macro. See <u>"Macro Pin Statement"</u> on page 74 for syntax information.

PROPERTY propName propVal

Specifies a numerical or string value for a macro property defined in the PROPERTYDEFINITIONS statement. The *propName* you specify must match the *propName* listed in the PROPERTYDEFINITIONS statement.

SITE siteName

Specifies the site associated with the macro. You can specify only one site. For Silicon Ensemble, this is the same as the row type specified in the ADD ROW command when floorplanning the design. The legal location checking for placement consists of mapping the macro site to the row sites to see if the name is the same and the orientations match.

SIZE width BY height

Specifies a placement bounding rectangle, in microns, for the macro. The bounding rectangle always stretches from (0, 0) to the point defined by SIZE. For example, given SIZE 10 BY 40, the bounding rectangle reaches from (0, 0) after adjustment due to the ORIGIN statement, to (100, 400).

Placers assume the placement bounding rectangle cannot overlap placement bounding rectangles of other macros, unless OBS OVERLAP shapes are used to create a non-rectangular area.

After placement, a DEF COMPONENTS placement pt indicates where the lower-left corner of the placement bounding rectangle is placed after any possible rotations or flips. The bounding

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LEF Syntax

rectangle width and height should be a multiple of the placement grid to allow for abutting cells.

For blocks, the placement bounding rectangle typically contains all pin and blockage geometries, but this is not required. For example, typical standard cells have pins that lie outside the bounding rectangle, such as power pins that are shared with cells in the next row above them.

SOURCE {USER | BLOCK}

Specifies the source of the macro being defined.

Value: Specify one of the following:

USER Macro is user-defined.

BLOCK Block macro is created when the LEF file is

written out.

SYMMETRY {X | Y | R90}

Specifies which macro orientations should be attempted by the placer before matching to the site of the underlying rows. In general, most standard cell macros should have symmetry X Y. N is always a legal candidate. For each type of symmetry defined, additional orientations become legal candidates. For more information on defining symmetry, see "Defining Symmetry" on page 66.

Possible orientations include:

X N and FS orientations should be tried.

Y N and FN orientations should be tried.

X Y N, FN, FS, and S orientations should all be tried.

R90 Specify this value only for pad cells. Do not specify

this value for standard cells.

Note: If you do not specify a SYMMETRY statement, only N orientation is tried.

For corner I/O pads, if the library includes BOTTOMLEFT, BOTTOMRIGHT, TOPLEFT, and TOPRIGHT I/O corner cells, then they are placed in north orientation (no flipping). However, if the library includes only one type of corner I/O, then SYMMETRY in x and y are required to create the rows for all four of them.

LEF Syntax

Defining Cover Macros

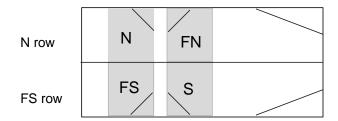
If you define a cover macro with its actual size, some place-and-route tools cannot place the rest of the cells in your design because it uses the cell boundary to check for overlaps. You can resolve this in two ways:

- The easiest way to support a cover macro is to define the cover macro with a small size, for example, 1 by 1. Silicon Ensemble does not require port figures to be within the cell boundary.
- If you want to define the cover macro with its actual size, create an overlap layer with the LAYER (nonrouting) TYPE OVERLAP statement. You define this overlap layer (cover macro) with the macro obstruction (OBS) statement. This method slows down the PLACE command slightly.

Defining Symmetry

Symmetry statements specify legal orientations for sites and macros. <u>Figure 1-10</u> on page 66 illustrates the normal orientations for single-height, flipped and abutted rows with standard cells and sites.

Figure 1-10 Normal Orientations for Single-Height Rows



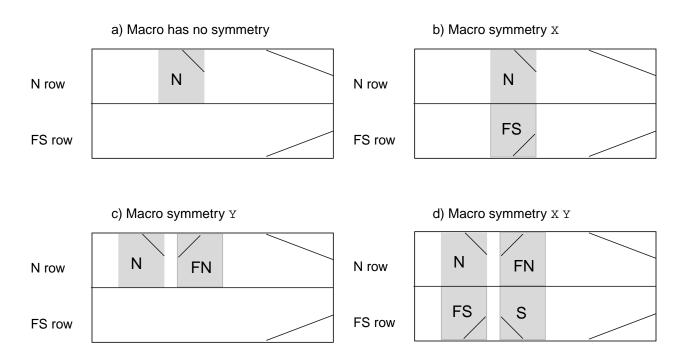
The following examples describe typical combinations of orientations for standard cells. Applications typically create only N (or FS for flipped) row orientations for horizontal standard cell rows; therefore, the examples describe these two rows.

Example 1-13 Single-Height Cells

Single-height cells for flipped and abutted rows should have SITE symmetry Y and MACRO symmetry X Y. These specifications allow N and FN macros in N rows, and FS and S macros in FS rows (see d in Figure 1-11 on page 67). These symmetries work with flipped and abutted rows, as well as rows that are not flipped and abutted. If the rows are not flipped, the cells all have N orientation. The extra MACRO symmetry of X is not required in this case, but causes no problems.

LEF Syntax

Figure 1-11 Legal Placements for Row Sites with Symmetry Y

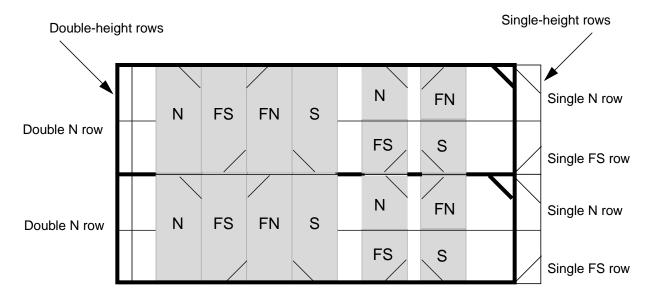


Example 1-14 Double-Height Cells

Double-height cells that are intended to align with flipped and abutted single-height rows should have SITE symmetry X Y and MACRO symmetry X Y. These symmetries allow all four cell orientations (N, FN, FS, and S) to fit inside the double-height row (see Figure 1-12 on page 68). Usually, double-height rows are just N orientation rows that are abutted and aligned with a pair of single-height flipped and abutted rows.

LEF Syntax

Figure 1-12 Legal Placements for Single-Height Row Sites with Symmetry Y and Double-Height Row Sites with Symmetry X Y



Note: The single-height rows are shifted slightly to the right of the double-height rows in the above figure for illustration purposes. In a real design, they should be aligned.

Example 1-15 Special Orientations

Some single-height cells have special orientation needs. For example, the design requires flipped and abutted rows, but only N and FS orientations are allowed because of the special layout of well taps on the right side of a group of cells that borrow from the left side of the next cell. That is, you cannot place an N and FN cell against each other in one row because only N cells are allowed in an N row. In this case, the SITE symmetry should not be defined, and the MACRO symmetry should be X. A MACRO symmetry of X Y can also be defined because the Y-flipped macros (FN and S orientations) do not match the N or FS rows. This MACRO symmetry also works if there are no flipped rows, and only N rows.

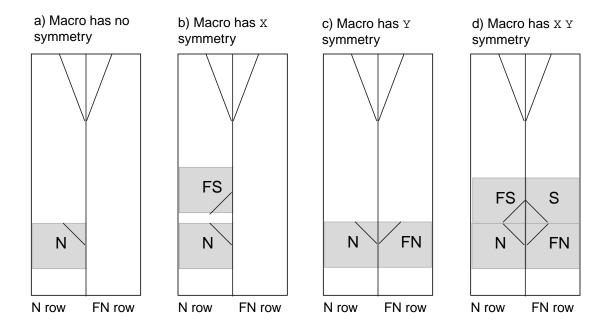
Example 1-16 Vertical Rows

Vertical rows use N or FN row and site orientations. The flipped, abutted vertical row orientation is N and FN, rather than the horizontal row orientation of N and FS. Otherwise, the meaning of the site symmetries and macro symmetries is the same as those for horizontal rows.

LEF Syntax

Single-height sites are normally given symmetry x, and single-height cells are normally given symmetry x y. Example d in <u>Figure 1-13</u> on page 69 shows the legal placement for a site with symmetry x, and the typical standard cell MACRO symmetry x y.

Figure 1-13 Legal Placements for Vertical Row Sites With Symmetry X



Layer Geometries

```
{ LAYER layerName [SPACING minSpacing | DESIGNRULEWIDTH value];
    [WIDTH width ;]
    { PATH pt ...;
    | PATH ITERATE pt ... stepPattern;
    | RECT pt pt;
    | RECT ITERATE pt pt stepPattern;
    | POLYGON pt pt pt pt ...;
    | POLYGON ITERATE pt pt pt pt ... stepPattern;
    } ...
    | VIA pt viaName;
    | VIA ITERATE pt viaName stepPattern;
} ...
```

Used in the macro obstruction (OBS) and pin port (PIN) statements to define layer geometries in the design.

DESIGNRULEWIDTH value

Specifies the effective design rule width. If specified, the

LEF Syntax

obstruction or pin is treated as a shape of this width for all spacing checks. If you specify DESIGNRULEWIDTH, you cannot specify the SPACING argument.

Type: Float

ITERATE

Creates an array of the PATH, RECT, POLYGON, or VIA geometry, as specified by the given step pattern. ITERATE specifications simplify the definitions of cover macros. The syntax for stepPattern is defined as follows:

DO numX BY numY STEP spaceX spaceY

Specifies the number of columns of numX

points.

numY Specifies the number of rows of points.

Specifies the spacing, in distance units, spaceX spaceY

between the columns and rows of points.

LAYER layerName

Specifies the layer on which to place the geometry.

Note: For macro obstructions, you can specify cut, implant, or overlap layers.

PATH pt

Creates a path between the specified points, such as pt1 pt2 pt3. The path automatically extends the length by half of the current width on both end points to form a rectangle. You can also specify a path with a single coordinate, in which case a square whose side is equal to the current width is placed with its center at pt.

POLYGON pt pt pt pt Specifies a sequence of at least four points to generate a polygon geometry. The polygon must be orthogonal (all edges parallel to the x or y axis), so each successive point must vary only one coordinate. Each POLYGON statement defines a polygon generated by connecting each successive point, and by connecting the first and last points.

RECT pt pt

Specifies a rectangle, where the two points specified are opposite corners of the rectangle. There is no functional difference between a geometry specified using PATH and a geometry specified using RECT.

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LEF Syntax

SPACING minSpacing

Specifies the minimum spacing allowed between this particular obstruction or pin and any other shape. This value overrides the normal LAYER-based spacing rules, including wide wire spacing rules. Therefore, a SPACING value of 0.1 μ m specifies that all other shapes must be spaced at least 0.1 μ m away, including large width objects that might normally require even more spacing.

If you specify SPACING, you cannot specify the DESIGNRULEWIDTH argument.

VIA pt viaName

Specifies the via to placeand the placement location.

WIDTH width

Specifies the width that the PATH statements use. If you do not specify width, the default width for that layer is used. When you specify a width, that width remains in effect until the next WIDTH or LAYER statement. When another LAYER statement is given, the WIDTH is automatically reset to the default width for that layer.

Example 1-17 Layer Geometries Statement

The following example shows how to define a set of geometries, first by using ITERATE statements, then by using individual PATH, VIA and RECT statements.

The following two sets of statements are equivalent:

```
PATH ITERATE 532.0 534 1999.2 534

DO 1 BY 2 STEP 0 1446;

VIA ITERATE 470.4 475 VIABIGPOWER12

DO 2 BY 2 STEP 1590.4 1565;

RECT ITERATE 24.1 1.5 43.5 16.5

DO 2 BY 1 STEP 20.0 0;

PATH 532.0 534 1999.2 534;

PATH 532.0 1980 1999.2 1980;

VIA 470.4 475 VIABIGPOWER12;

VIA 2060.8 475 VIABIGPOWER12;

VIA 470.4 2040 VIABIGPOWER12;

VIA 2060.8 2040 VIABIGPOWER12;

RECT 24.1 1.5 43.5 16.5;

RECT 44.1 1.5 63.5 16.5;
```

LEF Syntax

Macro Obstruction Statement

```
[OBS

{ LAYER layerName [SPACING minSpacing | DESIGNRULEWIDTH value];
        [WIDTH width ;]
        { PATH pt ...;
        | PATH ITERATE pt ... stepPattern;
        | RECT pt pt;
        | RECT iterate pt pt stepPattern;
        | POLYGON pt pt pt pt ...;
        | POLYGON ITERATE pt pt pt pt ... stepPattern;
        } ...

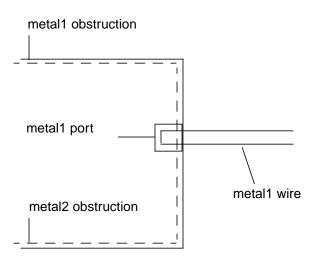
| VIA pt viaName;
        | VIA ITERATE pt viaName stepPattern;
        } ...
END]
```

Defines a set of obstructions (also called blockages) on the macro. You specify obstruction geometries using the layer geometry syntax. See <u>"Layer Geometries"</u> on page 69 for syntax information.

Normally, obstructions block routing, except for when a pin port overlaps an obstruction (a port geometry overrules an obstruction). For example, you can define a large rectangle for a metal1 obstruction and have metal1 ports in the middle of the obstruction. The port can still be accessed by a via, if the via is entirely inside the port.

In <u>Figure 1-14</u> on page 72, the router can only access the metal1 port from the right. If the metal2 obstruction did not exist, the router could connect to the port with a metal12 via, as long as the metal1 part of the via fit entirely inside the metal1 port.

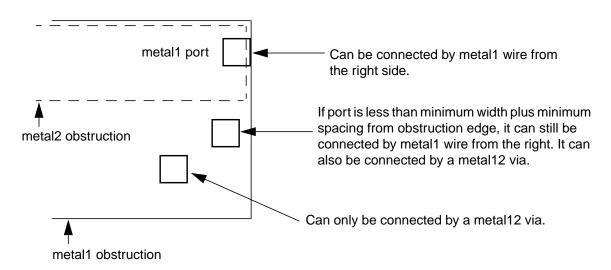
Figure 1-14



LEF Syntax

Routing can also connect to such a port on the same layer if the routing does not cross any obstruction by more than a distance of the total of minimum width plus minimum spacing before reaching the pin. This is because the port geometry is known to be "real," and any obstruction less than a distance of minimum width plus minimum spacing away from the port is not a real obstruction. If the pin is more than minimum width plus minimum spacing away from the obstruction edge, the router can only route to the pin from the layer above or below using a via (see Figure 1-15 on page 73).

Figure 1-15



If a port is on the edge of the obstruction, a wire can be routed to the port without violations. Pins that are partially covered with obstructions or in apparent violation with nearby obstructions can limit routing options. Even though the violations are not real, the router assumes they are. In these cases, extend each obstruction to cover the pin. The router then accesses the pin as described above.

Benefits of Combining Obstructions

Significant routing time can be saved if obstructions are simplified. Especially in metal1, construct obstructions so that free tracks on the layer are accessible to the router. If most of the routing resource is obstructed, simplify the obstruction modeling by combining small obstructions into a single large obstruction. For example, use the bounding box of all metal1 objects in the cell, rather than many small obstructions, as the bounding box of the obstruction.

You must be sure to model via obstructions over the rest of the cell properly. A single, large cut12 obstruction over the rest of the cell can do this in some cases, as when metal1 resource exists within the cell outside the power buses.

LEF Syntax

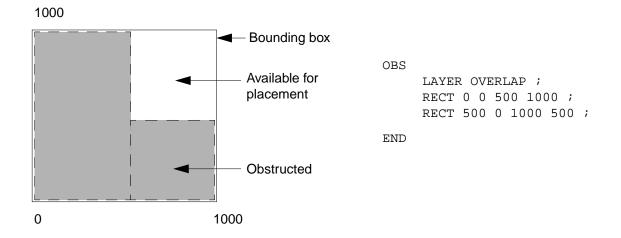
Rectilinear Blocks

Normally, footprint descriptions in LEF are rectangular. However, it is possible to describe rectilinear footprints using an overlap layer. The overlap layer is defined specifically for this purpose and does not contain any routing.

Describe a rectilinear footprint by setting the SIZE of the macro as a whole to a rectangular bounding box, then defining obstructions within the bounding box on the overlap layer. The obstructions on the overlap layer indicate areas within the bounding box which no other macro should overlap. The obstructions should completely cover the rectilinear shape of the macro, but not the portion of the bounding box that might overlap with other macros during placement.

Note: Specify the overlaps for the macro using the OBS statement. To do this, specify a layer of type OVERLAP and then give the overlap geometries, as shown in <u>Figure 1-16</u> on page 74.

Figure 1-16



Macro Pin Statement

```
[PIN pinName
    [TAPERRULE ruleName ;]
    [FOREIGN foreignPinName [STRUCTURE [pt [orient]]];]
    [LEQ pinName ;] ...
    [DIRECTION {INPUT | OUTPUT [TRISTATE] | INOUT | FEEDTHRU} ;]
    [USE { SIGNAL | ANALOG | POWER | GROUND | CLOCK } ;]
    [SHAPE {ABUTMENT | RING | FEEDTHRU} ;]
    [MUSTJOIN pinName ;]
    {PORT
        [CLASS {NONE | CORE} ;]
        {layerGeometries} ...
```

LEF Syntax

```
[PROPERTY propName propVal;]...

[ANTENNAPARTIALMETALAREA value [LAYER layerName];]...

[ANTENNAPARTIALMETALSIDEAREA value [LAYER layerName];]...

[ANTENNAPARTIALCUTAREA value [LAYER layerName];]...

[ANTENNADIFFAREA value [LAYER layerName];]...

[ANTENNAMODEL {OXIDE1 | OXIDE2 | OXIDE3 | OXIDE4};]...

[ANTENNAGATEAREA value [LAYER layerName];]...

[ANTENNAMAXAREACAR value LAYER layerName;]...

[ANTENNAMAXSIDEAREACAR value LAYER layerName;]...
```

END pinName]

Defines pins for the macro. PIN statements must be included in the LEF specification for each macro. All pins, including VDD and VSS, must be specified. The first pin listed becomes the first pin in the database. List the pins in the following order:

- Netlist pins, including inout pins, output pins, and input pins
- Power and ground pins
- Mustjoin pins

ANTENNADIFFAREA value [LAYER layerName]

Specifies the diffusion (diode) area, in micron-squared units, to which the pin is connected on a layer. If you do not specify a layer name, the value applies to all layers. For more information on process antenna calculation, see <u>Appendix D</u>, "Calculating and <u>Fixing Process Antenna Violations</u>,"

ANTENNAGATEAREA value [LAYER layerName]

Specifies the gate area, in micron-squared units, to which the pin is connected on a layer. If you do not specify a layer name, the value applies to all layers. For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations."

ANTENNAMAXAREACAR value LAYER layerName

For hierarchical process antenna effect calculation, specifies the maximum cumulative area ratio value on the specified <code>layerName</code>, using the metal area at or below the current pin layer, excluding the pin area itself. This is used to calculate the actual cumulative antenna ratio on the pin layer, or the layer above it.

LEF Syntax

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations."

ANTENNAMAXCUTCAR value LAYER layerName

For hierarchical process antenna effect calculation, specifies the maximum cumulative antenna ratio value on the specified layerName, using the cut area at or below the current pin layer, excluding the pin area itself. This is used to calculate the actual cumulative antenna ratio for the cuts above the pin layer.

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations."

ANTENNAMAXSIDEAREACAR value LAYER layerName

For hierarchical process antenna effect calculation, specifies the maximum cumulative antenna ratio value on the specified <code>layerName</code>, using the metal side wall area at or below the current pin layer, excluding the pin area itself. This is used to calculate the actual cumulative antenna ratio on the pin layer or the layer above it.

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

ANTENNAMODEL {OXIDE1 | OXIDE2 | OXIDE3 | OXIDE4}

Specifies the oxide model for the pin. If you specify an ANTENNAMODEL statement, the value affects all ANTENNAGATEAREA and ANTENNA*CAR statements for the pin that follow it until you specify another ANTENNAMODEL statement. The ANTENNAMODEL statement does not affect ANTENNAPARTIAL*AREA and ANTENNADIFFAREA statements because they refer to the total metal, cut, or diffusion area connected to the pin, and do not vary with each oxide model. Default: OXIDE1, for a new PIN statement Value: OXIDE1 or OXIDE2.

Note: OXIDE1 and OXIDE2 are currently supported. If you specify OXIDE3 or OXIDE4, current tools parse and ignore them.

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LEF Syntax

Because LEF is often used incrementally, if an ANTENNA statement occurs twice for the same oxide model, the last value specified is used.

For most standard cells, there is only one value for the ANTENNAPARTIAL*AREA and ANTENNADIFFAREA values per pin; however, for a block with six routing layers, it is possible to have six different ANTENNAPARTIAL*AREA values and six different ANTENNAPINDIFFAREA values per pin. It is also possible to have six different ANTENNAPINGATEAREA and ANTENNAPINMAX*CAR values for each oxide model on each pin.

Example 1-18 Pin Antenna Model Statement

The following example describes oxide model information for pins IN1 and IN2.

```
MACRO GATE1
 PIN IN1
   ANTENNADIFFAREA 1.0 ;
                                     #not affected by ANTENNAMODEL
   ANTENNAMODELOXIDE OXIDE1 ;
                                    #OXIDE1 not required, but is good practice
   ANTENNAGATEAREA 1.0 ;
                                     #OXIDE1 gate area
   ANTENNAMAXAREACAR 50.0 LAYER m1; #metal1 CAR value
    ANTENNAMODEL OXIDE2 ;
                                     #OXIDE2 starts here
                                     #OXIDE2 gate area
   ANTENNAGATEAREA 3.0;
 PIN IN2
    ANTENNADIFFAREA 2.0 ;
                                     #not affected by ANTENNAMODEL
    ANTENNAPARTIALMETALAREA 2.0 LAYER m1;
    #no OXIDE1 specified for this pin
   ANTENNAMODEL OXIDE2 ;
   ANTENNAGATEAREA 1.0 ;
```

ANTENNAPARTIALCUTAREA value [LAYER layerName]

Specifies the partial cut area above the current pin layer and inside the macro cell on the layer. For a hierarchical design, only the cut layer above the I/O pin layer is needed for partial antenna ratio calculation. If you do not specify a layer name, the value applies to all layers.

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

LEF Syntax

ANTENNAPARTIALMETALAREA value [LAYER layerName]

Specifies the partial metal area connected directly to the I/O pin and the inside of the macro cell on the layer. For a hierarchical design, only the same metal layer as the I/O pin, or the layer above it, is needed for partial antenna ratio calculation. If you do not specify a layer name, the value applies to all layers.

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations."

Note: Metal area is calculated by adding the pin's geometric metal area and the ANTENNAPARTIALMETALAREA value.

ANTENNAPARTIALMETALSIDEAREA value [LAYER layerName]

Specifies the partial metal side wall area connected directly to the I/O pin and the inside of the macro cell on the layer. For a hierarchical design, only the same metal layer as the I/O pin or the layer above is needed for partial antenna ratio calculation. If you do not specify a layer name, the value applies to all layers.

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

CLASS {NONE | CORE}

Specifies whether or not the port is a core port. A core port is only used on power and ground I/O pads. The core port indicates which power or ground port to connect to a core ring for the chip (inside the I/O pads).

Default: NONE

DIRECTION {INPUT | OUTPUT [TRISTATE] | INOUT | FEEDTHRU}

Specifies the pin type.

Default: INPUT

Value: Specify one of the following:

INPUT Pin that accepts signals coming into the cell.

OUTPUT Pin that drives signals out of the cell. The

[TRISTATE] optional TRISTATE argument indicates tristate

output pins for ECL designs.

INOUT Pin that can accept signals going either in or out

of the cell.

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LEF Syntax

FEEDTHRU

FOREIGN foreignPinName

Specifies which foreign system pin name within the macro GDSII structure or which GDSII structure itself to use to extract pin port geometries from, and output to, when an instance of this macro is placed and this pin is used.

layerGeometries

Defines port geometries for the pin. You specify port geometries using layer geometries syntax. See <u>"Layer Geometries"</u> on page 69 for syntax information.

LEQ pinName

Specifies that the pin being defined should be logically equivalent to the previously defined pinName. All the LEQ pins equivalent to the first pin must be defined immediately after the first pin. LEQ pins must be defined contiguously.

MUSTJOIN pinName

Specifies the name of another pin in the cell that must be connected with the pin being defined. MUSTJOIN pins provide connectivity that must be made by the router. In the LEF file, each pin referred to must be defined before the referring pin. The remaining MUSTJOIN pins in the set do not need to be defined contiguously.

Note: MUSTJOIN pin names are never written to the DEF file; they are only used by routers to add extra connection points during routing.

MUSTJOIN pins have the following restrictions:

- A MUSTJOIN pin cannot be a LEQ pin.
- A set of MUSTJOIN pins cannot have more than one schematic pin.
- Nonschematic MUSTJOIN pins must be defined after all other pins.
- LEQ macros can have a different number and order of nonschematic MUSTJOIN pins.

Schematic and nonschematic MUSTJOIN pins are handled in slightly different ways. For schematic MUSTJOIN pins, the pins are added to the pin set for the (unique) net associated with the

LEF Syntax

ring for each component instance of the macro. The net is routed in the usual manner, and routing data for the MUSTJOIN pins are included in routing data for the net.

The mustion routing is not necessarily performed before the rest of the net. Timing relations should not be given for MUSTJOIN pins, and internal mustioin routing is modeled as lumped capacitance at the schematic pin.

Nonschematic MUSTJOIN pin sets get routed in the usual manner. However, when the DEF file is outputted, routing data is reported in the NETS section of the file as follows:

MUSTJOIN compName pinName + regularWiring ;

Here, compName is the component and pinName is an arbitrary pin in the set. You can also use the preceding to input prewiring for the MUSTJOIN pin, using FIXED or COVER.

PIN pinName

Specifies the name for the library pin.

PORT

Starts a pin port statement, which defines a collection of geometries that are electrically equivalent points. A pin can have multiple ports. Routers connect to any of the member geometries of a port, without affecting the electrical performance of the circuit.

PROPERTY propName propVal

Specifies a numerical or string value for a pin property defined in the PROPERTYDEFINITIONS statement. The propName you specify must match the propName listed in the

PROPERTYDEFINITIONS statement.

SHAPE

Specifies a pin with special connection requirements because of its shape.

Value: Specify one of the following:

ABUTMENT Pin that goes straight through cells with a

regular shape and connects to pins on

adjoining cells without routing.

Pin on a large block that forms a ring around RING

> the block to allow connection to any point on the ring. Cover macro special pins also

typically have shape RING.

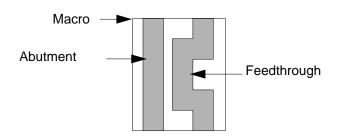
LEF Syntax

FEEDTHRU

Pin with an irregular shape with a jog or neck within the cell.

Figure 1-17 on page 81 shows an example of an abutment and a feedthrough pin.

Figure 1-17



Note: For Silicon Ensemble, when you define feedthrough and abutment pins for use with SROUTE FOLLOWPINS, you must do the following:

- Feedthrough pin widths must be the same on both edges and consistent with the routing width used with the SROUTE FOLLOWPINS command.
- Feedthrough pin centers on both edges must align for successful routing.
- Power pins in fork shapes must be represented in two ports and be defined as a feedthrough shape. In most other cases, power pin geometries do not represent more than one port.
- An abutment pin must have at least one geometric rectangle with layer and width consistent with the values specified in the SROUTE FOLLOWPINS command.

STRUCTURE [pt [orient]

Includes all or part of the pin physical data in a separate GDSII structure, rather than the macro GDSII structures. This is normally used for LEQ pins; and it allows the different physical implementations for each LEQ pin to be selectable when GDSII is output, based upon which pin is used. The pin port geometries are the union of those found in the macro GDSII structure (by pin name texting) and the geometries in the pin GDSII structure (also texted).

pt specifies the pin origin (lower left corner when the macro is in north orientation) offset from the foreign origin. The FOREIGN statement has a default offset value of 0 0, if pt is not specified.

LEF Syntax

orient specifies the orientation of the foreign cell when the macro is in north orientation. The default orient value is north.

For Silicon Ensemble, the calculation of absolute location for the foreign reference in OUTPUT GDSII is affected by component placement location, component orientation, and the pin foreign coordinate offset, but not by the pin foreign orientation.

TAPERRULE ruleName

Specifies the nondefault rule to use when tapering wires to the pin.

USE {ANALOG | CLOCK | GROUND | POWER | SIGNAL}

Specifies how the pin is used. Pin use is required for timing

analysis.

Default: SIGNAL

Value: Specify one of the following:

Pin is used for analog connectivity. ANALOG

Pin is used for clock net connectivity. CLOCK

Pin is used for connectivity to the chip-GROUND

level ground distribution network.

Pin is used for connectivity to the chip-POWER

level power distribution network.

Pin is used for regular net connectivity. SIGNAL

Macro Pin Considerations

Note the following when defining macro pins:

- LEQ pins must be identical for EEQ or LEQ macros.
- A given macro can have more than one set of LEQ pins.
- A set of LEQ pins cannot have more than one schematic pin (that is, a component pin connected to a net in DEF).
- You must manually select which pins to connect in the netlist.

Manufacturing Grid

[MANUFACTURINGGRID value ;]

LEF Syntax

Defines the manufacturing grid for the design. The manufacturing grid is used for geometry alignment. When specified, shapes and cells are placed in locations that snap to the manufacturing grid.

value

Specifies the value for the manufacturing grid, in microns.

value must be a positive number.

Type: Float

Maximum Via Stack

```
[MAXVIASTACK value [RANGE bottomLayer topLayer];]
```

Specifies the maximum number of single-cut stacked vias that are allowed on top of each other (that is, in one continuous stack). A via is considered to be in a stack with another via if the cut of the first via overlaps any part of the cut of the second via. The MAXVIASTACK statement should follow the LAYER statements in the LEF file; however, it is not attached to any particular layer. You can specify only one MAXVIASTACK statement in a LEF file.

RANGE bottomLayer topLayer

Specifies a range of layers for which the maximum stacked via rule applies. If you do not specify a range, the value applies for

all layers.

value Specifies the maximum allowed number of single-cut stacked

vias.

Type: Integer

Example 1-19 Maximum Via Stack Statement

The following MAXVIASTACK statement specifies that only four stacked vias are allowed on top of each other. This rule applies to all layers.

```
LAYER m9
...
END LAYER
MAXVIASTACK 4 ;
```

If you specify the following statement instead, the stacked via limit applies only to layers *m1* through *m7*.

```
MAXVIASTACK 4 RANGE m1 m7 ;
```

Names Case Sensitive

```
NAMESCASESENSITIVE {ON | OFF} ;
```

LEF Syntax

Specifies if LEF data is case sensitive.

Note: Many applications do not support NAMECASESENSITIVE OFF, because they are dependent on matching case-sensitive names in Verilog.

Nondefault Rule

```
[NONDEFAULTRULE rulename1
{LAYER layerName
    WIDTH width;
    SPACING minSpacing;
    [WIREEXTENSION value;]
    [RESISTANCE RPERSQ value;]
    [CAPACITANCE CPERSQDIST value;]
    [EDGECAPACITANCE value;]
    END layerName} ...
{VIA viaStatement} ...
[SPACING
    [SAMENET layerName layerName minSpace [STACK];] ...
END SPACING]
[PROPERTY propName propValue;] ...
```

Defines the wiring width, design rule spacing, and via size for regular (signal) nets. These characteristics must be equal to or greater than those characteristics for the default regular routing.

You do not need to define cut layers for the nondefault rule.

Some tools have limits on the total number of nondefault rules they can store. This limit can be as low as 30; however most tools that support 90 nanometer rules (that is, LEF 5.5) can handle at least 255.

Note: Use the VIA statement to define vias for nondefault wiring.

CAPACITANCE CPERSQDIST value

Specifies the capacitance for each square unit, in picofarads per square micron. This is used to model wire-to-ground capacitance.

EDGECAPACITANCE value

Specifies a floating-point value of peripheral capacitance, in

LEF Syntax

picofarads per micron. The place-and-route tool uses this value in two situations:

- Estimating capacitance before routing
- Calculating segment capacitance after routing

For the second calculation, the tool uses value only if you set layer thickness, or layer height, to 0. In this situation, the peripheral capacitance is used in the following formula: segment capacitance = (layer capacitance per square x segment width x segment length) + (peripheral capacitance x 2 (segment width + segment length))

For Silicon Ensemble, if you do not specify a value for EDGECAPACITANCE, the values of the Timing.Fringcap.layernum environmental variables are used instead.

LAYER layerName

Specifies the name of the layer.

NONDEFAULTRULE rulename 1

Specifies the name for the nondefault rule.

PROPERTY propName propVal

Specifies a numerical or string value for a nondefault rule property defined in the PROPERTYDEFINITIONS statement. The *propName* you specify must match the *propName* listed in the PROPERTYDEFINITIONS statement.

RESISTANCE RPERSO value

Specifies the resistance for a square of wire, in ohms per square micron.

Type: Float

SPACING Defines same-net spacing for the nondefault rule. This argument

uses the same syntax as the same-net spacing statement. For

syntax information, see "Same-Net Spacing" on page 89.

SPACING minSpacing Specifies the recommended minimum spacing of routes using

this NONDEFAULTRULE to other geometries. If the spacing is given, it must be at least as large as the foundry minimum spacing rules defined in the LAYER definitions. Routers should

LEF Syntax

attempt to meet this recommended spacing rule; however, the spacing rule can be relaxed to the foundry spacing rules along some parts of the wire if the routing is very congested, or it is difficult to reach a pin.

Adding extra space to a nondefault rule allows a designer to reduce cross-coupling capacitance and noise, but a clean route with no actual foundry spacing violations will still have precedence.

VIA viaStatment

Defines a via. You must define vias for each nondefault rule. You define nondefault vias using the same syntax as default vias. For syntax information, see <u>"Via"</u> on page 95. All vias, default and nondefault, must have unique via names.

If you define more than one via for a rule, the router chooses which via to use.

By omitting the WIDTH statement (below), you can also create a nondefault rule that covers all vias that do not have via widths explicitly defined.

WIDTH width

Specifies the nondefault routing width. The nondefault routing width for the first rule name must be wider than or equal to the default wiring. The nondefault width for each successive rule name must be wider than or equal to the width of the previous rule name.

WIREEXTENSION value

Specifies the distance by which wires are extended at vias. Enter zero to specify no extension. Values other than zero must be greater than or equal to half of the routing width for the layer, as defined in the nondefault rule.

Default: Wires are extended half of the routing width

Type: Float

Example 1-20 Nondefault Rule Statements

NONDEFAULTRULE RULE1
LAYER M1
WIDTH 10.0;
SPACING 2.2;
END M1

LEF Syntax

```
LAYER M2
      WIDTH 10.0 ;
      SPACING 2.2;
    END M2
    LAYER M3
      WIDTH 11.0 ;
      SPACING 3.2;
    END M3
    VIA nd1VIA12
      FOREIGN IN1X;
      RESISTANCE 0.2;
      LAYER M1 ;
         RECT -3 -3 3 3 ;
      LAYER V1 ;
        RECT -1.0 -1.0 1.0 1.0;
      LAYER M2 ;
        RECT -3 -3 3 3 ;
    END nd1VIA12
    VIA nd1VIA23
      LAYER M3 ;
        RECT -2.2 -2.2 2.2 2.2;
      LAYER V2 ;
        RECT -0.8 -0.8 0.8 0.8;
      LAYER M2 ;
        RECT -2.0 -2.0 2.0 2.0;
    END nd1VIA23
    SPACING
       SAMENET
         CUT01 M1 0.1 STACK;
    END SPACING
END RULE1
```

In the following example, RULE1 uses a wire extension of 70 on layer *M1* instead of the default extension of 0.

```
NONDEFAULTRULE RULE1

LAYER M1

WIDTH 120;

WIREEXTENSION 70;

.....

END M1
.....
```

END

Because no wire extension is specified in RULE2, the rule defaults to 0.

LEF Syntax

```
NONDEFAULTRULE RULE2
LAYER M1
WIDTH 130 ;
.....
END M1
.....
```

No Wire Extension

```
[NOWIREEXTENSIONATPIN {ON | OFF} ;]
```

Specifies whether to extend wires at pins. By default (OFF), wires are extended one-half of their width at pins.

Property Definitions

Lists all properties used in the LEF file. You must define properties in the PROPERTYDEFINITIONS statement before you can refer to them in other sections of the LEF file.

objectType Specifies the object type being defined. You can define

properties for the following object types:

LAYER

LIBRARY

MACRO

NONDEFAULTRULE

PIN

VIA

VIARULE

propName Specifies a unique property name for the object type.

LEF Syntax

propType Specifies the property type for the object type. You can specifiy

one of the following property types:

INTEGER

REAL

STRING

RANGE min max Limits real number and integer property values to a specified

range. That is, the value must be greater than or equal to min

and less than or equal to max.

value | "stringValue"

Assigns a numeric value or a name to a LIBRARY object type.

Note: Assign values to other properties in the section of the LEF file that describes the object to which the property applies.

Example 1-21 Property Definitions Statement

The following example shows library via and macro property definitions.

```
PROPERTYDEFINITIONS

LIBRARY versionNum INTEGER 12;
LIBRARY title STRING "Cadence96";

VIA count INTEGER RANGE 1 100;

MACRO weight REAL RANGE 1.0 100.0;
MACRO type STRING;

END PROPERTYDEFINITIONS
```

Same-Net Spacing

```
[SPACING
[SAMENET layerName layerName minSpace [STACK];]...
END SPACING]
```

Defines the same-net spacing rules. Same-net spacing rules determine minimum spacing between geometries in the same net and are only required if same-net spacing is smaller than different-net spacing, or if vias on different layers have special stacking rules. These specifications are used for design rule checking by the routing and verification tools.

Spacing is the edge-to-edge separation, both orthogonal and diagonal. Same-net spacing rules are less restrictive than different-net spacing rules.

LEF Syntax

Note: If SAMENET rules are not defined, via stacking is legal by default.

layerName layerName Specify the names of the layers for which the same-net spacing

rule applies. You can specify spacing rules for routing layers and

cut layers. For a routing layer, the same-net spacing rule is

defined by specifying the same layer name twice.

minSpace Specifies the minimum spacing.

STACK Allows stacked vias at a routing layer. The STACK keyword is

intended for use between two adjacent CUT layers. The use of the STACK keyword on METAL layers is considered obsolete, and

is ignored.

Example 1-22 Same-Net Spacing Rules

The following example sets the minimum same-net spacing for layer *M1*:

```
SAMENET M1 M1 1.5;
```

This statement is only needed if the same-net spacing is different than the different-net spacing already in the M1 LAYER section.

The following example defines spacing for cut layers. The statement sets the same-net spacing to 2.3 microns (also in the xy plane) for pairs of features, where one geometry is on CUT01 and the other geometry is on CUT12, and disables stacked (overlapped) vias.

```
SAMENET CUT01 CUT12 2.3 ;
```

You can allow stacked vias at a routing layer by including the STACK keyword in the same-net specification for that layer. For example, the following specification allows a 1-2 via and a 2-3 via to be stacked at the same point in the design. If they do not exactly align, the same-net spacing rule of 1.5 microns is applied.

```
SAMENET CUT12 CUT23 1.5 STACK ;
```

If you want to allow arbitrary stacking between vias, you can either use the default behavior by not specifying a SAMENET rule, or you can do it explicitly using the following statement:

```
SAMENET via12 via23 0.0 STACK;
```

The following example allows abutted or wider spaced cuts, but does not allow stacking or overlapping:

```
SAMENET vial2 via23 0.0;
```

LEF Syntax

Nondefault Rules and Same-Net Spacing

NONDEFAULT rules inherit the default SPACING SAMENET rules. However if the NONDEFAULT rule has its own SAMENET rules, these rules override the default values.

For example, no SAMENET rules at all allows stacking and overlap for default and nondefault routes. However, the following default:

```
SAMENET cut12 cut23 0.1;
```

turns off via12 and via23 stacking for all default and nondefault routes, and requires the vias to be separated by 0.1 microns.

A default SPACING section with

```
SAMENET cut12 cut23 0.1;
```

followed by a NONDEFAULT rule with

```
SAMENET cut12 cut23 0.1 STACK;
```

allows an exactly aligned stacked via for the nondefault routes, but does not allow stacking for the nondefault routes.

Site

```
SITE siteName
    CLASS {PAD | CORE};
[SYMMETRY {X | Y | R90} ...;]
SIZE width BY height;
END siteName
```

Defines a placement site in the design. A placement site gives the placement grid for a family of macros, such as I/O, core, block, analog, digital, short, tall, and so forth.

```
CLASS {PAD | CORE} Specifies whether the site is an I/O pad site or a core site.
```

```
SITE siteName Specifies the name for the placement site.
```

```
SIZE width BY height Specify the dimensions of the site in normal (or north) orientation. in microns.
```

```
SYMMETRY {X | Y | R90}
```

Indicates which site orientations are equivalent. The sites in a given row all have the same orientation as the row. Generally, site symmetry should be used to control the flipping allowed

LEF Syntax

inside the rows. For more information on defining symmetry, see "Defining Symmetry" on page 66.

Possible orientations include:

- X Site is symmetric about the x axis. This means that N and FS sites are equivalent, and FN and S sites are equivalent. A macro with an orientation of N matches N or FS rows.
- Site is symmetric about the y axis. This means that N and FN sites are equivalent, and FS and S sites are equivalent. A macro with an orientation of N matches N or FN rows.
- X Y Site is symmetric about the x and y axis. This means that N, FN, FS, and S sites are equivalent. A macro with orientation N matches N, FN, FS, or S rows.
- R90 Site is symmetric when rotated 90 degrees. Typically, this value is not used.

Note: Typically, a site for single-height standard cells uses symmetry Y, and a site for double-height standard cells uses symmetry X Y.

Units

```
[UNITS

[TIME NANOSECONDS convertFactor;]

[CAPACITANCE PICOFARADS convertFactor;]

[RESISTANCE OHMS convertFactor;]

[POWER MILLIWATTS convertFactor;]

[CURRENT MILLIAMPS convertFactor;]

[VOLTAGE VOLTS convertFactor;]

[DATABASE MICRONS LEFconvertFactor;]

[FREQUENCY MEGAHERTZ convertFactor;]

END UNITS]
```

Defines the units of measure in LEF. The values tell you how to interpret the numbers found in the LEF file. Units are fixed with a <code>convertFactor</code> for all unit types, except database units and capacitance. For more information, see "Convert Factors" on page 94. Currently, other values for <code>convertFactor</code> appearing in the <code>UNITS</code> statement are ignored; these values are intended for future use.

The UNITS statement is optional and, when used, must precede the LAYER statements.

LEF Syntax

CAPACITANCE PICOFARADS convertFactor

Interprets one LEF capacitance unit as 1 picofarad.

CURRENT MILLIAMPS convertFactor

Interprets one LEF current unit as 1 milliamp.

DATABASE MICRONS LEFconvertFactor

Interprets one LEF distance unit as multiplied when converted into databse units.

If you omit the DATABASE MICRONS statement, a default value of 100 is recorded as the *LEFconvertFactor* in the database. In this case, one micron would equal 100 database units.

FREQUENCY MEGAHERTZ convertFactor

Interprets one LEF frequency unit as 1 megahertz.

POWER MILLIWATTS convertFactor

Interprets one LEF power unit as 1 milliwatt.

RESISTANCE OHMS convertFactor

Interprets one LEF resistance unit as 1 ohm.

TIME NANOSECONDS convertFactor

Interprets one LEF time unit as 1 nanosecond.

VOLTAGE VOLTS convertFactor

Interprets one LEF voltage unit as 1 volt.

Database Units Information

Database precision is relative to Standard International (SI) units. LEF values are converted to integer values in the library database as follows.

SI unit	Database precision
1 nanosecond	= 1,000 DBUs
1 picofarad	= 1,000,000 DBUs
1 ohm	= 10,000 DBUs
1 milliwatt	= 10,000 DBUs
1 milliamp	= 10,000 DBUs

LEF Syntax

SI unit	Database precision
1 volt	= 1,000 DBUs

Convert Factors

Currently, LEF only supports values of 100, 200, 1000, and 2000 for *LEFconvertFactor*. The following table illustrates the conversion of LEF distance units into database units.

LEFconvertFactor	LEF	Database Units
100	1 micron	100
200	1 micron	200
1000	1 micron	1000
2000	1 micron	2000

The DEF database precision cannot be more precise than the LEF database precision. This means the DEF convert factor must always be less than or equal to the LEF convert factor. The following table shows the valid pairings of the LEF convert factor and the corresponding DEF convert factor.

LEFconvertFactor	DEFconvertFactor
100	100
200	100
200	200
1000	100
1000	1000
2000	100
2000	2000

Note: For Silicon Ensemble, the LEF convert factor must be the same as the DEF convert factor.

Any other values or combinations of the LEF convert factor and DEF convert factor are not supported in the DATABASE MICRONS statement.

LEF Syntax

An incremental LEF should have the same value as a previous LEF. An error message warns you if an incremental LEF has a different value than what is recorded in the database.

Use Min Spacing

```
[USEMINSPACING OBS { ON | OFF } ;]
[USEMINSPACING PIN { ON | OFF } ;]
```

Defines how minimum spacing is calculated for obstruction (blockage) and pin geometries.

OBS Specifies that the minimum spacing applies to obstruction

geometries.

ON | OFF Specifies how to calculate minimum spacing. If you specify ON

(the default for obstruction), the spacing is the minimum layer spacing. If you specify OFF (the default for pins), the spacing is the range spacing that corresponds to the minimum width (in x

and y directions) of the pin or obstruction.

PIN Specifies that the minimum spacing applies to pin geometries.

Version

```
VERSION number ;
```

Specifies which version of the LEF syntax is being used. number is a string of the form major.minor.subMinor, such as 5.5.

Note: Many applications default to the latest version of LEF/DEF supported by the application (which depends on how old the application is). The latest version as described by this document is 5.5. However, a default value of 5.5 is not formally part of the language definition; therefore, you cannot be sure that all applications use this default value. Also, because the default value varies with the latest version, you should not depend on this.

Via

```
VIA viaName
[DEFAULT]
[TOPOFSTACKONLY]
[FOREIGN foreignCellName [pt [orient]];]
[RESISTANCE value;]
{LAYER layerName;
{RECT pt pt;}...}...
[PROPERTY propName propVal;]...
```

LEF Syntax

END viaName

Defines vias for usage by signal routers (that is, vias that will be used in the DEF NETS section).

Note: Use the VIARULE statement to define special wiring.

DEFAULT

Indicates that the via can be used for default routing by the signal routers. Signal routers use the LAYER WIDTH, LAYER SPACING, and DEFAULT VIAS for routing unless a NONDEFAULTRULE is specified. Normally, several default vias are specified for each routing-cut-routing layer combination, and the router will choose which via to use. You must define default vias between metal1 and masterslice layers if there are pins on the masterslice layers.

Note: Default vias have exactly three layers used: a cut layer, and two layers that touch the cut layer (routing or masterslice). The cut layer rectangle must be between the two routing or masterslice layer rectangles.

FOREIGN foreignCellName [pt [orient]]

Specifies the foreign (GDSII) structure name to use when placing an instance of the via. Only one foreign declaration is allowed for a via. The optional pt coordinate specifies the cell origin (normally, the via center) offset relative to the foreign origin. The FOREIGN statement has a default offset value of 0 0, if pt is not specified.

The optional *orient* value specifies the orientation of the foreign cell when the macro is in north orientation. The default *orient* value is north.

For vias used in any routing, via coordinates must be consistent with their location at the intersection of the wires. Vias referenced in pins or obstructions must have the GDSII origin at the center of the via.

Example 1-23 Foreign Statement

The following example defines a FOREIGN statement for via B.

VIA B FOREIGN B -2 -3;

LEF Syntax

The negative offset specifies that the GDSII structure origin should be above and to the right of the via origin. For example, for a 2-by-2 via, with (0 0) to (2 2) coordinates in GDSII, the FOREIGN statement uses (1 1) to put the origin at the center.

LAYER layerName

Specifies the layer on which to create the rectangles that make up the via. Normal vias have exactly three layers used: a cut layer, and two layers that touch the cut layer (routing or masterslice).

In the past, it was possible to create a via with just a cut layer, but this is not recommended because many tools cannot support this style of via. This type of via was only used to create obstructions, and does not appear in real routing data. Cut layer obstructions should be put directly into the MACRO OBS section, instead of using a "cut layer" via.

WARNING: Vias can be rectilinear rather than square, but some routers cannot orient vias; they all stay in normal orientation in the layout. Define vias of the proper shape for each direction needed. Be careful of non-square vias in components that can be rotated, because the vias cannot be oriented. Define components with appropriate vias.

PROPERTY propName propVal

Specifies a numerical or string value for a via property defined in the PROPERTYDEFINITIONS statement. The *propName* you specify must match the *propName* listed in the PROPERTYDEFINITIONS statement.

RECT pt pt

Specify the geometries that make up the via. For vias used only in macros or pins, reference locations and rectangle coordinates must be consistent.

RESISTANCE value

Specifies the total resistance of the via, given as the resistance per via.

Type: Float, in units of ohms

Note: This is not a resistance per via-cut value; it is the total resistance of the via.

LEF Syntax

TOPOFSTACKONLY

Prevents the router from using the via except for via stacking. When defining stacked vias, use TOPOFSTACKONLY to instruct the router to use this via (rather than the default via) to satisfy minimum area rules.

For a *metal1* to *metal5* stack, the TOPOFSTACKONLY via will be used for all except the bottom via. Thus, the bottom routing layer of a TOPOFSTACKONLY via should satisfy the minimum area rules.

viaName

Specifies the name for the via.

Example 1-24 Via Statements

The following example defines a three-layer design with the TOPOFSTACKONLY keyword. To satisfy the minimum-area rule requirement, you specify three vias: the default via and two overhang vias to accommodate two different directions. This provides the router the flexibility to choose the most suitable via during routing.

The following example defines default Via23 with layer Metal2, Metal3, and Cut23 contact cut.

```
VIA Via23 DEFAULT
LAYER Metal2;
RECT -0.7 -0.7 0.7 0.7;
LAYER Cut23;
RECT -0.4 -0.4 0.4 0.4;
LAYER Metal3;
RECT -0.6 -0.6 0.6 0.6;
END Via23
```







Default

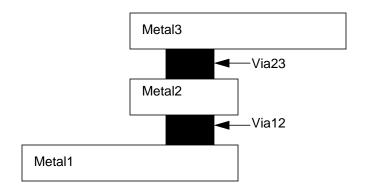
North

South

The following examples defines Via23_north with Metal2, Metal3, and contact cut placed at the top. Notice that Metal2 is longer and extends to the north.

LEF Syntax

```
VIA Via23_north DEFAULT
TOPOFSTACKONLY
LAYER Metal2;
RECT -0.7 -0.7 0.7 1.7;
LAYER Cut23;
RECT -0.4 -0.4 0.4 0.4;
LAYER Metal3;
RECT -0.6 -0.6 0.6 0.6;
END Via23_north
```



The following example defines Via23_south with Meta12, Meta13, and the contact cut placed at the top. Notice that Meta12 is longer and extends to the south.

```
VIA Via23_south DEFAULT TOPOFSTACKONLY
LAYER Metal2;
RECT -0.7 -1.7 0.7 0.7;
LAYER Cut23;
RECT -0.4 -0.4 0.4 0.4;
LAYER Metal3;
RECT -0.6 -0.6 0.6 0.6;
END Via23_south
```

The following figure shows a foreign offset.



LEF Syntax

Via Rule

```
VIARULE viaRuleName

LAYER layerName;

DIRECTION {HORIZONTAL | VERTICAL};

[WIDTH minWidth TO maxWidth;]

LAYER layerName;

DIRECTION {HORIZONTAL | VERTICAL};

[WIDTH minWidth TO maxWidth;]

{VIA viaName;}...

[PROPERTY propName propVal;]...

END viaRuleName
```

Defines which vias to use at the intersection of special wires of the same net. Normally, a VIARULE GENERATE statement is used to create a via for the intersection of two special wires. However, if a special case occurs that cannot be defined by the VIARULE GENERATE statement—for example, you require a via with unusual offsets or geometry—you can use the VIARULE statement to explicitly describe the type of via to use at the intersection of two special wires on specific routing layers with a specific width.

You must specify appropriate via rules for all possible wire widths that can occur in special wiring.

```
DIRECTION {HORIZONTAL | VERTICAL}
```

Specifies the wire direction. If you specify a WIDTH range, the rule applies to wires of the specified DIRECTION that fall within the range. Otherwise, the rule applies to all wires of the specified DIRECTION on the layer.

LAYER layerName

Specifies the routing layers for the top or bottom of the via.

PROPERTY propName propVal

Specifies a numerical or string value for a via rules property defined in the PROPERTYDEFINITIONS statement. The propName you specify must match the propName listed in the PROPERTYDEFINITIONS statement.

VIA viaName

Specifies a previously defined via to test for the current via rule. The first via in the list that can be placed at the location without design rule violations is selected. The vias must all have exactly three layers in them. The three layers must include the same routing layers as listed in the LAYER statements of the VIARULE, and a cut layer that is between the two routing layers.

VIARULE *viaRuleName* Specifies the name to identify the via rule.

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LEF Syntax

WIDTH minWidth TO maxWidth

Specifies a wire width range. If the widths of two intersecting special wires fall within the wire width range, the VIARULE is used. To fall within the range, the widths must be greater than or equal to minWidth and less than or equal to maxWidth.

Note: WIDTH is defined by wire direction, not by layer. If you specify a WIDTH range, the rule applies to wires of the specified DIRECTION that fall within the range.

Example 1-25 Via Rule Statement

In the following example, whenever an m1 wire with a width between 0.5 and 1.0 intersects an m2 wire with a width between 1.0 and 2.0, the via generation code attempts to put a $via12_1$ at the intersection first. If the $via12_1$ cause a DRC violation, a $via12_2$ is then tried. If both fail, the default behavior from a VIARULE GENERATE statement for m1 and m2 is used.

```
VIARULE viaRule1

LAYER m1;

WIDTH 0.5 TO 1.0;

LAYER m2;

WIDTH 1.0 TO 2.0;

VIA via12_1;

VIA via12_2;

END viaRule1
```

Creating a Via from a Via Rule

You can specify how to create a via from a particular via rule in the following ways:

- List the vias explicitly, as described in this section. The router places the first via that does not create any design rule violations.
- Provide a via generation specification for creating the via. This method is shown in <u>"Via Rule Generate"</u> on page 102.

For Silicon Ensemble, when the SROUTE, ADD WIRE, and MOVE WIRE commands need a via, they examine the via rules in the order of specification in the LEF file for applicability. The first two layer and direction declarations must match the layers and directions of the intersecting wire segments.

If the widths of the wires fall in the ranges given by the WIDTH specifications, that via rule is used. If no via rule applies, the default via rule is used. To create a default via rule that covers all vias other than those whose widths are explicitly defined, omit the WIDTH statement when

LEF Syntax

you create the via rule. To avoid VERIFY LIBRARY violations for undefined vias, a default via rule should exist that can be used for any wiring width not explicitly defined.

Changing Net Representation

For Silicon Ensemble, if you want to change the net representation from special to regular so that the automatic routers route the net, use CHANGE NET REPRESENTATION and do the following:

- Ensure that all wires in the net are the default or nondefault width for regular wiring. If not, the conversion does not occur.
- Ensure that the vias in the net are defined in the VIA section (defines vias for the default regular wiring) and the NONDEFAULT RULE section (defines vias for all regular wiring except the default wiring). If they are not, the vias will be missing after the conversion.

To change regular wiring to special wiring so that you can interactively route the net, use CHANGE NET REPRESENTATION and do the following:

- Ensure that all wire widths in the net are special wire widths.
- Ensure that all vias are defined in the VIA RULE section (defines vias for special wiring) or the VIA RULE GENERATE section.

Via Rule Generate

```
VIARULE viaRuleName GENERATE
    LAYER routingLayerName;
        { DIRECTION {HORIZONTAL | VERTICAL} ;
            [OVERHANG overhang;]
            [METALOVERHANG metaloverhang;]
        | ENCLOSURE overhang1 overhang2 ;}
        [WIDTH minWidth TO maxWidth;]
    LAYER routingLayerName;
       { DIRECTION {HORIZONTAL | VERTICAL} ;
            [OVERHANG overhang;]
            [METALOVERHANG metaloverhang;]
        | ENCLOSURE overhang1 overhang2 ;}
       [WIDTH minWidth TO maxWidth;]
    LAYER cutLayerName ;
       RECT pt pt ;
       SPACING xSpacing BY ySpacing ;
       [RESISTANCE resistancePerCut ;]
END viaRuleName
```

LEF Syntax

Defines formulas for generating via arrays. Use the VIARULE GENERATE statement to cover special wiring that is not explicitly defined in the VIARULE statement.

Rather than specifying a list of vias for the situation, you can create a formula to specify how to generate the cut layer geometries.

```
DIRECTION {HORIZONTAL | VERTICAL}
```

Specifies the wire direction. If you specify a WIDTH range, the rule applies to wires of the specified DIRECTION that fall within the range. Otherwise, the rule applies to all wires of the specified DIRECTION on the layer.

Note: OVERHANG and METALOVERHANG are defined by wire direction, not by layer. For the via generated, both metal layers (for example, *metal1* and *metal2*) will have the same METALOVERHANG and OVERHANG values. It is not possible to have different overhangs for different routing layers. You must set the overhang in both directions to the distance needed by the layer that needs the largest overhang.

Example 1-26 Via Rule Generate Direction Statement

The following example describes a formula for generating via cuts using DIRECTION. If you specify DIRECTION, the WIDTH range is based on the connecting horizontal or vertical wire, not the layer of the connecting wire. Therefore, a horizontal wire that is between 0 and 1.0 μ m wide and a vertical wire that is between 0 and 2.0 μ m wide will trigger ViaGen1, independent of whether the horizontal wire is M1 or M2.

```
VIARULE viaGen1 GENERATE

LAYER M1;

DIRECTION HORIZONTAL;

WIDTH 0 TO 1.0;

OVERHANG 0.5;

LAYER M2;

DIRECTION VERTICAL;

WIDTH 0 TO 2.0;

OVERHANG 0.5;

LAYER CUT12;

RECT -0.07 -0.07 0.07 0.07;

SPACING 0.30 BY 0.30;

END viaGen1
```

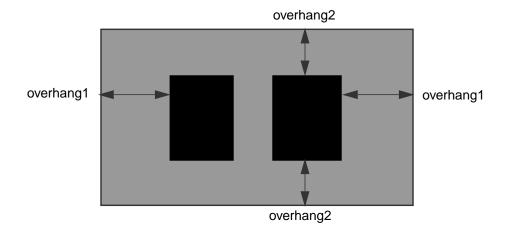
LEF Syntax

ENCLOSURE overhang1 overhang2

Specifies that the via must be covered by metal on two opposite sides by at least <code>overhang1</code>, and on the other two sides by at least <code>overhang2</code> (see Figure 1-18 on page 104). The via generation code then chooses the direction of overhang that best maximizes the number of cuts that can fit in the via. Type: Floats, specified in microns

Note: If you specify ENCLOSURE, you cannot specify DIRECTION, OVERHANG, and METALOVERHANG.

Figure 1-18



Example 1-27 Via Rule Generate Enclosure Statement

The following example describes a formula for generating via cuts using ENCLOSURE.

```
VIARULE via12 GENERATE
   LAYER m1 ;
   ENCLOSURE 0.05 0.01 ; #2 sides must be >=0.05, 2 other sides must be >=0.01
   WIDTH 0.2 TO 100.0 ; #for m1, between 0.2 to 100 microns wide
   LAYER m2;
   ENCLOSURE 0.05 0.01 ; #2 sides must be >=0.05, 2 other sides must be >=0.01
   WIDTH 0.2 TO 100.0 ; #for m2, between 0.2 to 100 microns wide
   LAYER cut12
   RECT -0.07 -0.07 0.07 0.07 ; #cut is .14 by .14
   SPACING 0.30 BY 0.30 ; #center-to-center spacing
END via12
```

LEF Syntax

The cut layer SPACING ADJACENTCUTS statement can override the VIARULE cut layer SPACING statements. For example, assume the following cut layer information also is defined in the LEF file:

```
LAYER cut 12
...
SPACING 0.20 ADJACENTCUTS 3 WITHIN 0.22;
```

The 0.20 μ m edge-to-edge spacing in the ADJACENTCUTS statement is larger than the VIARULE GENERATE example spacing of 0.16 (0.30 – 0.14). Whenever the VIARULE GENERATE rule creates a via that is larger that 2x2 cuts (that is, 2x3, 3x2, 3x3 and so on), the 0.20 spacing from the ADJACENTCUTS statement is used instead.

Note: The spacing in VIARULE GENERATE is center-to-center spacing, whereas the spacing in ADJACENTCUTS is edge-to-edge.

GENERATE Defines a formula for generating the appropriate via.

LAYER *cutLayerName* Specifies the cut layer for the generated via.

LAYER routingLayerName

Specifies the routing layers for the top and bottom of the via.

METALOVERHANG metaloverhang

Specifies the amount of metal overhang between the edge of the wire and the edge of the via for the specified wire DIRECTION, for both metal layers. (See <u>Figure 1-20</u> on page 106.)

Default: The value that matches the overhang

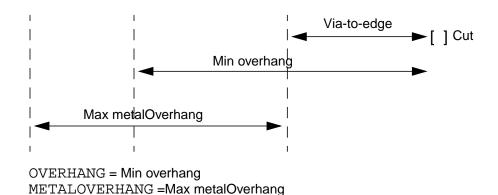
Metal overhang is calculated in the following way:

```
(width of via) + (2 \times \text{overhang}) - (width of wire)) /2
```

Even though OVERHANG and METALOVERHANG define upper and lower bounds of a single property, their points of reference are different. (See <u>Figure 1-19</u> on page 106.)

LEF Syntax

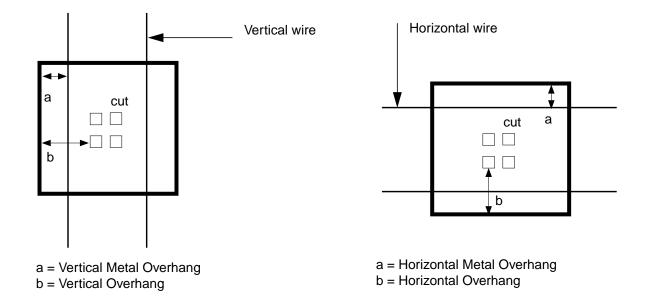
Figure 1-19



OVERHANG overhang

Specifies the amount of metal between contact cuts and the edge of the via for the specified wire DIRECTION, for both metal layers. (See <u>Figure 1-20</u> on page 106.)

Figure 1-20



RECT pt pt

Specifies the location of the lower left contact cut rectangle.

RESISTANCE resistancePerCut

Specifies the resistance of the cut layer, given as the resistance

LEF Syntax

per contact cut. *Type:* Float

SPACING xSpacing BY ySpacing

Defines center-to-center spacing in the x and y dimensions to create an array of contact cuts. The number of cuts of an array in each direction is the most that can fit within the bounds of the intersection formed by the two special wires. Cuts are only generated where they do not violate stacked or adjacent via design rules.

Note: This value can be overridden by the SPACING ADJACENTCUTS value in the cut layer statement.

VIARULE *viaRuleName* Specifies the name for the formula.

WIDTH minWidth TO maxWidth

Specifies a wire width range within which the wire must fall in order for the rule to apply. That is, the wire width must be greater than or equal to minWidth and less than or equal to maxWidth.

Note: WIDTH is defined by wire direction, not by layer. If you specify a WIDTH range, the rule applies to wires of the specified DIRECTION that fall within the range.

Turn Via Rules

Turn via rules fill in the corner area at the intersection between two special wires on the same layer, where each wire must be extended by half the width of the other wire. Single-layer turns in special wiring are defined as single-layer vias. Each routing layer needs to specify a turn rule with no size restriction and no rectangle.

LEF Syntax

DEFINE and ALIAS

This chapter contains information about the following topics.

- DEFINE statements:
 - DEFINE Expressions on page 110
 - □ DEFINE Syntax on page 113
 - □ DEFINE Expansion on page 114
 - □ <u>DEFINE Examples</u> on page 115
- ALIAS statements:
 - □ ALIAS Definition on page 116
 - □ ALIAS Examples on page 116
 - □ ALIAS Expansion on page 117

DEFINE Statements

DEFINE statements assign variable names to Boolean, numeric, and string expressions in a Library Exchange Format (LEF) or Design Exchange Format (DEF) file. INPUT LEF and INPUT DEF evaluate each expression when the LEF or DEF file is read. The variable remains fixed until redefined by a subsequent DEFINE statement. Once you create a DEFINE variable, it can subsequently appear in place of any LEF or DEF token. DEFINE statements are not saved into the database.

DEFINE variables are used in LEF and DEF files for substitution. For example, if you define the variables &X and &Y, you can use the following LEF statement:

```
SIZE &X BY &Y
```

Each expression has a fixed type, that is, numeric, string, or Boolean. The type is determined by the DEFINE token used: &DEFINE (numeric), &DEFINES (string), or &DEFINEB (Boolean).

DEFINE and ALIAS

The expression value and the DEFINE token must match. For example, when you use &DEFINEB to assign an expression, the expression must always evaluate to a Boolean value.

DEFINE Expressions

Expressions in DEFINE statements are written in either single- or multiple-line forms. Each single-line expression must appear entirely on one line of the LEF or DEF file. The three types of single-line expressions follow.

- numericExpression
- booleanExpression
- stringExpresssion

Each multiple-line expression has an IF/THEN/ELSE form and spans several lines. The three types of multiple-line expressions follow.

- numericlFexpression
- booleanlFexpression
- stringlFexpression

Note: Expressions can contain parentheses for grouping. However, you must insert a space or tab character between any parenthesis or operator token and an adjacent operand.

numericExpression

Valid numeric expressions evaluate to a numeric constant. You can use the following operands.

- Integer constant
- Real constant
- numericExpressionName

When an operand is a numeric expression name, you must have previously assigned a value using a &DEFINE statement. The value of *numericExpressionName* is used when evaluating the expression.

Numeric operators (in decreasing order of precedence) are as follows:

- 1. () (parentheses)
- 2. (unary negation)

DEFINE and ALIAS

```
    * /
    + - (binary)
```

Otherwise, evaluation is from left to right. The following are examples of valid numeric expressions:

```
( 32234 + 31105 ) * 3 / 2
( &X1 - 22921 + &X2 / 2 ) * - 1.88E-2
&Z1 * ( ( &X2 - 3.3E2 ) / &Y3 )
```

stringExpression

Valid string expressions evaluate to a string constant and can have either of the following forms:

- "stringText"
- stringExpressionName

The *stringText* is any alphanumeric string and must be enclosed in quotes. The quote character (") is allowed within the string text because the string terminator is the quote character followed by a space, tab, or EOL. When a string expression is a *stringExpressionName*, it must have been previously assigned using a &DEFINES statement.

The following operators can be used in string expressions:

- () parenthesis
- + concatenation

For example:

```
&name + "-" + &type
```

booleanExpression

Valid Boolean expressions evaluate to the Boolean constants, true or false. Boolean expressions are generated by the following:

■ Two numeric expressions connected by one of the following binary numeric operators:

```
EQ or = (equal)NEQ or <> (not equal)
LT or < (less than) GT or > (greater than)
LEQ or <= GEQ or >= (greater
```

DEFINE and ALIAS

```
(less than or equal)than or equal)
AND (non-zero = True) OR (non-zero = True)
```

■ Two string expressions connected by one of the following binary string operators:

```
EQ or = (equal)NEQ or <> (not equal)
LT or < (less than)GT or > (greater than)
LEQ or <= GEQ or >=
```

For the above operators, the comparison looks at the character codes, starting from the left. Non-null strings are greater than null strings.

ANDOR

For AND/OR string expression evaluation, a non-null string is considered True, and a null string (" ") is considered False.

■ Two Boolean expressions connected by one of the following binary Boolean operators:

```
AND (logical and)OR (logical or) EQNEQ
```

- A Boolean, numeric, or string expression inverted by the unary Boolean operator NOT. (Numerics and strings evaluate to true or false.)
- booleanExpressionName
- Combinations of the above

When an operand is a Boolean expression name, it must have been previously assigned using a &DEFINEB statement. The value of *booleanExpressionName* is used when evaluating the expression. Operators used in Boolean expressions have the following decreasing order of precedence:

```
1. ()
```

```
2. - (unary)
```

3. */

4. + - (binary)

5. EQ, NEQ, LT, GT, LEQ, GEQ, =, <>, <, >, <=, >=

6. NOT

7. AND

8. OR

DEFINE and ALIAS

Otherwise, evaluation is from left to right.

The following are examples of Boolean expressions:

```
&X1 > 22876
(If X1 is numeric.)
  &FLAG <> "INT" AND &DELAY > 1.3E-3
(If &FLAG is string; &DELAY is numeric.)
  NOT &T1 OR NOT &S1
(If &T1 and &S1 are Boolean.)
```

numericlFexpression

Numeric IF expressions have the following form:

```
IF { booleanExpression }
   THEN { numericExpression | numericIFexpression }
   ELSE { numericExpression | numericIFexpression }
```

stringlFexpression

String IF expressions have the following form:

```
IF { booleanExpression }
   THEN { stringExpression | stringIFexpression }
   ELSE { stringExpression | stringIFexpression }
```

booleanIFexpression

Boolean IF expressions have the following form:

```
IF { booleanExpression }
   THEN { booleanExpression | booleanIFexpression }
   ELSE { booleanExpression | booleanIFexpression }
```

DEFINE Syntax

DEFINE statements assign expressions to variables. Each type of expression (numeric, string, and Boolean) has a different DEFINE statement syntax, as shown below:

DEFINE and ALIAS

Variable names have the following restrictions:

- Must begin with an ampersand (&)
- Are case sensitive based on the value of NAMESCASENSITIVE in the LEF input, or the value of Input.Lef.Names.Case.Sensitive
- Cannot contain spaces, tabs, or control characters

DEFINE statements have the following restrictions:

- &DEFINE, &DEFINES, and &DEFINEB are reserved keywords and must be the first token in any line in which they appear.
- IF, THEN, ELSE, TRUE, FALSE, and all operators are reserved tokens within a DEFINE statement.
- Spaces or tabs must be placed between all operators and operands, and between parentheses and operands.
- DEFINE statements end with a semicolon (;) as a delimiter.
- When a DEFINE statement assigns an expression name to a numericExpression, stringExpression, or booleanExpression, the definition must appear on the same line. A DEFINE statement can span multiple lines only if it assigns an expression name to an IF expression. In this case, the first IF keyword must appear on the same line as the DEFINE statement.
- When an expression name appears inside a DEFINE statement, the current value of the expression name is used to evaluate the DEFINE expression.

DEFINE Expansion

You can specify DEFINE symbols as expression expansion parameters for LEF or DEF files. A DEFINE can serve as a substitute for any token of a LEF or DEF file. DEFINE expansion can be considered as the reverse operation of expression definition. That is, to retrieve the

DEFINE and ALIAS

current *ExpressionName*, use && *ExpressionName*. If an *ExpressionName* does not have a current value, no substitution occurs. All EOL (end of line), space, and tab characters are preserved in a string DEFINE statement.

Syntax for ExpressionName expansion is defined as follows:

```
&ExpressionName
```

where *ExpressionName* is any *Name* previously defined.

DEFINE Examples

The following are examples of numeric DEFINE statements:

```
&DEFINE &A1 = 2.5E4 ;

&DEFINE &RES = IF &MARK = "FREE"

THEN &A1 + &B1

ELSE &A1 - &B1 ;
```

The following are examples of string DEFINE statements:

```
&DEFINES &VERSION = "3.1.8";
&DEFINES &DIR = IF &TAG
THEN "INPUT"
ELSE "OUTPUT";
```

The following are examples of Boolean DEFINE statements:

```
&DEFINEB &TAG = &DONE AND NOT &SEL ; &DEFINEB &FLAG = IF &X < &Y THEN TRUE ELSE FALSE ;
```

IF expressions can be nested as shown in the following examples:

DEFINE and ALIAS

ALIAS Statements

You can use alias statements in LEF and DEF files to define commands or parameters associated with the library or design. An alias statement can appear anywhere in a LEF or DEF file as follows:

```
&ALIAS &&aliasName = aliasDefinition &ENDALIAS
```

&ALIAS and &ENDALIAS are both reserved keywords and are not case sensitive. An alias statement has the following requirements:

- &ALIAS must be the first token in the line in which it appears.
- aliasName is string name and must appear on the same line as &ALIAS. It is case sensitive based on the value of NAMESCASENSITIVE in the LEF input, or the value of Input.Lef.Names.Case.Sensitive.
- aliasName cannot contain any of the following special characters: #, space, tab, or control characters.
- &ENDALIAS must be the last token in the line in which it appears.
- Multiple commands can appear in the alias definition, separated by semicolons. However, the last command must not be terminated by a semicolon.

ALIAS Definition

The alias name (aliasName) is an identifier for the associated alias definition (aliasDefinition). The data reader stores the alias definition in the database. If the associated alias name already exists in the database, a warning is issued and the existing definition is replaced.

Alias definitions are text strings with the following properties:

- aliasDefinition is any text excluding "&ENDALIAS".
- All EOL, space, and tab characters are preserved.
- aliasDefinition text can expand to multiple lines.

ALIAS Examples

The following examples include legal and illegal alias statements:

The following statement is legal.

DEFINE and ALIAS

&ALIAS &&MAC = SROUTE ADDCELL AREA &&CORE &ENDALIAS

■ The following statement is illegal because MAC does not start with "&&".

```
&ALIAS MAC = SROUTE AREA &&CORE &ENDALIAS
```

■ The following statement is illegal because &ALIAS is not the first token in this line.

```
( 100 200 ) &ALIAS &&MAC = SROUTE AREA &&CORE &ENDALIAS
```

■ The following statement is legal. It contains multiple commands; the last command is not terminated by a semicolon.

```
$ALIAS $$ = INPUT LEF myfile.txt;
VERIFY LIBRARY
ENDALIAS
```

The following examples show legal and illegal alias names:

■ "Engineer_change" is a legal alias name.

```
&&Engineer_change
```

■ "&Version&History&&" is a legal alias name.

```
&&&Version&History&&
```

"design history" is an illegal alias name. It contains a space character and is considered as two tokens: an aliasName token "&&design," and a non-aliasName token "history".

```
&&design history
```

■ "someName#IO-pin-Num" is an illegal alias name. It contains a "#" character and is translated as one aliasName token "&&someName". The "#" is considered a comment character.

```
&&someName#IO-pin-Num
```

ALIAS Expansion

Alias expansion is the reverse operation of alias definition. The following is the syntax for alias expansion.

```
&&aliasName
```

where *aliasName* is any name previously defined by an alias statement. If an *aliasName* does not exist in the database, no substitution occurs.

You use aliases as string expansion parameters for LEF or DEF files. An alias can substitute for any token of a LEF or DEF file.

DEFINE and ALIAS

Working with LEF

This chapter contains information about the following topics.

- Incremental LEF on page 119
- Error Checking on page 120

Incremental LEF

INPUT LEF can add new data to the current database, providing an incremental LEF capability. Although it is possible to put an entire LEF library in one file, some systems require that you put certain data in separate files.

This feature also is useful, for example, when combined with the INPUT GDSII command, to extract geometric data from a GDSII-format file and add the data to the database.

When using INPUT LEF on a database that has been modified previously, save the previous version before invoking INPUT LEF. This provides a backup in case the library information has problems and the database gets corrupted or lost.



The original LEF file, created with FINPUT LEF (or with INPUT LEF when no database is loaded), must contain all the layers.

Adding Objects to the Library

INPUT LEF can add the following objects to the database:

- New via
- New via rule
- Samenet spacings (if none have been specified previously)
- New macro

Working with LEF

If geometries have not been specified for an existing via, INPUT LEF can add layers and associated rectangle geometries. If not specified previously for a macro, INPUT LEF can add the following:

- FOREIGN statement
- EEQ
- LEQ
- Size
- Overlap geometries
- Obstruction geometries

If not previously specified for an existing macro pin, INPUT LEF can add the following:

- Mustjoins
- Ports and geometries

The database created by INPUT LEF can contain a partial library. Run VERIFY LIBRARY before proceeding.

If new geometries are added to a routed database, run VERIFY GEOMETRY and VERIFY CONNECTIVITY to identify new violations.

Important

When defining a pin with no port geometries with the intent of incrementally adding them, *do not* include an empty PORT statement as shown below.

```
MACRO abc
...
PIN a
...
PORT # dummy pin-port, do not
END # include these two lines
END a
...
```

Error Checking

To help develop, test, and debug generic libraries and parametric macros, LEF and DEF have a user-defined error checking facility. This facility consists of seven utilities that you can use

Working with LEF

from within a LEF or DEF file during the scanning phase of LEF/DEF readers. These utilities have the following features:

- A message facility that writes to one or more text files during LEF or DEF input
- An error handling facility that logs user detected warnings, errors, and fatal errors

The error checking utilities have the following syntax:

```
&CREATEFILE &fileAlias =
    { stringExpression
      stringIF-ELSEexpression } ;
&OPENFILE &fileAlias;
&CLOSEFILE &fileAlias;
&MESSAGE
    {&fileAlias | &MSGWINDOW} = message;
&WARNING
    {&fileAlias | &MSGWINDOW} = message ;
&ERROR
    {&fileAlias | &MSGWINDOW} = message ;
&FATALERROR
    {&fileAlias | &MSGWINDOW} = message;
message =
    { &fileAlias | stringExpression
      stringIF-ELSEexpression
      stringIFexpression }
```

Message Facility

The message facility outputs user-defined messages during the scanning phase of LEF and DEF input. These messages can be directed to the message window.

&CREATEFILE

The &CREATEFILE utility first assigns a token (&fileAlias) to represent a named file. The file name is derived from a previously defined string, a quoted string, or an IF-ELSE expression that evaluates to a string. The following example illustrates these three cases.

Working with LEF

```
&CREATEFILE &messages =

IF &errortrap

THEN "errs.txt"

ELSE "/dev/null";
```

The derived file name must be a legal file name in the host environment. The default directory is the current working directory. The file names are case sensitive.

&CREATEFILE creates an empty file with the given name and opens the file. If the token is already bound to another open file, a warning is issued, the file is closed, and the new file is opened. If the file already exists, the version number is incremented.

&CLOSEFILE and &OPENFILE

The &CLOSEFILE utility closes the file bound to a given token; &OPENFILE opens the file bound to a given token. &CLOSEFILE and &OPENFILE control the number of open files. Each operating system has a limit for the number of open files. Therefore, &CLOSEFILE might be needed to free up extra file descriptors.

Files are closed in the following ways.

- All user files are closed at the end of the scanning phase of the LEF and DEF readers.
- All user files are closed if the scanning phase aborts.
- If &CREATEFILE is invoked with a token that is already bound to an open file, that file is closed before opening the new file.

&MESSAGE

The &MESSAGE utility appends text to the file represented by the &fileAlias token, or to the message window if &MSGWINDOW is specified.

&MSGWINDOW is a special file alias that is not created, opened, or closed. The assigned expression (right side of the statement) can be one of the following:

&fileAlias Must correspond to a valid file that has been successfully opened. The contents of the file are appended to the target file (or message window).

stringExpression

Either a string or a string token.

For example:

Working with LEF

```
&DEFINES &romword16 =

"ROM word size = 16 bits";

&MESSAGE &mesgs = "ROM size = 256";

&MESSAGE &mesgs = &romword16;
```

stringIF-ELSEexpression

String IF-ELSE expressions evaluate a Boolean expression and then branch to string values, for example:

```
&&MESSAGE &mesgs =

IF (&&c_flag = 0)

THEN "FLAG C set to 0"

ELSE IF ( &&c_flag = 1 )

THEN "FLAG C set to 1"

ELSE "FLAG C set to 2";
```

As shown in this example, IF-ELSE expressions can be nested.

stringIFexpression

A string IF expression is an IF-ELSE expression without the ELSE phrase. The Boolean expression is evaluated, and if true, the THEN string is sent to the target file; if false, no string is sent, for example,

```
&MESSAGE &mesgs =

IF ( &&buf = "INV_BIG" )

THEN "INV_BIG buffers" ;
```

Neither the file alias token nor &MSGWINDOW can be part of the assigned expression.

Error-Checking Facility

In addition to the message facility, you have partial control of the error checking facility of the LEF and DEF readers. When scanning LEF or DEF input, the readers record warnings, errors, and fatal errors. At the end of the scan, the total number of each is sent to the message window before proceeding with the reader phase.

If a fatal error is detected, input is aborted after the scanning phase.

With the user interface to the error checking facility, the LEF and DEF files can include custom error checking. User detected warnings, errors, and fatal errors, can be logged, thereby incrementing the DEF/LEF reader's warning, error, and fatal error counts.

Working with LEF

A user-detected fatal error terminates input just as with the resident error checking facility. In addition, the user defined error checking facility utilities can send message strings to the message window.

&WARNING, &ERROR, and &FATALERROR

The &WARNING, &ERROR, and &FATALERROR utilities use the same syntax as the &MESSAGE utility. These utilities can send message strings to files and to the message window in the same manner as &MESSAGE. In addition, when the assigned expression is a string IF expression, or a string IF-ELSE expression, then the associated counter (warnings, errors, or fatal errors) is incremented by 1 if any IF condition evaluates to true.

DEF Syntax

This chapter contains information about the following topics:

- About Design Exchange Format Files on page 126
 - □ General Rules on page 126
 - Order of DEF Statements on page 127
- <u>DEF Statement Definitions</u> on page 128
 - □ Blockages on page 128
 - □ Bus Bit Characters on page 129
 - □ Components on page 130
 - □ <u>Design</u> on page 132
 - □ Die Area on page 133
 - □ <u>Divider Character</u> on page 133
 - □ Extensions on page 133
 - □ Fills on page 134
 - □ GCell Grid on page 134
 - □ Groups on page 136
 - ☐ History on page 137
 - □ Names Case Sensitive on page 137
 - □ Nets on page 138
 - Regular Wiring Statement on page 144
 - □ Pins on page 147
 - □ Pin Properties on page 155

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	Property Definitions on page 156
	Regions on page 159
	Rows on page 160
	Scan Chains on page 161
	Slots on page 168
	Special Nets on page 169
	Special Wiring Statement on page 173
	Technology on page 178
	Technology on page 178 Tracks on page 179
_	
_	Tracks on page 179

About Design Exchange Format Files

A Design Exchange Format (DEF) file contains the design-specific information of a circuit and is a representation of the design at any point during the layout process. The DEF file is an ASCII representation using the syntax conventions described in "Typographic and Syntax" Conventions" on page 10.

DEF conveys logical design data to, and physical design data from, place-and-route tools. Logical design data can include internal connectivity (represented by a netlist), grouping information, and physical constraints. Physical data includes placement locations and orientations, routing geometry data, and logical design changes for backannotation. Placeand-route tools also can read physical design data, for example, to perform ECO changes.

For standard-cell-based/ASIC flow tools, floorplanning is part of the design flow. You typically use the various floorplanning commands to interactively create a floorplan. This data then becomes part of the physical data output for the design using the ROWS, TRACKS, GCELLGRID, and DIEAREA statements. You also can manually enter this data into DEF to create the floorplan.

General Rules

Note the following information about creating DEF files:

DEF Syntax

- Lines in the DEF file are limited to 2,048 characters (extra characters are truncated on input).
- Net names and cell names also are limited to 2,048 characters.
- DEF statements end with a semicolon (;). You must leave a space before the semicolon.
- Each section can be specified only once. Sections end with END SECTION.
- You must define all objects before you reference them except for the + ORIGINAL argument in the NETS section.
- No regular expressions or wildcard characters are recognized except for (* pinName) in the SPECIALNETS section.

Order of DEF Statements

Standard DEF files can contain the following statements and sections. You must specify the statements and sections in the following order.

```
VERSION statement
NAMESCASESENSITIVE statement
DIVIDERCHAR statement
BUSBITCHARS statement
DESIGN statement
[ TECHNOLOGY statement ]
[ UNITS statement ]
[ HISTORY statement ] ...
[ PROPERTYDEFINITIONS section ]
[ DIEAREA statement ]
[ ROWS statement ] ...
[ TRACKS statement ] ...
[ GCELLGRID statement ] ...
[ VIAS statement ]
[ REGIONS statement ]
COMPONENTS section
[ PINS section ]
[ PINPROPERTIES section ]
[ BLOCKAGES section ]
[ SLOTS section ]
[ FILLS section ]
[ SPECIALNETS section ]
NETS section
[ SCANCHAINS section ]
[ GROUPS section ]
[ BEGINEXT section ] ...
END DESIGN statement
```

DEF Syntax

Note: You can include BEGINEXT sections at any point.

DEF Statement Definitions

The following definitions describe the syntax arguments for the statements and sections that make up a DEF file. The statements and sections are listed in alphabetical order, *not* in the order they must appear in a DEF file. For the correct order, see <u>Order of DEF Statements</u> on page 127.

Blockages

Defines placement and routing blockages in the design. You can define simple blockages (blockages specified for an area), or blockages that are associated with specific instances (components). You can only associate blockages with placed instances. If you move the instance, its blockage moves with it.

COMPONENT compName	Specifies a component with which to associate a blockage. Specify with LAYER layerName to create a routing blockage associated with a component. Specify with PLACEMENT to create a placement blockage associated with a component.
FILLS	Creates a blockage on the specified layer where metal fills cannot be placed.
LAYER layerName	Specifies the layer on which to create a blockage.
numBlockages	Specifies the number of blockages in the design.
PLACEMENT	Creates a placement blockage. You can create a simple placement blockage, or a placement blockage attached to a specific component.

DEF Syntax

PUSHDOWN	Specifies that the blockage was pushed down into the block from the top level of the design.
RECT pt pt	Specifies the coordinates of the blockage geometry. The coordinates you specify are absolute. If you associate a blockage with a component, the coordinates are not relative to the component's origin.
SLOTS	Creates a blockage on the specified layer where slots cannot be placed.

Example 4-1 Blockages Statement

The following example shows a BLOCKAGES section that defines eight blockages in the following order: two *metal2* routing blockages, a pushed down routing blockage, a routing blockage attached to component | i4, a floating placement blockage, a pushed down placement blockage, a placement blockage attached to component | i3, and a fill blockage.

```
BLOCKAGES 7 ;
     - LAYER metal1
          RECT ( -300 -310 ) ( 320 330 )
          RECT ( -150 -160 ) ( 170 180 ) ;
     - LAYER metal1 + PUSHDOWN
          RECT ( -150 -160 ) ( 170 180 ) ;
     - LAYER metal1 + COMPONENT | i4
         RECT ( -150 -160 ) ( 170 180 ) ;
     - PLACEMENT
          RECT ( -150 -160 ) ( 170 180 ) ;
     - PLACEMENT + PUSHDOWN
          RECT ( -150 -160 ) ( 170 180 ) ;
     - PLACEMENT + COMPONENT | i3
          RECT ( -150 -160 ) ( 170 180 ) ;
     - LAYER metal1 + FILLS
          RECT ( -160 -170 ) ( 180 190 ) ;
END BLOCKAGES
```

Bus Bit Characters

```
BUSBITCHARS "delimiterPair";
```

Specifies the pair of characters used to specify bus bits when DEF names are mapped to or from other databases. The characters must be enclosed in double quotation marks. For example:

```
BUSBITCHARS "()";
```

DEF Syntax

If one of the bus bit characters appears in a DEF name as a regular character, you must use a backslash (\) before the character to prevent the DEF reader from interpreting the character as a bus bit delimiter.

Components

```
COMPONENTS numComps ;
     [- compName modelName
          [ + EEQMASTER macroName]
         [+ SOURCE {NETLIST | DIST | USER | TIMING}]
         [+ FOREIGN foreignCellName pt orient]
          [+ {FIXED pt orient | COVER pt orient | PLACED pt orient
                UNPLACED ]
          [+ WEIGHT weight]
          [+ REGION regionName]
          [+ PROPERTY {propName propVal} ...]...
     ;] ...
END COMPONENTS
```

Defines design components, their location, and associated attributes.

compName mode 1Name Specifies the component name in the design, which is an instance of mode 1Name, the name of a model defined in the library. A mode 1Name must be specified with each compName.

COVER pt orient

Specifies that the component has a location and is a part of a cover macro. A COVER component cannot be moved by automatic tools or interactive commands. You must specify the component's location and its orientation.

EEQMASTER macroName Specifies that the component being defined should be electrically equivalent to the previously defined macroName.

FIXED pt orient

Specifies that the component has a location and cannot be moved by automatic tools, but can be moved using interactive commands. You must specify the component's location and orientation.

FOREIGN foreignCellName pt orient

The FOREIGN parameter is available if you want to interface to a foreign format such as GDSII. In LEF, a macro can be defined with FOREIGN cell references. The FOREIGN parameter in the DEF repeats the LEF specification for the component. The

DEF Syntax

FOREIGN parameter is ignored by DEF readers that use LEF for macro definitions.

Specifies the foreign (GDSII) structure name to use when placing an instance of the component. You must also specify the component origin (lower left corner when the component is in north orientation) offset from the foreign origin, and the orientation of the foreign cell when the component is in north orientation.

numComps

Specifies the number of components defined in the COMPONENTS section.

PLACED pt orient

Specifies that the component has a location, but can be moved using automatic layout tools. You must specify the component's location and orientation.

PROPERTY propName propVal

Specifies a numerical or string value for a component property defined in the PROPERTYDEFINITIONS statement. The propName you specify must match the propName listed in the PROPERTYDEFINITIONS statement.

REGION regionName

Specifies a region in which the component must lie. regionName specifies a region already defined in the REGIONS section. If the region is smaller than the bounding rectangle of the component itself, the DEF reader issues an error message and ignores the argument. If the region does not contain a legal location for the component, the component remains unplaced after the placement step.

SOURCE {NETLIST | DIST | USER | TIMING}

Specifies the source of the component.

Value: Specify one of the following:

DIST Component is a physical component (that is,

it only connects to power or ground nets), such as filler cells, well-taps, and decoupling

caps.

NETLIST Component is specified in the original netlist.

This is the default value, and is normally not

written out in the DEF file.

DEF Syntax

	TIMING	Component is a logical rather than physical change to the netlist, and is typically used as a buffer for a clock-tree, or to improve timing on long nets.
	USER	Component is generated by the user for some user-defined reason.
UNPLACED	Specifies that the	component does not have a location.
WEIGHT weight	Specifies the weight of the component., which determines whether or not automatic placement attempts to keep the component near the specified location. weight is only meaningful when the component is placed. All non-zero weights have the same effect during automatic placement. Default: 0	

Specifying Orientation

If a component has a location, you must specify its location and orientation. A component can have any of the following orientations:

Value	Definition	Value	Definition
N	North	FN	Flipped north
S	South	FS	Flipped south
W	West <	FW	Flipped west
E	East	FE	Flipped east

Components are always placed such that the lower left corner of the cell is the origin (0,0) after any orientation. When a component flips about the y axis, it flips about the component center. When a component rotates, the lower left corner of the bounding box of the component's sites remains at the same placement location.

Design

DESIGN designName ;

Specifies a name for the design. The DEF reader reports a warning if this name is different from that in the database. In case of a conflict, the just specified name overrides the old name.

DEF Syntax

Die Area

```
[DIEAREA pt pt ;]
```

Specifies the corner points of the bounding rectangle for the design. All objects must be defined within this rectangle. pt is a float number.

Divider Character

```
DIVIDERCHAR "character";
```

Specifies the character used to express hierarchy when DEF names are mapped to or from other databases. The character must be enclosed in double quotation marks. For example:

```
DIVIDERCHAR "/" ;
```

If the divider character appears in a DEF name as a regular character, you must use a backslash (\) before the character to prevent the DEF reader from interpreting the character as a hierarchy delimiter.

Extensions

```
[BEGINEXT "tag"
extensionText
ENDEXT]
```

Adds customized syntax to the DEF file that can be ignored by tools that do not use that syntax. You can also use extensions to add new syntax not yet supported by your version of LEF/DEF, if you are using version 5.1 or later. Add extensions as separate sections.

extensionText Defines the contents of the extension.

"tag" Identifies the extension block. You must enclose tag in quotes.

Example 4-2 Extension Statement

```
BEGINEXT "1VSI Signature 1.0"

CREATOR "company name"

DATE "timestamp"

REVISION "revision number"

ENDEXT
```

DEF Syntax

Fills

Defines the rectangluar shapes that represent metal fills in the design. Each fill is defined as an individual rectangle.

Specifies the layer on which to create the fill.

numFills

Specifies the number of LAYER statements in the FILLS statement, not the number of rectangles.

RECT pt pt

Specifies the lower left and upper right corner coordinates of the fill geometry.

Example 4-3 Fills Statement

The following example defines fills for layers MET1 and MET2.

```
FILLS 2 ;

- LAYER MET1

RECT (1000 2000) (1500 4000)

RECT (2000 2000) (2500 4000)

RECT (3000 2000) (3500 4000) ;

- LAYER MET2

RECT (1000 2000) (1500 4000)

RECT (1000 4500) (1500 6500)

RECT (1000 7000) (1500 9000)

RECT (1000 9500) (1500 11500) ;

END FILLS
```

GCell Grid

```
[GCELLGRID
     {X start DO numColumns+1 STEP space} ...
     {Y start DO numRows+1 STEP space ;} ...]
```

Defines the gcell grid for a standard cell-based design. Each GCELLGRID statement specifies a set of vertical (X) and horizontal (Y) lines, or tracks, that define the gcell grid.

DO numColumns+1 Specifies the number of columns in the grid.

DEF Syntax

DO numRows+1	Specifies the number of rows in the grid.
STEP space	Specifies the spacing between tracks.
X start, Y start	Specify the location of the first vertical (X) and first horizontal (Y) track.

GCell Grid Boundary Information

The boundary of the gcell grid is the rectangle formed by the extreme vertical and horizontal lines. The gcell grid partitions the routing portion of the design into rectangles, called gcells. The lower left corner of a gcell is the origin. The X size of a gcell is the distance between the upper and lower bounding vertical lines, and the Y size is the distance between the upper and lower bounding horizontal lines.

For example, the grid formed by the following two GCELLGRID statements creates gcells that are all the same size (100 x 200 in the following):

```
GCELLGRID X 1000 DO 101 STEP 100 ;
GCELLGRID Y 1000 DO 101 STEP 200 ;
```

A gcell grid in which all gcells are the same size is called a uniform gcell grid. Adding GCELLGRID statements can increase the granularity of the grid, and can also result in a nonuniform grid, in which gcells have different sizes.

For example, adding the following two statements to the above grid generates a nonuniform grid:

```
GCELLGRID X 3050 DO 61 STEP 100 ; GCELLGRID Y 5100 DO 61 STEP 200 ;
```

When a track segment is contained inside a gcell, the track segment belongs to that gcell. If a track segment is aligned on the boundary of a gcell, that segment belongs to the gcell only if it is aligned on the left or bottom edges of the gcell. Track segments aligned on the top or right edges of a gcell belong to the next gcell.

GCell Grid Restrictions

Every track segment must belong to a gcell, so gcell grids have the following restrictions:

- The X coordinate of the last vertical track must be less than, and not equal to, the X coordinate of the last vertical gcell line.
- The Y coordinate of the last horizontal track must be less than, and not equal to, the Y coordinate of the last horizontal gcell line.

DEF Syntax

Gcells grids also have the following restrictions:

- Each GCELLGRID statement must define two lines.
- Every gcell need not contain the vertex of a track grid. But, those that do must be at least as large in both directions as the default wire widths on all layers.

Missing GCell Grid Statements

Default cases occur when the GCELLGRID statements for the X direction, Y direction, or both, are missing. Then INITIALIZE FLOORPLAN automatically creates a gcell grid in the missing direction that

- Starts at the first track and covers the last track.
- Uses a gcell X or Y size set to 15 via-line spacings.
- Uses the via-line spacing from the layer that has the preferred direction the same as the direction of the missing GCELLGRID statement. If two or more layers have the same preferred direction, the smallest via-line spacing is used.

You select a gcell grid based on routing resources for the floorplan. Available tracks can be actual channels such as core channels or the channeled areas around I/O pads. They also can be quasichannels created by the underlying row pattern or the layout of pin rails in the components. Blocked tracks are unavailable for routing in a given direction because of component obstructions or pins.

Groups

```
[GROUPS numGroups ;
      [- groupName compNameRegExpr ...
      [+ REGION regionNam]
      [+ PROPERTY {propName propVal} ...] ...
;] ...
END GROUPS]
```

Defines groups in a design.

compNameRegExpr

Specifies the components that make up the group. Do not assign any component to more than one group. You can specify any of the following::

■ A component name, for example C3205

DEF Syntax

 A list of component names separated by spaces, for example, I01 I02 C3204 C3205

A regular expression for a set of components, for example, IO* and C320*

groupName

Specifies the name for a group of components.

numGroups

Specifies the number of groups defined in the GROUPS section.

PROPERTY propName propVal

Specifies a numerical or string value for a group property defined in the PROPERTYDEFINITIONS statement. The propName you specify must match the propName listed in the PROPERTYDEFINITIONS statement.

REGION regionName

Specifies a rectangular region in which the group must lie. regionName specifies a region previously defined in the REGIONS section. If region restrictions are specified in both COMPONENT and GROUP statements for the same component, the component restriction overrides the group restriction.

History

```
[HISTORY anyText ;] ...
```

Lists a historical record about the design. Each line indicates one record. Any text excluding a semicolon (;) can be included in <code>anyText</code>. The semicolon terminates the <code>HISTORY</code> statement. Linefeed and <code>Return</code> do not terminate the <code>HISTORY</code> statement. Multiple <code>HISTORY</code> lines can appear in a file.

Names Case Sensitive

```
NAMESCASESENSITIVE {OFF | ON} ;
```

Determines if DEF data is case sensitive. The NAMESCASESENSITIVE statement must be on the first noncommented line after the VERSION statement. The case sensitivity of the DEF data must match that of the LEF data used in the design.

DEF Syntax

Nets

```
NETS numNets ;
     [- { netName
            [ ( {compName pinName | PIN pinName} [ + SYNTHESIZED] ) ] ...
        | MUSTJOIN ( compName pinName ) }
        [+ SHIELDNET shieldNetName ] ...
        [+ VPIN vpinName [LAYER layerName] pt pt
            [PLACED pt orient | FIXED pt orient | COVER pt orient]] ...
        [ + SUBNET subnetName
            [ ( {compName pinName | PIN pinName | VPIN vpinName} ) ] ...
            [NONDEFAULTRULE rulename]
            [regularWiring] ...] ...
        [+ XTALK class]
        [ + NONDEFAULTRULE ruleName]
        [regularWiring] ...
        [+ SOURCE {DIST | NETLIST | TEST | TIMING | USER}]
        [+ FIXEDBUMP]
        [+ FREQUENCY frequency]
        [+ ORIGINAL netName]
        [+ USE {ANALOG | CLOCK | GROUND | POWER | RESET | SCAN | SIGNAL
                  | TIEOFF } ]
        [+ PATTERN {BALANCED | STEINER | TRUNK | WIREDLOGIC}]
        [+ ESTCAP wireCapacitance]
        [+ WEIGHT weight]
        [+ PROPERTY {propName propVal} ...] ...
     ;] ...
END NETS
```

Defines netlist connectivity for nets containing regular pins. The default design rules apply to these pins, and the regular routers route to these pins. The SPECIALNETS statement defines netlist connectivity for nets containing special pins.

Input arguments for a net can appear in the NETS section or the SPECIALNETS section. In case of conflicting values, the DEF reader uses the last value encountered. NETS and SPECIALNETS statements can appear more than once in a DEF file. If a particular net has mixed wiring or pins, specify the special wiring and pins first.

compName pinName	Specifies the name of a regular component pin on a net or a subnet. LEF MUSTJOIN pins, if any, are not included; only the "master pin" (the one without the MUSTJOIN statement) is included. If a subnet includes regular pins, the regular pins must be included in the parent net.
COVER pt orient	Specifies that the pin has a location and is a part of the cover

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macro. A COVER pin cannot be moved by automatic tools or by

DEF Syntax

interactive commands. You must specify the pin's location and orientation.

ESTCAP wireCapacitance

Specifies the estimated wire capacitance for the net. ESTCAP can be loaded with simulation data to generate net constraints for timing-driven layout.

FIXED pt orient

Specifies that the pin has a location and cannot be moved by automatic tools, but can be moved by interactive commands. You must specify the pin's location and orientation.

FIXEDBUMP

Indicates that the bump net cannot be reassigned to a different pin.

It is legal to have a pin without geometry to indicate a logical connection, and to have a net that connects that pin to two other instance pins that have geometry. Area I/Os have a logical pin that is connected to a bump and an input driver cell. The bump and driver cell have pin geometries (and, therefore, should be routed and extracted), but the logical pin is the external pin name without geometry (typically the Verilog pin name for the chip).

Because bump nets are usually routed with special routing, they also can be specified in the SPECIALNETS statement. If a net name appears in both the NETS and SPECIALNETS statements, the FIXEDBUMP keyword also should appear in both statements. However, the value only exists once within a given application's database for the net name.

Because DEF is often used incrementally, the last value read in is used. Therefore, in a typical DEF file, if the same net appears in both statements, the FIXEDBUMP keyword (or lack of it) in the NETS statement is the value that is used, because the NETS statement is defined after the SPECIALNETS statement.

For an example specifying the FIXEDBUMP keyword, see <u>"Fixed Bump"</u> on page 170.

FREQUENCY frequency

Specifies the frequency of the net, in hertz. The frequency value is used by the router to choose the correct number of via cuts required for a given net, and by validation tools to verify that the AC current density rules are met. For example, a net described

DEF Syntax

with + FREQUENCY 100 indicates the net has 100 rising and 100

falling transitions in 1 second.

Type: Float

LAYER *layerName*

Specifies the layer on which the virtual pin lies.

MUSTJOIN (compName pinName)

Specifes that the net is a mustioin. If a net is designated MUSTJOIN, its name is generated by the system. Only one net should connect to any set of mustjoin pins. Mustjoin pins for macros are defined in LEF. The only reason to specify a MUSTJOIN net in DEF (identified arbitrarily by one of its pins) is to specify prewiring for the MUSTJOIN connection.

Otherwise, nets are generated automatically where needed for mustjoin connections specified in the library. If the input file specifies that a mustjoin pin is connected to a net, the DEF reader connects the set of mustjoin pins to the same net. If the input file does not specify connections to any of the mustjoin pins, the DEF reader creates a local MUSTJOIN net.

netName

Specifies the name for the net. Each statement in the NETS section describes a single net. There are two ways of identifying the net: netName or MUSTJOIN. If the netName is given, a list of pins to connect to the net also can be specified. Each pin is identified by a component name and pin name pair (compName pinName) or as an I/O pin (PIN pinName). Parentheses ensure readability of output. The keyword MUSTJOIN cannot be used as a netName.

NONDEFAULTRULE ruleName

Specifies the LEF-defined nondefault rule to use when creating the net and wiring. When specified with SUBNET, names the nondefault rule to use when creating the subnet and its wiring.

numNets

Specifies the number of nets defined in the NETS section.

ORIGINAL netName

Specifies the original net partitioned to create multiple nets, including the net being defined.

PATTERN {BALANCED

STEINER | TRUNK | WIREDLOGIC}

Specifies the routing pattern used for the net.

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DEF Syntax

Default: STEINER

Value: Specify one of the following:

BALANCED Used to minimize skews in timing delays

for clock nets.

STEINER Used to minimize net length.

TRUNK Used to minimize delay for global nets.

WIREDLOGIC Used in ECL designs to connect ouput

and mustjoin pins before routing to the

remaining pins.

PIN pinName Specifies the name of an I/O pin on a net or a subnet.

PLACED pt orient Specifies that the pin has a location, but can be moved during

automatic layout. You must specify the pin's location and

orientation.

PROPERTY propName propVal

Specifies a numerical or string value for a net property defined in the PROPERTYDEFINITIONS statement. The propName you

specify must match the propName listed in the

PROPERTYDEFINITIONS statement.

regularWiring Specifies the regular physical wiring for the net or subnet. For

regular wiring syntax, see "Regular Wiring Statement" on

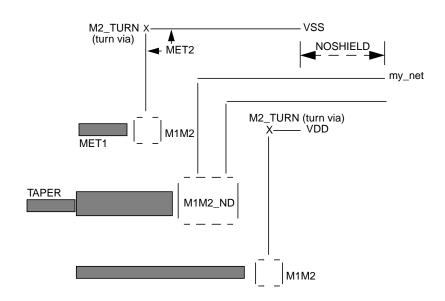
page 144.

SHIELDNET shieldNetName

Specifies the name of a special net that shields the regular net

DEF Syntax

being defined. A shield net for a regular net is defined eariler in the DEF file in the SPECIALNETS section.



SOURCE {DIST | NETLIST | TEST | TIMING | USER}

Specifies the source of the net. The value of this field is preserved when input to the DEF reader.

Value: Specify one of the following:

DIST Net is the result of adding physical components

(that is, components that only connect to power or ground nets), such as filler cells, well-taps, tiehigh and tie-low cells, and decoupling caps.

default value, and is not normally written out in

the DEF file.

TEST Net is part of a scanchain.

TIMING Net represents a logical rather than physical

change to netlist, and is used typically as a buffer for a clock-tree, or to improve timing on long nets.

USER Net is user defined.

SUBNET subnetName

Names and defines a subnet of the regular net netName. A subnet must have at least two pins. The subnet pins can be

DEF Syntax

virtual pins, regular pins, or a combination of virtual and regular

pins. A subnet pin cannot be a mustjoin pin.

SYNTHESIZED Specifies that the scan pin has been synthesized. After

synthesis, OUTPUT DEF marks the scan pin as SYNTHESIZED

and the net as TEST.

USE {ANALOG | CLOCK | GROUND | POWER | RESET | SCAN | SIGNAL | TIEOFF}

Specifies how the net is used. Value: Specify one of the following:

ANALOG Used as an analog signal net.

CLOCK Used as a clock net.

GROUND Used as a ground net.

POWER Used as a power net.

RESET Used as a reset net.

SCAN Used as a scan net.

SIGNAL Used as a digital signal net.

TIEOFF Used as a tie-high or tie-low net.

VPIN *vpinName pt pt* Specifies the name of a virtual pin, and its physical geometry.

Virtual pins can be used only in subnets. A SUBNET statement refers to virtual pins by the vpinName specified here. You must define each virtual pin in a + VPIN statement before you can list

it in a SUBNET statement.

WEIGHT weight Specifies the weight of the net. Automatic layout tools attempt to

shorten the lengths of nets with high weights. Do not specify a net weight larger than 10, or assign weights to more than 3

percent of the nets in a design.

Note: The net constraints method of controlling net length is

preferred over using net weights.

XTALK class Specifies the crosstalk class number for the net. If you specify

the default value (0), XTALK will not be written to the DEF file.

Default: 0
Type: Integer
Value: 0 to 200

DEF Syntax

Regular Wiring Statement

Specifies regular wiring for the net.

COVER Specifies that the wiring cannot be moved by either automatic

layout or interactive commands. If no wiring is specified for a particular net, the net is unrouted. If you specify COVER, you must

also specify layerName.

FIXED Specifies that the wiring cannot be moved by automatic layout,

but can be changed by interactive commands. If no wiring is specified for a particular net, the net is unrouted. If you specify

FIXED, you must also specify layerName.

1ayerName
Specifies the layer on which the wire lies. You must specify

layerName if you specify COVER, FIXED, ROUTED, or NEW. Specified layers must be routable, and reference to a cut layer

generates an error.

NEW layerName Indicates a new wire segment, that is, that there is no wire

segment between the last specified coordinate and the next coordinate. Also specifies the name of the layer on which the new wire lies. Noncontinuous paths can be defined in this

manner.

NOSHIELD Specifies that the last wide segment of the net is not shielded. If

the last segment is not shielded, and is tapered, specify TAPER

under the LAYER argument, instead of NOSHIELD.

ROUTED Specifies that the wiring can be moved by the automatic layout

tools. If no wiring is specified for a particular net, the net is unrouted. If you specify ROUTED, you must also specify

layerName.

TAPER Specifies that the next contiguous wire segment is created using

the default rule.

DEF Syntax

Specifies that the next contiguous wire segment is created using TAPERRULE ruleName the specified nondefault rule. $(xy)(x^*),(x^*)$ Specifies the coordinate of the form. For more information, see "Specifying Coordinates" on page 145 value Specifies how far the wire is extended at the specified point. If the value is omitted, wires extend half the routing width for the layer or rule. You can use the following extension values only on pins: 0 The WIREEXTENSION value for the layer or rule You can use extension values larger than half the width only before or after a via. Places the specified via at the last specified coordinate. The DEF viaName reader does not detect a mismatch between the current layer

Specifying Coordinates

To maximize compactness of the design files, the coordinates allow for the asterisk (*) convention. Here, (x *) indicates that the Y coordinate last specified in the wiring

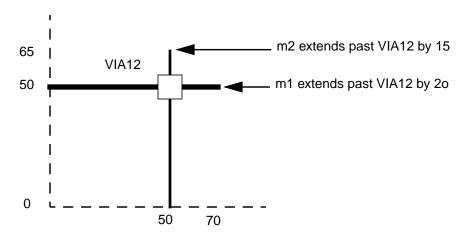
and a via.

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DEF Syntax

specification is used; (* $_Y$) indicates that the X coordinate last specified is used. Use (* * $_{Value}$) to specify a wire extension at a via.

ROUTED M1 (0 50) (50 * 20) VIA12 (* * 15) (* 0)



Each coordinate sequence defines a connected orthogonal path through the points. The first coordinate in a sequence must not have an * element.

Because nonorthogonal segments are not allowed, subsequent points in a connected sequence must create orthogonal paths. For example, the following sequence is a valid path:

```
( 100 200 ) ( 200 200 ) ( 200 500 )
```

The following sequence is an equivalent path:

```
( 100 200 ) ( 200 * ) ( * 500 )
```

The following sequence is not valid because it represents a nonorthogonal segment.

```
( 100 200 ) ( 300 500 )
```

Specifying Orientation

If you specify the pin's placement status, you must specify its location and orientation. A pin can have any of the following orientations:

Value	Definition	Value	Definition	
N	North	FN	Flipped north	
S	South	FS	Flipped south	
W	West	FW	Flipped west	

DEF Syntax

Value	Definition	Value	Definition
E	East	FE	Flipped east

Example 4-4 Nets Statements

The following example defines a virtual pin.

```
+ VPIN M7K.v2 LAYER MET2 ( -10 -10 ) ( 10 10 ) FIXED ( 10 10 )

+ SUBNET M7K.2 ( VPIN M7K.v2 ) ( /PREG_CTRL/I$73/A I )

NONDEFAULTRULE rule1

ROUTED MET2 ( 27060 341440 ) ( 26880 * ) ( * 213280 )

M1M2 ( 95040 * ) ( * 217600 ) ( 95280 * )

NEW MET1 ( 1920 124960 ) ( 87840 * )

COVER MET2 ( 27060 341440 ) ( 26880 * )
```

The following example defines a shielded net.

Pins

```
[PINS numPins ;
     [ [- pinName + NET netName]
        [+ SPECIAL]
         [+ DIRECTION {INPUT | OUTPUT | INOUT | FEEDTHRU}]
         [+ USE {SIGNAL | POWER | GROUND | CLOCK | TIEOFF | ANALOG | SCAN | RESET}]
        [+ ANTENNAPINPARTIALMETALAREA value [LAYER layerName]] ...
        [+ ANTENNAPINPARTIALMETALSIDEAREA value [LAYER layerName]] ...
        [+ ANTENNAPINPARTIALCUTAREA value [LAYER layerName]] ...
        [+ ANTENNAPINDIFFAREA value [LAYER layerName]] ...
        [+ ANTENNAMODEL {OXIDE1 | OXIDE2 | OXIDE3 | OXIDE4}] ...
        [+ ANTENNAPINGATEAREA value [LAYER layerName]] ...
         [+ ANTENNAPINMAXAREACAR value LAYER layerName] ...
        [ + ANTENNAPINMAXSIDEAREACAR value LAYER layerName]
        [+ ANTENNAPINMAXCUTCAR value LAYER layerName] ...
        [+ LAYER layerName pt pt]
        [+ COVER pt orient | FIXED pt orient | PLACED pt orient]
     ; ] ...
```

DEF Syntax

END PINS]

Defines external pins. Each pin definition assigns a pin name for the external pin and associates the pin name with a corresponding internal net name. The pin name and the net name can be the same.

For Silicon Ensemble, when a block (subchip) is to be created from the design using OUTPUT LEF BLOCK, the PINS statement includes a physical description of the pin and can include placement information. When the block is placed in the next level of the design, the existing wiring for the given net and any connected pin ports are promoted to a single pin port with the given pin name. If you use the PINMAP option of the OUTPUT LEF BLOCK command, all pin assignments in the PINS table are ignored.

When the design is a chip rather than a block, the PINS statement describes logical pins, without placement or physical information. Logical pins allow timing constraints to pass correctly between Silicon Ensemble and other tools.

ANTENNAMODEL {OXIDE1 | OXIDE2 | OXIDE3 | OXIDE4}

Specifies the oxide model for the pin. If you specify an ANTENNAMODEL statement, that value affects all ANTENNAGATEAREA and ANTENNA*CAR statements for the pin that follow it until you specify another ANTENNAMODEL statement. The ANTENNAMODEL statement does not affect ANTENNAPARTIAL*AREA and ANTENNADIFFAREA statements because they refer to the total metal, cut, or diffusion area connected to the pin, and do not vary with each oxide model. Default: OXIDE1, for a new PIN statement Value: OXIDE1 or OXIDE2.

Note: OXIDE1 and OXIDE2 are currently supported. If you specify OXIDE3 or OXIDE4, current tools parse and ignore them.

Because DEF is often used incrementally, if an ANTENNA statement occurs twice for the same oxide model, the last value specified is used.

Usually, you only need to specify a few ANTENNA values; however, for a block with six routing layers, it is possible to have six different ANTENNAPARTIAL*AREA values and six different ANTENNAPINDIFFAREA values per pin. It is also possible to have six different ANTENNAPINGATEAREA and ANTENNAPINMAX*CAR values for each oxide model on each pin.

Example 4-5 Antenna Model Statement

DEF Syntax

The following example describes the OXIDE1 and OXIDE2 models for pin clock1. Note that the ANTENNAPINDARTIALMETALAREA and ANTENNAPINDIFFAREA values are not affected by the oxide values.

ANTENNAPINDIFFAREA value [LAYER layerName]

Specifies the diffusion (diode) area to which the pin is connected on a layer. If you do not specify <code>layerName</code>, the value applies to all layers. This is not necessary for output pins.

Type: Integer

Value: Due to the maximum integer size, you can specify a value up to 2^{31} -1 in database units. In microns squared, this is 22^{31} -1 / DEFConvertFactor².

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations."

ANTENNAPINGATEAREA value [LAYER layerName]

Specifies the gate area to which the pin is connected on a layer. If you do not specify <code>layerName</code>, the value applies to all layers. This is not necessary for input pins.

Type: Integer

Value: Due to the maximum integer size, you can specify a value up to 2^{31} -1 in database units. In microns squared, this is 2^{31} -1 / DEFConvertFactor².

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

ANTENNAPINMAXAREACAR value LAYER layerName

For hierarchical process antenna effect calculation, specifies the

DEF Syntax

maximum cumulative antenna ratio value, using the metal area at or below the current pin layer, excluding the pin area itself. Use this to calculate the actual cumulative antenna ratio on the pin layer, or the layer above it.

Type: Integer

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

ANTENNAPINMAXCUTCAR value LAYER layerName

For hierarchical process antenna effect calculation, specifies the maximum cumulative antenna ratio value, using the cut area at or below the current pin layer, excluding the pin area itself. Use this to calculate the actual cumulative antenna ratio for the cuts above the pin layer.

Type: Integer

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations."

ANTENNAPINMAXSIDEAREACAR value LAYER layerName

For hierarchical process antenna effect calculation, specifies the maximum cumulative antenna ratio value, using the metal side wall area at or below the current pin layer, excluding the pin area itself. Use this to calculate the actual cumulative antenna ratio on the pin layer, or the layer above it.

Type: Integer

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

$\verb|ANTENNAPINPARTIALCUTAREA| value [LAYER cutLayerName]|$

Specifies the partial cut area above the current pin layer and inside the macro cell on a layer. If you do not specify <code>layerName</code>, the value applies to all layers. For hierarchical designs, only the cut layer above the I/O pin layer is needed for partial antenna ratio calculation.

Type: Integer

Value: Due to the maximum integer size, you can specify a value

DEF Syntax

up to 2^{31} -1 in database units. In microns squared, this is 2^{31} -1 / DEFConvertFactor².

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

ANTENNAPINPARTIALMETALAREA value [LAYER layerName]

Specifies the partial metal area connected directly to the I/O pin and the inside of the macro cell on a layer. If you do not specify <code>layerName</code>, the value applies to all layers. For hierarchical designs, only the same metal layer as the I/O pin, or the layer above it, is needed for partial antenna ratio calculation.

Type: Integer

Value: Due to the maximum integer size, you can specify a value up to 2^{31} -1 in database units. In microns squared, this is 2^{31} -1 / DEFConvertFactor².

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

ANTENNAPINPARTIALMETALSIDEAREA value [LAYER layerName]

Specifies the partial metal side wall area connected directly to the I/O pin and the inside of the macro cell on a layer. If you do not specify <code>layerName</code>, the value applies to all layers. For hierarchical designs, only the same metal layer as the I/O pin, or the layer above it, is needed for partial antenna ratio calculation.

Type: Integer

Value: Due to the maximum integer size, you can specify a value up to 2^{31} -1 in database units. In microns squared, this is 2^{31} -1 / DEFConvertFactor².

For more information on process antenna calculation, see Appendix D, "Calculating and Fixing Process Antenna Violations,"

COVER pt orient

Specifies the pin's location, orientation, and that it is a part of the cover macro. A COVER pin cannot be moved by automatic tools or by interactive commands. If you specify a placement status for a pin, you must also include a LAYER statement.

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DEF Syntax

DIRECTION {INPUT | OUTPUT | INOUT | FEEDTHRU}

Specifies the pin type.

Value: Specify one of the following:

INPUT Pin that accepts signals coming into the cell.

OUTPUT Pin that drives signals out of the cell.

INOUT Pin that can accept signals going either in or out

of the cell.

FEEDTHRU

FIXED pt orient Specifies the pin's location, orientation, and that it's location

cannot be moved by automatic tools, but can be moved by interactive commands. If you specify a placement status for a

pin, you must also include a LAYER statement.

LAYER layerName pt pt

Specifies the routing layer used for the pin, and the pin geometry on that layer. If you specify a placement status for a pin, you must

include a LAYER statement.

numPins Specifies the number of pins defined in the PINS section.

pinName + NET netName

Specifies the name for the external pin, and the corresponding

internal net (defined in NETS or SPECIALNETS statements).

PLACED pt orient Specifies the pin's location, orientation, and that it's location is

fixed, but can be moved during automatic layout. If you specify a placement status for a pin, you must also include a LAYER

statement.

SPECIAL Identifies the pin as a special pin. Regular routers do not route to

special pins. The special router routes special wiring to special

pins.

USE {ANALOG | CLOCK | GROUND | POWER | RESET | SCAN | SIGNAL | TIEOFF}

Specifies how the pin is used.

Default: SIGNAL

Value: Specify one of the following:

ANALOG Pin is used for analog connectivity.

CLOCK Pin is used for clock net connectivity.

DEF Syntax

GROUND	Pin is used for connectivity to the chip- level ground distribution network.
POWER	Pin is used for connectivity to the chip- level power distribution network.
RESET	Pin is used as reset pin.
SCAN	Pin is used as scan pin.
SIGNAL	Pin is used for regular net connectivity.
TIEOFF	Pin is used as tie-high or tie-low pin.

Extra Physical PIN(S) for One Logical PIN

In the design of place and route blocks, you sometimes want to add extra physical connection points to existing signal ports (usually to enable the signal to be accessed from two sides of the block). One pin has the same name as the net it is connected to. This pin is related to the pins specified in GCF for boundary conditions. Any other pins added to the net must use the following naming conventions.

For extra non-bus bit pin names, use the following syntax:

pinname.extraN N is a positive integer, incremented as the physical pins are added

For example:

```
PINS n;
- a + NET a ...;
- a.extral + NET a ...;
```

For extra bus bit pin names, use the following syntax:

```
basename.extraN[index]
```

basename is simple part of bus bit pin/net name N is a positive integer, incremented as the physical pins are added.

[index] identifies the specific bit of the bus

For example:

```
PINS n;
- a[0] + net a[0] ...;
- a.extral[0] + net a[0] ...;
```

DEF Syntax

Note: The brackets [] are the BUSBITCHARS as defined in the DEF header.

Specifying Orientation

If you specify the pin's placement status, you must specify its location and orientation. A pin can have any of the following orientations:

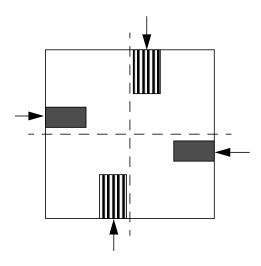
Value	Definiti	on	Value	Definition	
N	North		FN	Flipped north	
S	South		FS	Flipped south	
W	West		FW	Flipped west	
E	East		FE	Flipped east	

Example 4-6 Pins Statements

The following example describes a physical I/O pin.

```
# M1 width = 50, track spacing = 120
# M2 width = 60, track spacing = 140
DIEAREA ( -5000 -5000 ) ( 5000 5000 ) ;
TRACKS Y -4900 DO 72 STEP 140 LAYER M2 M1;
TRACKS X -4900 DO 84 STEP 120 LAYER M1 M2;
PINS 4;
# Pin on the left side of the block
- BUSA[0]+ NET BUSA[0] + DIRECTION INPUT
        + LAYER M1 ( -25 0 ) ( 25 165 ) # .5 M1 W + 1 M2 TRACK
        + PLACED ( -5000 2500 ) E ;
# Pin on the right side of the block
- BUSA[1] + NET BUSA[1] + DIRECTION INPUT
        + LAYER M1 ( -25 0 ) ( 25 165 ) \# .5 M1 W + 1 M2 TRACK
        + PLACED ( 5000 -2500 ) W ;
# Pin on the bottom side of the block
- BUSB[0] + NET BUSB[0] + DIRECTION INPUT
        + LAYER M2 ( -30~0 ) ( 30~150 ) \#~.5~M2~W~+~1~M1~TRACK
        + PLACED ( -2100 -5000 ) N ;
```

DEF Syntax



The following example shows how a logical I/O pin would appear in the DEF file. The pin is defined in Verilog for a chip-level design.

```
module chip (OUT, BUSA, BUSB);
    input [0:1] BUSA, BUSB;
    output OUT;
....
endmodule
```

The PINS section in DEF looks like this:

```
PINS 5;

- BUSA[0] + NET BUSA[0] + DIRECTION INPUT;

- BUSA[1] + NET BUSA[1] + DIRECTION INPUT;

- BUSB[0] + NET BUSB[0] + DIRECTION INPUT;

- BUSB[1] + NET BUSB[1] + DIRECTION INPUT;

- OUT + NET OUT + DIRECTION OUTPUT;

END PINS
```

Pin Properties

DEF Syntax

END PINPROPERTIES]

Defines pin properties in the design.

For Clock Tree Generator, properties are assigned to pins to indicate the clock root and to pass information about triggering edge, excluded pins, and TLF insertion delay to the clock router.

compName pinName Specifes a component pin. Component pins are identified by the

component name and pin name.

num Specifies the number of pins defined in the PINPROPERTIES

section.

PIN pinName Specifies an I/O pin.

PROPERTY propName propVal

Specifies a numerical or string value for a pin property defined in the PROPERTYDEFINITIONS statement. The propName you

specify must match the propName listed in the

PROPERTYDEFINITIONS statement.

Example 4-7 Pin Properties Statement

```
- CORE/g76 CKA + PROPERTY CLOCK "FALLING"
- compl A + PROPERTY CLOCK "EXCLUDED"
- rp/regB clk + PROPERTY CLOCK "INSERTION"
```

Property Definitions

Lists all properties used in the design. You must define properties in the PROPERTYDEFINITIONS statement before you can refer to them in other sections of the DEF file.

objectType Specifies the object type being defined. You can define

properties for the following object types:

COMPONENT

DEF Syntax

COMPONENTPIN

DESIGN

GROUP

NET

REGION

ROW

SPECIALNET

Specifies a unique property name for the object type. propName

Specifies the property type for the object type. You can specifiy propType

one of the following property types:

INTEGER

REAL

STRING

Limits real number and integer property values to a specified RANGE min max

range.

value | stringValue

Assigns a numeric value or a name to a DESIGN object.

Note: Assign values to properties for component pins in the PINPROPERTIES section. Assign values to other properties in the section of the LEF file that describes the object to which the property applies.

Example 4-8 Property Definitions Statements

The following examples shows a PROPERTYDEFINITIONS section that defines properties for the design, component pin, and component object types.

```
PROPERTYDEFINITIONS
    DESIGN versionNum INTEGER 12;
    DESIGN title STRING "Buffer";
    COMPONENTPIN count INTEGER RANGE 1 100;
    COMPONENT weight REAL RANGE 1.0 100.0;
    COMPONENT type STRING;
```

DEF Syntax

END PROPERTYDEFINITIONS

When using the ultra placer and ultra router, use the IGNOREOPTIMIZATION property keyword to specify nets that are not to be processed by any optimization. The property keyword IGNOREOPTIMIZATION needs to be defined in both the NETS and SPECIALNETS sections, as shown in the following example:

```
PROPERTYDEFINITIONS

...

NET IGNOREOPTIMIZATION STRING;

SPECIALNET IGNOREOPTIMIZATION STRING;

...

END PROPERTYDEFINITIONS

SPECIALNETS 200;

- sn1 + PROPERTY IGNOREOPTIMIZATION "";

- sn2 + PROPERTY IGNOREOPTIMIZATION "";

...

END SPECIALNETS

NETS 10000

- n1 + PROPERTY IGNOREOPTIMIZATION "";

...

END NETS
```

The ultra placer and ultra router applications require maximum switching frequency per net information to determine wire self heat and hot electron constraints on signals and clocks. The PROPERTY keyword is FREQUENCY, and needs to be defined in both the NETS and SPECIALNETS sections, as shown in the following example:

```
PROPERTYDEFINITIONS
...
NET FREQUENCY REAL;
SPECIALNET FREQUENCY REAL;
...
END PROPERTYDEFINITIONS

SPECIALNETS 200;
- sn1 + PROPERTY FREQUENCY 100.0;
- sn2 + PROPERTY FREQUENCY 200.0;
...
END SPECIALNETS

NETS 10000
- n1 + PROPERTY FREQUENCY 100.0;
...
END NETS
```

DEF Syntax

The DEF PROPERTYDEFINITIONS section can use the DESIGN object type to point to non-netlist files, such as timing and GCF files, or timing properties derived from GCF constructs. These GCF properties are reserved. Do not create, delete, or modify the properties. Do not delete the referenced files.

```
PROPERTYDEFINITIONS

DESIGN ACTIVITYFILE STRING "../DATA/VCD/mpeg_big.vcd";

NET AVGFREQUENCY REAL;

DESIGN GCFCONSTRAINTS_TIMESTAMP STRING "931884620";

DESIGN GCFCONSTRAINTS STRING "../DATA/GCF/mpeg.constr.gcf";

DESIGN GCFCLOCKROOTS STRING "PIN clk";

DESIGN GCFLIBRARY_TIMESTAMP STRING "932087472";

DESIGN GCFLIBRARY_STRING "../DATA/GCF/mpeg.tlf41.gcf";

END PROPERTYDEFINITIONS
```

Regions

```
[REGIONS numRegions ;
    [- regionName {pt pt} ...
        [+ TYPE {FENCE | GUIDE}]
        [+ PROPERTY {propName propVal} ...] ...
;] ...
END REGIONS]
```

Defines regions in the design. A region is a physical area to which you can assign a component or group.

numRegions

Specifies the number of regions defined in the design.

PROPERTY propName propVal

Specifies a numerical or string value for a region property defined in the PROPERTYDEFINITIONS statement. The *propName* you specify must match the *propName* listed in the PROPERTYDEFINITIONS statement.

regionName pt pt

Names and defines a region. You define a region as one or more rectangular areas specified by pairs of coordinate points.

For Silicon Ensemble, if a region name is not specified, the system automatically generates a region name based on the value of the environmental variable Region.Within.Prefix. The system names the region by appending a number to the Region.Within.Prefix string.

DEF Syntax

You can suppress region names by setting the environmental variable Output.DEF.Suppress.Region.Name to True.

TYPE {FENCE | GUIDE} Specifies the type of region.

Default: All instances assigned to the region are placed inside the region boundaries, and other cells are also placed inside the region.

Value: Specify one of the following:

All instances assigned to this type of region must FENCE

be exclusively placed inside the region

boundaries. No other instances are allowed inside

this region.

All instances assigned to this type of region GUIDE

should be placed inside this region; however, it is

a preference, not a hard constraint. Other

constraints, such as wire length and timing, can

override this preference.

Example 4-9 Regions Statement

```
REGIONS 1 ;
     - REGION1 ( 0 0 ) ( 1200 1200 )
        + PROPERTY REGIONORDER 1 ;
```

Rows

```
[ROW rowName rowType origX origY orient
      { DO numX BY 1 STEP spaceX 0 | DO 1 BY numY STEP 0 spaceY }
      [+ PROPERTY {propName propVal} ...] ...;] ...
```

Defines rows in the design.

DO numX BY 1 STEP spaceX 0 | DO 1 BY numY STEP 0 spaceY

Specifies a horizontal or vertical step pattern to create the row.

Specifies the number of columns in the numX

pattern.

Specifies the spacing between the columns. spaceX

Specifies the number of rows in the pattern. numY

Specifies the spacing between the rows. spaceY

orient Specifies the orientation of all sites in the row.

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DEF Syntax

Specifies the location in the design of the first site in the row. origX origY

PROPERTY propName propVal

Specifies a numerical or string value for a row property defined in the PROPERTY DEFINITIONS statement. The propName you specify must match the propName listed in the

PROPERTYDEFINITIONS statement.

For Silicon Ensemble, SITE statements in DEF files from versions earlier than 5.0 are read out as ROW statements. To output rows in SITE format, set the variable

Output.DEF.45.Format to TRUE.

Specifies the row name used to output the distance constraints rowName

between rows.

Specifies the site type to use for the row. For Silicon Ensemble, rowType

this is the same as the name specified by the TYPE option of the ADD ROW command. A standard cell site is a placement location for cells of a particular type. Sites are defined in the LEF file.

Scan Chains

```
[SCANCHAINS numScanChains ;
     [- chainName
        [+ PARTITION partitionName [MAXBITS maxbits]]
        [+ COMMONSCANPINS [ ( IN pin )] [( OUT pin ) ] ]
         + START {fixedInComp | PIN} [outPin]
        [+ FLOATING
           \{floatingComp [ (IN pin )] [ (OUT pin )] [ (BITS numBits )] \} ...]
        [ + ORDERED
           {fixedComp [ ( IN pin ) ] [ ( OUT pin ) ] [ ( BITS numBits ) ]} ...
         + STOP {fixedOutComp | PIN} [inPin] ]
     ;] ...
END SCANCHAINS 1
```

Defines scan chains in the design. Scan chains are a collection of cells that contain both scan-in and scan-out pins. These pins must be defined in the PIN statement of LEF file with USE SCAN.

Specifies the name of the scan chain. Each statement in the chainName SCANCHAINS section describes a single scan chain.

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DEF Syntax

COMMONSCANPINS [(IN pin)] [(OUT pin)]

Specifies the scan-in and scan-out pins for each component that does not have a scan-in and scan-out pin specified. You must specify either common scan-in and scan-out pins, or individual scan-in and scan-out pins for each component.

FLOATING {floatingComp[(IN pin)][(OUT pin)][(BITS numBits)]}

Specifies the floating list. You can have one or zero floating lists. If you specify a floating list, it must contain at least one component.

fixedComp
 Specifies the component name.
 (IN pin)
 Specifies the scan-in pin. If you do not specify a scan-in pin, the router uses the pin you specified for the common scan pins.

(OUT pin) Specifies the scan-out pin. If you do not specify a scan-out pin, the router uses the pin you specified for the common scan

pins.

BITS numBits Specifies the sequential bit length of any

chain element. This allows application tools that do not have library access to determine the sequential bit length contribution of any chain element to ensure the MAXBITS constraints are not violated for chains in a given partition. You can specify 0 to indicate when elements are

nonsequential.

Default: 1

Type: Integer

Note: Scan chain reordering commands can use floating components in any order to synthesize a scan chain. Floating components cannot be shared with other scan chains unless they are in the same PARTITION. Each component should only be used once in synthesizing a scan chain.

MAXBITS maxBits

When specified with chains that include the PARTITION keyword, sets the maximum bit length (flip-flop bit count) that the chain can grow to in the partition.

Default: 0, which means that tool-specific defaults apply

DEF Syntax

(probably the highest bit length of any chain in the partition).

Type: Integer

Value: Specify a value that is at least as large as the size of the

current chain.

numScanChains

Specifies the number of scan chains to synthesize.

ORDERED {fixedComp[(IN pin)] [(OUT pin)] [(BITS numBits)]} Specifies an ordered list. You can specify none or several ordered lists. If you specify an ordered list, you must specify at least two fixed components for each ordered list.

> fixedComp Specifies the component name.

Specifies the scan-in pin. If you do not (IN pin)

> specify a scan-in pin, the router uses the pin you specified for the common scan

pins.

(OUT pin) Specifies the scan-out pin. If you do not

> specify a scan-out pin, the router uses the pin you specified for the common scan

pins.

Specifies the sequential bit length of any BITS numBits

chain element. This allows application tools that do not have library access to determine the sequential bit length

contribution of any chain element to ensure the MAXBITS constraints are not violated for chains in a given partition. You can specify 0 to indicate when elements are

nonsequential. Default: 1

Type: Integer

Note: Scan chain reordering commands should synthesize these components in the same order that you specify them in the list. Ordered components cannot be shared with other scan chains unless they are in the same PARTITION. Each component should only be used once in synthesizing a scan chain.

PARTITION partitionName

Specifies a partition name. This statement allows reordering

DEF Syntax

tools to determine inter-chain compatibility for element swapping (both FLOATING elements and ORDERED elements). It associates each chain with a partition group, which determines their compatibility for repartitioning by swapping elements between them.

Chains with matching PARTITION names constitute a swap-compatible group. You can change the length of chains included in the same partition (up to the MAXBITS constraint on the chain), but you cannot eliminate chains or add new ones; the number of chains in the partition is always preserved.

If you do not specify the PARTITION keyword, chains are assumed to be in their own single partition, and reordering can be performed only within that chain.

Example 4-10 Partition Scanchain Statements

Chain chain1_clock1 is specified without a MAXBITS keyword. The maximum allowed bit length of the chain is assumed to be the sequential length of the longest chain in any clock1 partition.

```
SCANCHAINS 77 ;
    - chain1_clock1
    + PARTITION clock1
    + START block1/bsr_reg_0 Q
    + FLOATING
        block1/pgm_cgm_en_reg_reg ( IN SD ) ( OUT QZ )
        ...
        block1/start_reset_dd_reg ( IN SD ) ( OUT QZ )
        + STOP block1/start_reset_d_reg SD ;
```

Chain chain2_clock2 is specified with a PARTITION statement that associates it with clock2, and a maximum bit length of 1000. The third element statement in the FLOATING list is a scannable register bank that has a sequential bit length of 4. The ORDERED list element statements have total bit lengths of 1 each because the muxes are specified with a maximum bit length of 0.

```
- chain2_clock2
+ PARTITION clock2
MAXBITS 1000
+ START block1/current_state_reg_0_QZ
+ FLOATING
    block1/port2_phy_addr_reg_0_ ( IN SD ) ( OUT QZ )
    block1/port2_phy_addr_reg_4_ ( IN SD ) ( OUT QZ )
    block1/port3_intfc ( IN SD ) ( OUT MSB ) ( BITS 4 )
    ...
+ ORDERED
    block1/mux1 ( IN A ) ( OUT X ) ( BITS 0 )
    block1/ff1 ( IN SD ) ( OUT Q )
```

DEF Syntax

```
block1/mux2 ( IN A ) ( OUT X ) ( BITS 0 )
block1/ff2 ( IN SD ) ( OUT Q ) ;
```

Chain chain3_clock2 is also specified with a PARTITION statement that associates it with clock2. This means it is swap-compatible with chain2_clock2. The specified maximum bit length for this chain is 1200.

```
- chain3_clock2
+ PARTITION clock2
   MAXBITS 1200
+ START block1/LV_testpoint_0_Q_reg Q
+ FLOATING
   block1/LV_testpoint_0_Q_reg ( IN SE ) ( OUT Q )
   block1/tm_state_reg_1_ (IN SD ) ( OUT QZ )
```

Chain chain4_clock3 is specified with a PARTITION statement that associates it with clock3. The second element statement in the FLOATING list is a scannable register bank that has a sequential bit length of 8, and default pins. The ORDERED list element statements have total bit lengths of 2 each because the mux is specified with a maximum bit length of 0.

```
- chain4_clock3
+ PARTITION clock3
+ START block1/prescaler_IO/lfsr_reg1
+ FLOATING
    block1/dp1_timers
    block1/bus8 ( BITS 8 )
    ...
+ ORDERED
    block1/ds1/ff1 ( IN SD ) ( OUT Q )
    block1/ds1/mux1 ( IN B ) ( OUT Y ) ( BITS 0 )
    block1/ds1/ff2 ( IN SD ) ( OUT Q )
    ...
```

START { fixedInComp

```
| PIN} [outPin]
```

Specifies the start point of the scan chain. You must specify this point. The starting point can be either a component, fixedInComp, or an I/O pin, PIN. If you do not specify outPin, the router uses the pin specified for common scan pins.

Note: For Silicon Ensemble, if you do not specify outPin, TROUTE uses the pin you specified for the common scan pins. If the scan chain starts at an I/O pin, you must specify the I/O pin name as the outPin.

TROUTE allows different scan chains to share the start and stop scan components. However, TROUTE does not allow sharing of the other scan components by different scan chains.

DEF Syntax

STOP {fixedOutComp |

```
PIN} [inPin]
```

Specifies the end point of the scan chain. You must specify this point. The stop point can be either a component, fixedOutComp, or an I/O pin, PIN. If you do not specify inPin, the router uses the pin specified for common scan pins.

Note: For Silicon Ensemble, if you do not specify the inPin, TROUTE uses the pin you specified for the common scan pins. If the scan chain stops at an I/O pin, you must specify the I/O pin name as the inPin. The stop component can be shared with other scan chains.

Scan Chain Rules

Note the following when defining scan chains.

- Each scan-in/scan-out pin pair of adjacent components in the ordered list cannot have different owning nets (unless each net has SOURCE TEST tags or both are tie-off nets).
 - During execution of INPUT DEF, if the scan net owning the scan-in pin uses a different scan-out pin, a warning message appears suggesting that you use TROUTE DETACH to resolve the net conflict. If you do not run TROUTE DETACH, a problem message appears and the process stops.
- No net (except a tie-off net) can connect a scan-out pin of one component to the scan-in pin of a component in a different scan chain.
- TROUTE is the only tool that can attach or detach synthesized scan pins from or to the scan net. However, you can attach or detach synthesized pins by modifying a library model. You can also attach or detach random logic pins in the synthesized scan nets with incremental INPUT DEF or INPUT DEF ECO.
- For incremental DEF, if you have a COMPONENTS section and a SCANCHAINS section in the same DEF file, the COMPONENTS section must appear before the SCANCHAINS section. If the COMPONENTS section and SCANCHAINS section are in different DEF files, you must read the COMPONENTS section (using INPUT DEF) or load the database before reading the SCANCHAINS section.

Example 4-11 Scan Chain Statements

DEF Syntax

```
- N1 ( C3 SO + SYNTHESIZED ) ( C11 SI
                 + SYNTHESIZED ) ( AND1 A ) ;
END NETS
SCANCHAINS 2; #Specified before INPUT DEF
     + COMMONSCANPINS ( IN SI ) ( OUT SO )
     + START SIPAD OUT
     + FLOATING C1 C2 ( IN D ) ( OUT Q ) C3 C4 C5...CN
     + ORDERED A1 ( OUT Q ) A2 ( IN D ) ( OUT Q ) ...
              AM (ND)
     + ORDERED B1 B2 ... BL
     + STOP SOPAD IN ;
     - S2
END SCANCHAINS
SCANCHAINS 2; #Specified after OUTPUT DEF
     + START SIPAD OUT
     + FLOATING C1 ( IN SI ) ( OUT SO )
          C2 ( IN D ) ( OUT Q )
          C3 ( IN SI ( OUT SO ) ... CN ( IN SI ) ( OUT SO )
     + ORDERED A1 ( IN SI ) ( OUT Q )
          A2 ( IN D ) ( OUT Q ) ... AM ( IN D ) ( OUT SO )
     + ORDERED B1 ( IN SI ) ( OUT SO )
          B2 ( IN SI ) ( OUT SO ) ...
     + STOP SOPAD IN ;
     - S2 ...;
END SCANCHAINS
Nets 100; #Number of nets resulting after TROUT synthesis.
     - SCAN-1 ( C1 SO + SYNTHESIZED )
               ( C4 SI + SYNTHESIZED ) + SOURCE TEST ;
     - N1 ( C3 SO + SYNTHESIZED ) ( C11 SI
                    + SYNTHESIZED ) ( AND1 A ) ;
END NETS
SCANCHAINS 2; #Specified before INPUT DEF
     + COMMONSCANPINS ( IN SI ) ( OUT SO )
     + START SIPAD OUT
     + FLOATING C1 C2 ( IN D ) ( OUT Q ) C3 C4 C5...CN
     + ORDERED A1 ( OUT Q ) A2 ( IN D ) ( OUT Q ) ...
              AM ( N D )
     + ORDERED B1 B2 ... BL
     + STOP SOPAD IN ;
     - S2
```

DEF Syntax

Slots

Defines the rectangular shapes that form the slotting of the wires in the design. Each slot is defined as an individual rectangle.

LAYER layerName	Specifies the layer on which to create slots.
numSlots	Specifies the number of LAYER statements in the SLOTS statement, <i>not</i> the number of rectangles.
RECT pt pt	Specifies the lower left and upper right corner coordinates of the slot geometry.

Example 4-12 Slots Statement

The following example defines slots for layers MET1 and MET2.

```
SLOTS 2 ;

- LAYER MET1

RECT (1000 2000) (1500 4000)

RECT (2000 2000) (2500 4000)

RECT (3000 2000) (3500 4000) ;

- LAYER MET2

RECT (1000 2000) (1500 4000)
```

DEF Syntax

```
RECT (1000 4500) (1500 6500)

RECT (1000 7000) (1500 9000)

RECT (1000 9500) (1500 11500) ;

END SLOTS
```

Special Nets

```
[SPECIALNETS numNets ;
    [- netName [ ( compNameRegExpr pinName [+ SYNTHESIZED] ) ] ...
    [+ VOLTAGE volts]
    [specialWiring] ...
    [+ SOURCE {DIST | NETLIST | TIMING | USER}]
    [+ FIXEDBUMP]
    [+ ORIGINAL netName]
    [+ USE {ANALOG | CLOCK | GROUND | POWER | RESET | SCAN | SIGNAL | TIEOFF}]
    [+ PATTERN {BALANCED | STEINER | TRUNK | WIREDLOGIC}]
    [+ ESTCAP wireCapacitance]
    [+ WEIGHT weight]
    [+ PROPERTY {propName propVal} ...] ...
;] ...
END SPECIALNETS]
```

Defines netlist connectivity for nets containing special pins. Each specification in the SPECIALNETS statement describes a single net, identified by *netName* and the special pins on the net. These pins are identified by their pin names and corresponding components.

Input parameters for a net can appear in the NETS section or the SPECIALNETS section. In case of conflicting values for an argument, the DEF reader uses the last value encountered for the argument. NETS and SPECIALNETS statements can appear more than once in a DEF file. If a particular net has mixed wiring or pins, specify the special wiring and pins first.

You can also specify the netlist in the COMPONENTS statement. If the netlist is specified in both NETS and COMPONENTS statements, and if the specifications are not consistent, an error message appears. On output, the writer outputs the netlist in either format, depending on the command arguments of the output command.

compNameRegExpr pinName

Specifies the name of a special pin on the net and its corresponding component. You can use a regular expression to specify a set of component names. During evaluation of the regular expression, components that match the expression but do not have a pin named *pinName* are ignored.

ESTCAP wireCapacitance

Specifies the estimated wire capacitance for the net. ESTCAP

DEF Syntax

can be loaded with simulation data to generate net constraints for timing-driven layout.

FIXEDBUMP

Indicates that the bump net cannot be reassigned to a different pin.

It is legal to have a pin without geometry to indicate a logical connection and to have a net that connects that pin to two other instance pins that have geometry. Area I/Os have a logical pin that is connected to a bump and an input driver cell. The bump and driver cell have pin geometries (and, therefore, should be routed and extracted), but the logical pin is the external pin name without geometry (typically the Verilog pin name for the chip).

Bump nets also can be specified in the NETS statement. If a net name appears in both the NETS and SPECIALNETS statements, the FIXEDBUMP keyword also should appear in both statements. However, the value only exists once within a given application's database for the net name.

Because DEF is often used incrementally, the last value read in is used. Therefore, in a typical DEF file, if the same net appears in both statements, the FIXEDBUMP keyword (or lack of it) in the NETS statement is the value that is used because the NETS statement is defined after the SPECIALNETS statement.

Example 4-13 Fixed Bump

The following example describes a logical pin that is connected to a bump and an input driver cell. The I/O driver cell and bump cells are specified in the COMPONENTS statement. Bump cells are usually placed with + COVER placement status so they cannot be moved manually by mistake.

```
COMPONENTS 200
  - driver1 drivercell + PLACED ( 100 100 ) N;
...
  - bumpa1 bumpcell + COVER ( 100 100 ) N;
  - bumpa2 bumpcell + COVER ( 200 100 ) N;
```

The pin is assigned in the PIN statment.

```
PINS 100
- n1 + NET n1 + SPECIAL + DIRECTION INPUT;
- n2 + NET n2 + SPECIAL + DIRECTION INPUT;
```

DEF Syntax

In the SPECIALNETS statement, the net n1 is assigned to bumpa1 and cannot be reassigned. Note that another net n2 is assigned to bumpa2; however, I/O optimization commands are allowed to reassign bumpa2 to a different net.

SPECIALNETS 100

- n1 (driver1 in) (bumpa1 bumpin) + FIXEDBUMP ;

- n2 (driver2 in) (bumpa2 bumpin) ;

netName

Specifies the name of the net.

ORIGINAL netName

Specifies the original net partitioned to create multiple nets,

including the current net.

PATTERN {BALANCED

STEINER | TRUNK | WIREDLOGIC}

Specifies the routing pattern used for the net.

Default: STEINER

Value: Specify one of the following:

BALANCED Used to minimize skews in timing delays

for clock nets.

STEINER Used to minimize net length.

TRUNK Used to minimize delay for global nets.

WIREDLOGIC Used in ECL designs to connect output

and mustioin pins before routing to the

remaining pins.

PROPERTY propName propVal

Specifies a numerical or string value for a net property defined in the PROPERTYDEFINITIONS statement. The propName you

specify must match the propName listed in the

PROPERTYDEFINITIONS statement.

specialWiring

Specifies the special wiring for the net. For syntax information,

see Special Wiring Statement on page 173.

SOURCE {DIST | NETLIST | TIMING | USER}

Specifies how the net is created. The value of this field is preserved when input to the DEF reader.

DIST

Net is the result of adding physical components (that is, components that only connect to power or ground nets), such as filler cells, well-taps, tie-high and tie-low cells, and decoupling caps.

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DEF Syntax

default value, and is not normally written out in

the DEF file.

TEST Net is part of a scanchain.

TIMING Net represents a logical rather than physical

change to netlist, and is used typically as a buffer for a clock-tree, or to improve timing on long nets.

USER Net is user defined.

SYNTHESIZED Specifies that the scan pin is synthesized. After synthesis,

OUTPUT DEF marks the scan pin as SYNTHESIZED and the net

as TEST.

USE {ANALOG | CLOCK | GROUND | POWER | RESET | SCAN | SIGNAL | TIEOFF}

Specifies how the net is used.

Value: Specify one of the following:

ANALOG Used as an analog signal net.

CLOCK Used as a clock net.

GROUND Used as a ground net.

POWER Used as a power net.

RESET Used as a reset net.

SCAN Used as a scan net.

SIGNAL Used as a digital signal net.

TIEOFF Used as a tie-high or tie-low net.

VOLTAGE volts Specifies the voltage for the net as an integer in units of .001

volts. For example, 1.5 V is equal to 1500 in DEF.

WEIGHT weight Specifies the weight of the net. Automatic layout tools attempt to

shorten the lengths of nets with high weights. Do not specify a net weight larger than 10, or assign weights to more than 3

percent of the nets in a design.

Note: The net constraints method of controlling net length is

preferred over using net weights.

DEF Syntax

Special Wiring Statement

Defines the wiring for both routed and shielded nets.

COVER

Specifies that the wiring cannot be moved by either automatic layout or interactive commands. If no wiring is specified for a particular net, the net is unrouted. If you specify COVER, you must also specify layerName width.

DO numX BY numY STEP stepX stepY

Creates an array of power vias of the via specified with viaName.

Specify the following information:

numX numY Specifies the number of vias in the x and y directions. Do not specify 0 as a value.

Type: Integer

stepX stepY Specifies the step distance in the x and y

directions, in DEF distance database units.

Type: Integer

Example 4-14 Via Arrays

The following example specifies arrays of via VIAGEN21_2 on *metal1* and *metal2*.

```
SPECIALNETS 2 ;
-vdd ( * vdd )
+ ROUTED metall 150 ( 100 100 ) ( 200 * )
NEW metall 0 ( 200 100 ) VIAGEN21_2 DO 10 BY 20 STEP 10000 20000
NEW metal2 0 (-900 -30 ) VIAGEN21_2 DO 1000 BY 1 STEP 5000 0
```

DEF Syntax

As with any other VIA statement, the DO statement does not change the previous coordinate. Therefore, the following statement creates a metal1 wire of width 50 from (200 100) to (200 200) along with the via array that starts at (200 100).

NEW metal1 50 (200 100) VIAGEN21_2 DO 10 BY 20 STEP 1000 2000 (200 200)

FIXED

Specifies that the wiring cannot be moved by automatic layout, but can be changed by interactive commands. If no wiring is specified for a particular net, the net is unrouted. If you specify FIXED, you must also specify layerName width.

layerName width

Sets the width for wires on the specified layer. You must specify $layerName\ width$ if you specify COVER, FIXED, ROUTED, or NEW. Specified layers must be routable, and reference to a cut layer generates an error.

When a via is placed in special wiring, the previously established width is used for the wiring in the new layer. To change the width, a new path must be specified as follows: NEW layerName width.

Note: Wire width is stored as a half-width in the database. The width value is divided by 2 and truncated. Therefore, wire widths that are specified as odd integers in database precision units are rounded down to the next even integer before being written to the database.

NEW layerName width

Indicates a new wire segment, that is, that there is no wire segment between the last specified coordinate and the next coordinate. Also specifies the name of the layer on which the new wire lies, and the width for the wire. Noncontinuous paths can be defined in this manner.

ROUTED

Specifies that the wiring can be moved by automatic layout tools. If no wiring is specified for a particular net, the net is unrouted. If you specify ROUTED, you must also specify layerName width.

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DEF Syntax

SHAPE

Specifies a wire with special connection requirements because of its shape. This applies to vias as well as wires.

Value: Specify one of the following:

RING Used as ring, target for connection

PADRING Connects padrings

BLOCKRING Connects rings around the blocks

STRIPE Used as stripe

FOLLOWPIN Created by FOLLOWPIN

IOWIRE Connects I/O to target

COREWIRE Connects end points of FOLLOWPIN to

target

BLOCKWIRE Connects block pin to target

BLOCKAGEWIRE Created by ADD BLOCKAGE

FILLWIRE Connects metal fills to power and ground.

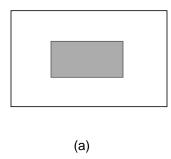
Represents fill wire that is connected to

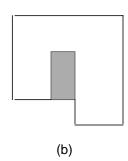
special net

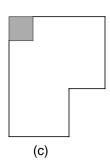
DRCFILL Used as a fill shape to correct DRC errors,

such as SPACING, MINENCLOSEDAREA, or MINSTEP violations on wires and pins of the same net (see Figure 4-1 on page 175.)

Figure 4-1







Examples of fill inside (a) a MINENCLOSEDAREA violation, (b) a SPACING violation, and (c) a MINSTEP violation.

DEF Syntax

SHIELD shieldNetName

Specifies the name of a regular net to be shielded by the special net being defined.

After describing shielded routing for a net, use +ROUTED to return to the routing of the special net being defined.

```
(x y) \{(x *) ( * y )\}
```

Specifies the coordinate of the form. For more information, see <u>"Specifying Coordinates"</u> on page 176

viaName

Specifies the name of the via to place at the last specified coordinate. The DEF reader does not detect a mismatch between the current layer and a via.

Specifying Coordinates

To maximize compactness of the design files, the coordinates allow for the asterisk (*) convention. For example, (x *) indicates that the Y coordinate last specified in the wiring specification is used; (* y) indicates that the X coordinate last specified is used.

Each coordinate sequence defines a connected orthogonal path through the points. The first coordinate in a sequence must not have an * element.

Because nonorthogonal segments are not allowed, subsequent points in a connected sequence must create orthogonal paths. For example, the following sequence is a valid path:

```
( 100 200 ) ( 200 200 ) ( 200 500 )
```

The following sequence is an equivalent path:

```
( 100 200 ) ( 200 * ) ( * 500 )
```

The following sequence is not valid because it represents a nonorthogonal segment.

```
( 100 200 ) ( 300 500 )
```

Special Pins and Wiring

Pins that appear in the SPECIALNETS statement are special pins. The regular routers do not route to these pins. The special router routes special wiring to special pins. If you use a component-based format to input the connectivity for the design, special pins to be routed by the special router also must be specified in the SPECIALNETS statement, because pins included in the COMPONENTS statement are considered regular.

DEF Syntax

For Silicon Ensemble, ADD WIRE creates regular routing for DEF output if the width is default, and no antennae are created. Similarly, ADD WIRE creates special routing for DEF output for nondefault widths and where antennae are created.

The following example inputs connectivity in a component-based format, specifies VDD and VSS pins as special pins, and marks VDD and VSS nets for special routing:

```
COMPONENTS 3;

- C1 AND N1 N2 N3; - C2 AND N4 N5 N6;

- C3 OR N3 N6 N7;

END COMPONENTS

SPECIALNETS 2;

- VDD ( * VDD ) + WIDTH M1 5;

- VSS ( * VSS );

END SPECIALNETS
```

Changing Net Representation

For Silicon Ensemble, you can change regular nets appearing in the NETS statement to special with the following command:

```
CHANGE NET netID REPRESENTATION SPECIAL
```

Changing the net does not change pin type. Wires, vias, and pins in the net remain regular. In some cases, verification reports problems such as this one:

```
Pin in net has no used library port
```

because nets that were connected by regular routing have been connected by special routing. Once INPUT DEF reads a DEF file, regular pins cannot be changed to special, and vice versa.

To change regular wiring to special wiring so you can interactively route the net, use CHANGE NET REPRESENTATION and do the following:

- Ensure that all wire widths in the net are special wire widths.
- Ensure that all vias are defined in the Via Rule section of the LEF file (defines vias for special wiring) or the Via Rule Generate section of the LEF file.

If you want to change the net representation from special to regular so that the automatic routers route the net, use CHANGE NET REPRESENTATION and do the following:

■ Ensure that all wires in the net are the default or nondefault width for regular wiring. If not, the conversion does not occur.

DEF Syntax

■ Ensure that the vias in the net are defined in the Via section of the LEF file (defines vias for the default regular wiring) and the Nondefault section of the LEF file (defines vias for all regular wiring except the default wiring). If not, the vias are missing after the conversion.

Shielded Routing

If, in a non-routed design, a net has + SHIELDNET attributes, the router adds shielded routing to this net. + NOSHIELD indicates the last wide segment of the net is not shielded. If the last segment is not shielded and is tapered, use the + TAPER keyword instead of + NOSHIELD. For example:

```
+ SHIELDNET VSS  # both sides will be shielded with VSS
+ SHIELDNET VDD  # one side will be shielded with VDD and
+ SHIELDNET VSS  # one side will be shielded with VSS
```

After you add shielded routing to a special net, it has the following syntax:

```
+ SHIELD regularNetName
MET2 regularWidth ( x y )
```

A shield net specified for a regular net should be defined earlier in the DEF file in the SPECIALNETS section. After describing shielded routing for a net, use + ROUTED to return to the routing of the current special net.

For example:

Technology

```
[TECHNOLOGY technologyName;]
```

Specifies a technology name for the design in the database. In case of a conflict, the previous name remains in effect.

DEF Syntax

Tracks

```
[TRACKS
  [{X | Y} start DO numtracks STEP space
      [LAYER layerName] ...
;] ...]
```

Defines the routing grid for a standard cell-based design. Typically, the routing grid is generated when the floorplan is initialized. The first track is located at an offset from the placement grid set by the OFFSET value for the layer in the LEF file. The track spacing is the PITCH value for the layer defined in LEF.

DO numTracks	Specifies the number of tracks to create for the grid. You cannot specify 0 $numtracks$.
LAYER layerName	Specifies the routing layer used for the tracks. You can specify more than one layer.
STEP space	Specifies the spacing between the tracks.
{X Y} start	Specifies the location and direction of the first track defined. x indicates vertical lines; y indicates horizontal lines. $start$ is the x or y coordinate of the first line. For example, y 3000 creates a set of vertical lines, with the first line going through (3000 0).

Units

```
[UNITS DISTANCE MICRONS DEFconvertFactor ;]
```

Specifies the convert factor used to convert DEF distance units into LEF distance units.

LEF only supports values of 100, 200, 1000, and 2000 for the LEF convert factor. The following table illustrates the conversion of LEF distance units into database units:

LEFconvertFactor	LEF	Database Units
100	1 micron	100
200	1 micron	200
1000	1 micron	1000
2000	1 micron	2000

For the Ultra Placer, the Ultra Router, and the Preview floorplanner, the DEF convert factor must be the same as the LEF convert factor.

DEF Syntax

The following table shows the valid pairings of the LEF convert factor and the corresponding DEF convert factor when the Ultra Placer and the Ultra Router are not used:

LEF Convert Factor	DEF Convert Factor
100	100
200	100
200	200
1000	100
1000	1000
2000	100
2000	2000

Any other values or combinations of the LEF convert factor and DEF convert factor are not supported in the UNITS DISTANCE MICRONS statement.

An incremental DEF should have the same value as a previous DEF. An error message warns you if an incremental DEF has a different value than what is recorded in the database.

Using DEF Units

The following table shows examples of how DEF units are used:

Units	DEF Units	DEF Value Example	Real Value
Time	.001 nanosecond	1500	1.5 nanoseconds
Capacitance	.000001 picofarad	1,500,000	1.5 picofarads
Resistance	.0001 ohm	15,000	1.5 ohms
Power	.0001 milliwatt	15,000	1.5 milliwatts
Current	.0001 milliamp	15,000	1.5 milliamps
Voltage	.001 volt	1500	1.5 volts

The DEF reader assumes divisor factors such that DEF data is given in the database units shown below.

Unit	Database Precision
1 nanosecond	= 1000 DBUs

DEF Syntax

Unit	Database Precision
1 picofarad	= 1,000,000 DBUs
1 ohm	= 10,000 DBUs
1 milliwatt	= 10,000 DBUs
1 milliampere	= 10,000 DBUs
1 volt	= 1000 DBUs

Version

```
VERSION versionNumber ;
```

Specifies which version of the DEF syntax is being used.

Vias

Lists the names and geometry definitions of all generated vias in the design.

PATTERNNAME patternName

Specfies the name of the pattern that encodes the cut pattern of the via. You can select either bitmapped or compressed for the pattern naming convention with the environmental variable Synthesis.ViaName.Convention. With the bitmapped convention, the upper limit is 64 cuts. With the compressed via convention, there is no upper limit for the via cut number. The compressed naming convention is recommended because it creates much shorter pattern names. The bitmapped naming convention is retained for compatibility with versions 4.3 and earlier. For more information, see "Compressed Via Pattern Encoding Convention" on page 202.

numVias

Specifies the number of vias listed in the VIA statement.

DEF Syntax

RECT layerName pt pt

Defines the via geometry for the specified layer . The points are specified with respect to the via origin. In most cases, the via origin is the center of the via bounding box. All geometries for the via, including the cut layers, are output by the DEF writer.

viaName

Specifies the via name. Via names are generated by appending a number after the rule name. Vias are numbered in the order in which they are created.

A

Examples

This appendix contains information about the following topics.

- LEF on page 183
- DEF on page 193
- Scan Chain Synthesis Example on page 198

LEF

```
# DEMO4 CHIP - 1280 ARRAY
NAMESCASESENSITIVE ON
    &alias &&area = (73600,74400) (238240,236400) &endalias
    &alias &&core = (85080,85500) (226760,224700) &endalias
    &alias &&m2stripes = sroute stripe net vss net vdd layer m2
        width
        320 count 2 pattern 87900 4200 218100
        area &&area core &&core &endalias
    &alias &&m3stripes = sroute stripe net vss net vdd layer m3
        width
        600 count 2 pattern 89840 6720 217520
        area &&area core &&core &endalias
    &alias &&powerfollowpins = sroute follow net vss net vdd layer
        ml width 560
        area &&area core &&core &endalias
    &alias &&powerrepair = sroute repair net vss net vdd area
        &&area core &&core &endalias
# PLACEMENT SITE SECTION
SITE CORE1 SIZE 67.2 BY 6 ; # GCD of all Y sizes of Macros END
    CORE1
SITE IOX SIZE 37.8 BY 444; \# 151.2 / 4 = 37.8, 4 sites per pad END IOX
SITE IOY SIZE 436.8 BY 30 ; \# 150 / 5 = 30 , 5 sites per pad END IOY
SITE SOUAREBLOCK SIZE 268.8 BY 252; END SOUAREBLOCK
SITE I2BLOCK SIZE 672 BY 504; END I2BLOCK
SITE LBLOCK SIZE 201.6 BY 168; END LBLOCK
SITE CORNER SIZE 436.8 BY 444; END CORNER
```

Examples

```
LAYER POLYS TYPE MASTERSLICE; END POLYS
LAYER PW TYPE MASTERSLICE; END PW
LAYER NW TYPE MASTERSLICE; END NW
LAYER PD TYPE MASTERSLICE ; END PD
LAYER ND TYPE MASTERSLICE; END ND
LAYER CUT01 TYPE CUT ; END CUT01
LAYER M1 TYPE ROUTING; DIRECTION VERTICAL; PITCH 5.6; WIDTH2.6;
    SPACING 1.5; END M1
LAYER CUT12 TYPE CUT ; END CUT12
LAYER M2 TYPE ROUTING ; DIRECTION HORIZONTAL ; PITCH 6.0 ;
    WIDTH 3.2 ; SPACING 1.6 ; END M2
LAYER CUT23 TYPE CUT ; END CUT23
LAYER M3 TYPE ROUTING; DIRECTION VERTICAL; PITCH 5.6; WIDTH 3.6;
    SPACING 1.6; END M3
LAYER OVERLAP TYPE OVERLAP; END OVERLAP
VIA C2PW DEFAULT LAYER PW; RECT -2.0 -2.0 2.0 2.0;
    LAYER CUT01 ; RECT -0.6 -0.6 0.6 0.6 ;
    LAYER M1 ; RECT -2.0 -2.0 2.0 2.0 ; END C2PW
VIA C2NW DEFAULT LAYER NW; RECT -2.0 -2.0 2.0 2.0;
    LAYER CUT01 ; RECT -0.6 -0.6 0.6 0.6 ;
    LAYER M1; RECT -2.0 -2.0 2.0 2.0; END C2NW
VIA C2PD DEFAULT LAYER PD ; RECT -2.0 -2.0 2.0 2.0 ;
    LAYER CUT01 ; RECT -0.6 -0.6 0.6 0.6 ;
    LAYER M1 ; RECT -2.0 -2.0 2.0 2.0 ; END C2PD
VIA C2ND DEFAULT LAYER ND ; RECT -2.0 -2.0 2.0 2.0 ;
    LAYER CUT01 ; RECT -0.6 -0.6 0.6 0.6 ;
    LAYER M1 ; RECT -2.0 -2.0 2.0 2.0 ; END C2ND
VIA C2POLY DEFAULT LAYER POLYS ; RECT -2.0 -2.0 2.0 2.0 ;
    LAYER CUT01 ; RECT -0.6 -0.6 0.6 0.6 ;
    LAYER M1 ; RECT -2.0 -2.0 2.0 2.0 ; END C2POLY
VIA VIA12 DEFAULT LAYER M1 ; RECT -2.0 -2.0 2.0 2.0 ;
    LAYER CUT12 ; RECT -0.7 -0.7 0.7 0.7 ;
    LAYER M2 ; RECT -2.0 -2.0 2.0 2.0 ; END VIA12
VIA VIA23 DEFAULT LAYER M3; RECT -2.0 -2.0 2.0 2.0;
    LAYER CUT23 ; RECT -0.8 -0.8 0.8 0.8 ;
    LAYER M2; RECT -2.0 -2.0 2.0 2.0; END VIA23
    SPACING SAMENET CUT01 CUT12 4.0 ;
    SAMENET CUT12 CUT23 4.0 ; END SPACING
VIARULE TURN1 GENERATE LAYER M1 ; DIRECTION VERTICAL ;
    LAYER M1; DIRECTION HORIZONTAL; END TURN1
VIARULE TURN2 GENERATE LAYER M2 ; DIRECTION VERTICAL ;
    LAYER M2; DIRECTION HORIZONTAL; END TURN2
VIARULE TURN3 GENERATE LAYER M3 ; DIRECTION VERTICAL ;
    LAYER M3; DIRECTION HORIZONTAL; END TURN3
VIA VIACENTER12 LAYER M1 ; RECT -4.6 -2.2 4.6 2.2 ;
    LAYER CUT12 ; RECT -3.1 -0.8 -1.9 0.8 ; RECT 1.9 -0.8 3.1 0.8 ;
    LAYER M2 ; RECT -4.4 -2.0 4.4 2.0 ; END VIACENTER12
```

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```
VIA VIATOP12 LAYER M1 ; RECT -2.2 -2.2 2.2 8.2 ;
    LAYER CUT12 ; RECT -0.8 5.2 0.8 6.8 ;
    LAYER M2 ; RECT -2.2 -2.2 2.2 8.2 ; END VIATOP12
VIA VIABOTTOM12 LAYER M1 ; RECT -2.2 -8.2 2.2 2.2 ;
    LAYER CUT12 ; RECT -0.8 -6.8 0.8 -5.2 ;
    LAYER M2; RECT -2.2 -8.2 2.2 2.2; END VIABOTTOM12
VIA VIALEFT12 LAYER M1; RECT -7.8 -2.2 2.2 2.2;
    LAYER CUT12 ; RECT -6.4 -0.8 -4.8 0.8 ;
    LAYER M2; RECT -7.8 -2.2 2.2 2.2; END VIALEFT12
VIA VIARIGHT12 LAYER M1 ; RECT -2.2 -2.2 7.8 2.2 ;
    LAYER CUT12 ; RECT 4.8 -0.8 6.4 0.8 ;
    LAYER M2; RECT -2.2 -2.2 7.8 2.2; END VIARIGHT12
VIA VIABIGPOWER12 LAYER M1 ; RECT -21.0 -21.0 21.0 21.0 ;
    LAYER CUT12 ; RECT -2.4 -0.8 2.4 0.8 ;
        RECT -19.0 -19.0 -14.2 -17.4; RECT -19.0 17.4 -14.2
            19.0;
        RECT 14.2 -19.0 19.0 -17.4; RECT 14.2 17.4 19.0 19.0;
        RECT -19.0 -0.8 -14.2 0.8 ; RECT -2.4 -19.0 2.4 -17.4 ;
        RECT 14.2 -0.8 19 0.8 ; RECT -2.4 17.4 2.4 19.0 ;
    LAYER M2 ; RECT -21.0 -21.0 21.0 ; END VIABIGPOWER12
VIARULE VIALIST12 LAYER M1 ; DIRECTION VERTICAL ; WIDTH 9.0 TO
    9.6;
    LAYER M2; DIRECTION HORIZONTAL; WIDTH 3.0 TO 3.0;
        VIA VIACENTER12 ; VIA VIATOP12 ; VIA VIABOTTOM12 ;
        VIA VIALEFT12; VIA VIARIGHT12; END VIALIST12
VIARULE VIAGEN12 GENERATE LAYER M1; DIRECTION VERTICAL;
    OVERHANG 1.4;
    LAYER M2; DIRECTION HORIZONTAL; OVERHANG 1.4;
    LAYER CUT12 ; RECT -0.8 -0.8 0.8 0.8 ;
    SPACING 5.6 BY 6.0; END VIAGEN12
VIA VIACENTER23 LAYER M3 ; RECT -2.2 -2.2 2.2 2.2 ;
    LAYER CUT23 ; RECT -0.8 -0.8 0.8 0.8 ;
    LAYER M2; RECT -2.0 -2.0 2.0; END VIACENTER23
VIA VIATOP23 LAYER M3 ; RECT -2.2 -2.2 2.2 8.2 ;
    LAYER CUT23 ; RECT -0.8 5.2 0.8 6.8 ;
    LAYER M2; RECT -2.2 -2.2 2.2 8.2; END VIATOP23
VIA VIABOTTOM23 LAYER M3 ; RECT -2.2 -8.2 2.2 2.2 ;
    LAYER CUT23 ; RECT -0.8 -6.8 0.8 -5.2 ;
    LAYER M2; RECT -2.2 -8.2 2.2 2.2; END VIABOTTOM23
VIA VIALEFT23 LAYER M3 ; RECT -7.8 -2.2 2.2 2.2 ;
    LAYER CUT23 ; RECT -6.4 -0.8 -4.8 0.8 ;
    LAYER M2; RECT -7.8 -2.2 2.2; END VIALEFT23
VIA VIARIGHT23 LAYER M3 ; RECT -2.2 -2.2 7.8 2.2 ;
    LAYER CUT23 ; RECT 4.8 -0.8 6.4 0.8 ;
    LAYER M2; RECT -2.2 -2.2 7.8 2.2; END VIARIGHT23
VIARULE VIALIST23 LAYER M3; DIRECTION VERTICAL; WIDTH 3.6 TO
    3.6;
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LAYER M2; DIRECTION HORIZONTAL; WIDTH 3.0 TO 3.0;
            VIA VIACENTER23 ; VIA VIATOP23 ; VIA VIABOTTOM23 ;
            VIA VIALEFT23 ; VIA VIARIGHT23 ; END VIALIST23
VIARULE VIAGEN23 GENERATE LAYER M3; DIRECTION VERTICAL;
    OVERHANG 1.4;
    LAYER M2; DIRECTION HORIZONTAL; OVERHANG 1.4;
    LAYER CUT23 ; RECT -0.8 -0.8 0.8 0.8 ;
    SPACING 5.6 BY 6.0; END VIAGEN23
MACRO CORNER CLASS ENDCAP BOTTOMLEFT; SIZE 436.8 BY 444; SYMMETRY X
Y ; SITE CORNER ;
    PIN VDD SHAPE RING ; DIRECTION INOUT ;
        PORT LAYER M2; WIDTH 20; PATH 426.8 200 200 200 200 434;
            END END VDD
    PIN VSS SHAPE RING ; DIRECTION INOUT ;
        PORT LAYER M2; WIDTH 20; PATH 100 434 100 100; LAYER M1;
            WIDTH 20 ; PATH 100 100 426.8 100 ; END END VSS END
                 CORNER
MACRO IN1X class pad ; FOREIGN IN1X ; SIZE 151.2 BY 444 ;
    SYMMETRY X ; SITE IOX ;
    PIN Z DIRECTION OUTPUT ;
        PORT LAYER M1 ; PATH 61.6 444 72.8 444 ; END END Z
    PIN PO DIRECTION OUTPUT ;
        PORT LAYER M1 ; PATH 78.4 444 84.0 444 ; END END PO
    PIN A DIRECTION INPUT ;
        PORT LAYER M1 ; PATH 95.2 444 100.8 444 ; END END A
    PIN PI DIRECTION INPUT ;
        PORT LAYER M1 ; PATH 106.4 444 112 444 ; END END PI
    PIN VDD DIRECTION INOUT; SHAPE ABUTMENT;
        PORT LAYER M2; WIDTH 20; PATH 10 200 141.2 200; END
    END VDD
    PIN VSS DIRECTION INOUT; SHAPE ABUTMENT;
        PORT LAYER M1; WIDTH 20; PATH 10 100 141.2 100; END
        END VSS END IN1X
MACRO IN1Y EEQ IN1X; FOREIGN IN1Y; class pad; SIZE 436.8 BY 150;
    SYMMETRY Y ; SITE IOY ;
    PIN Z DIRECTION OUTPUT ;
        PORT LAYER M2; PATH 0 69 0 75; END END Z
    PIN PO DIRECTION OUTPUT ;
        PORT LAYER M2; PATH 0 81 0 87; END END PO
    PIN A DIRECTION INPUT ;
        PORT LAYER M2; PATH 0 51 0 57; ENDEND A
    PIN PI DIRECTION INPUT ;
        PORT LAYER M2; PATH 0 39 0 45; END END PI
    PIN VDD DIRECTION INOUT ; SHAPE ABUTMENT ;
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PORT LAYER M2; WIDTH 20; PATH 236.8 10 236.8 140; END
    END VDD
    PIN VSS DIRECTION INOUT; SHAPE ABUTMENT;
        PORT LAYER M2; WIDTH 20; PATH 336.8 10 336.8 140; END
        END VSS END IN1Y
MACRO FILLER FOREIGN FILLER; SIZE 67.2 BY 6; SYMMETRY X Y R90;
    SITE CORE1 ;
    PIN VDD DIRECTION INOUT; SHAPE ABUTMENT;
        PORT LAYER M1; RECT 45.8 0 55 6; END END VDD
    PIN VSS DIRECTION INOUT; SHAPE ABUTMENT;
        PORT LAYER M1; RECT 12.2 0 21.4 6; END END VSS
    OBS LAYER M1 ; RECT 24.1 1.5 43.5 4.5 ; END END FILLER
MACRO INV FOREIGN INVS ; SIZE 67.2 BY 24 ; SYMMETRY X Y ; SITE CORE1 ;
    PIN Z DIRECTION OUTPUT ;
        PORT LAYER M2; PATH 30.8 9 42 9; END END Z
    PIN A DIRECTION INPUT ;
        PORT LAYER M1; PATH 25.2 15; END END A
    PIN VDD DIRECTION INOUT; SHAPE ABUTMENT;
        PORT LAYER M1 ; WIDTH 5.6 ; PATH 50.4 4.6 50.4 13.4 ; END
    END VDD
    PIN VSS DIRECTION INOUT; SHAPE ABUTMENT;
        PORT LAYER M1; WIDTH 5.6; PATH 16.8 4.6 16.8 13.4; END
    END VSS
    OBS LAYER M1 ; RECT 24.1 1.5 43.5 16.5 ; END END INV
MACRO BUF FOREIGN BUFS; SIZE 67.2 BY 126; SYMMETRY X Y; SITE
    CORE1 ;
    PIN Z DIRECTION OUTPUT ;
        PORT LAYER M2; PATH 25.2 39 42 39; END END Z
    PIN A DIRECTION INPUT ;
        PORT LAYER M1; PATH 30.8 33; END END A
    PIN VDD DIRECTION INOUT ; SHAPE FEEDTHRU ;
        PORT LAYER M1; WIDTH 5.6;
        PATH 50.4 4.6 50.4 10.0 56.0 10.0 56.0 115.8 50.4 115.8
             50.4 121.4 ; END END VDD
    PIN VSS DIRECTION INOUT; SHAPE FEEDTHRU;
        PORT LAYER M1; WIDTH 5.6;
        PATH 16.8 4.6 16.8 10.0 11.2 10.0 11.2 115.8 16.8 115.8
             16.8 121.4 ; END END VSS
    OBS LAYER M1 ; RECT 24.1 1.5 43.5 124.5 ; END END BUF
MACRO BIDIR1X FOREIGN BIDIR1X; class pad; SIZE 151.2 BY 444;
    SYMMETRY X ; SITE IOX ;
    PIN IO DIRECTION INOUT ;
        PORT LAYER M1 ; PATH 61.6 444 67.2 444 ; END END IO
    PIN ZI DIRECTION OUTPUT ;
        PORT LAYER M1 ; PATH 78.4 444 84.0 444 ; END END ZI
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PIN PO DIRECTION OUTPUT ;
        PORT LAYER M1 ; PATH 95.2 444 100.8 444 ; END END PO
    PIN A DIRECTION INPUT ;
        PORT LAYER M1 ; PATH 106.4 444 112.0 444 ; END END A
    PIN EN DIRECTION INPUT ;
        PORT LAYER M1; PATH 134.4 444 140.0 444; END END EN
    PIN TN DIRECTION INPUT ;
        PORT LAYER M1 ; PATH 28.0 444 33.6 444 ; END END TN
    PIN PI DIRECTION INPUT ;
        PORT LAYER M1 ; PATH 44.8 444 50.4 444 ; END END PI
    PIN VDD DIRECTION INOUT; SHAPE ABUTMENT;
        PORT LAYER M2; WIDTH 20; PATH 10 200 141.2 200; END END VDD
    PIN VSS DIRECTION INOUT; SHAPE ABUTMENT;
        PORT LAYER M1; WIDTH 20; PATH 10 100 141.2 100; END
        END VSS END BIDIR1X
MACRO BIDIR1Y EEQ BIDIR1X; class pad; FOREIGN BIDIR1Y; SIZE 436.8
    BY 150; SYMMETRY Y; SITE IOY;
    PIN IO DIRECTION INOUT ;
        PORT LAYER M2; PATH 0 69 0 75; END END IO
    PIN ZI DIRECTION OUTPUT ;
        PORT LAYER M2; PATH 0 93 0 99; END END ZI
    PIN PO DIRECTION OUTPUT ;
        PORT LAYER M2; PATH 0 81 0 87; END END PO
    PIN A DIRECTION INPUT ;
        PORT LAYER M2; PATH 0 15 0 21; END END A
    PIN EN DIRECTION INPUT ;
        PORT LAYER M2; PATH 0 27 0 33; END END EN
    PIN TN DIRECTION INPUT ;
        PORT LAYER M2; PATH 0 39 0 45; END END TN
    PIN PI DIRECTION INPUT ;
        PORT LAYER M2; PATH 0 51 0 57; END END PI
    PIN VDD DIRECTION INOUT; SHAPE ABUTMENT;
        PORT LAYER M2; WIDTH 20; PATH 236.8 10 236.8 140; END
    END VDD
    PIN VSS DIRECTION INOUT; SHAPE ABUTMENT;
        PORT LAYER M2; WIDTH 20; PATH 336.8 10 336.8 140; END
        END VSS END BIDIR1Y
MACRO OR2 FOREIGN OR2S; SIZE 67.2 BY 42; SYMMETRY X Y; SITE
    CORE1 ;
    PIN Z DIRECTION OUTPUT ;
        PORT LAYER M2; PATH 25.2 39 42 39; END END Z
    PIN A DIRECTION INPUT ;
        PORT LAYER M1; PATH 25.2 15; END END A
    PIN B DIRECTION INPUT ;
        PORT LAYER M1; PATH 25.2 3; END END B
    PIN VDD DIRECTION INOUT ; SHAPE FEEDTHRU ;
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PORT LAYER M1; WIDTH 5.6;
        PATH 50.4 4.6 50.4 10.0 ; PATH 50.4 27.4 50.4 37.4 ;
        VIA 50.4 3 C2PW ; VIA 50.4 21 C2PW ; VIA 50.4 33 C2PW ;
        VIA 50.4 39 C2PW; END END VDD
    PIN VSS DIRECTION INOUT; SHAPE FEEDTHRU;
        PORT LAYER M1; WIDTH 5.6; PATH 16.8 4.6 16.8 10.0;
        PATH 16.8 27.4 16.8 37.4 ;
        VIA 16.8 3 C2NW; VIA 16.8 15 C2NW; VIA 16.8 21 C2NW;
        VIA 16.8 33 C2NW; VIA 16.8 39 C2NW; END END VSS
    OBS LAYER M1 ; RECT 24.1 1.5 43.5 40.5 ; END END OR2
MACRO AND2 FOREIGN AND2S; SIZE 67.2 BY 84; SYMMETRY X Y; SITE
    CORE1 ;
    PIN Z DIRECTION OUTPUT ;
        PORT LAYER M2; PATH 25.2 39 42 39; END END Z
    PIN A DIRECTION INPUT ;
        PORT LAYER M1; PATH 42 15; END END A
    PIN B DIRECTION INPUT ;
        PORT LAYER M1; PATH 42 3; END END B
    PIN VDD DIRECTION INOUT; SHAPE ABUTMENT;
        PORT LAYER M1; WIDTH 5.6; PATH 50.4 4.6 50.4 79.4; END
    END VDD
    PIN VSS DIRECTION INOUT; SHAPE ABUTMENT;
        PORT LAYER M1; WIDTH 5.6; PATH 16.8 4.6 16.8 79.4; END
        END VSS
    OBS LAYER M1 ; RECT 24.1 1.5 43.5 82.5 ; END END AND2
MACRO DFF3 FOREIGN DFF3S; SIZE 67.2 BY 210; SYMMETRY X Y; SITE
    CORE1 ;
    PIN O DIRECTION OUTPUT ;
        PORT LAYER M2; PATH 19.6 99 47.6 99; END END Q
    PIN ON DIRECTION OUTPUT ;
        PORT LAYER M2 ; PATH 25.2 123 42 123 ; END END ON
    PIN D DIRECTION INPUT ;
        PORT LAYER M1; PATH 30.8 51; END END D
    PIN G DIRECTION INPUT ;
        PORT LAYER M1; PATH 25.2 3; END END G
    PIN CD DIRECTION INPUT ;
        PORT LAYER M1; PATH 36.4 75; END END CD
    PIN VDD DIRECTION INOUT; SHAPE FEEDTHRU;
        PORT LAYER M1; WIDTH 5.6; PATH 50.4 4.6 50.4 205.4;
    END END VDD
    PIN VSS DIRECTION INOUT; SHAPE FEEDTHRU;
        PORT LAYER M1; WIDTH 5.6; PATH 16.8 4.6 16.8 205.4;
    END END VSS
    OBS LAYER M1; RECT 24.1 1.5 43.5 208.5; PATH 8.4 3 8.4 123;
        PATH 58.8 3 58.8 123 ; PATH 64.4 3 64.4 123; END END DFF3
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MACRO NOR2 FOREIGN NOR2S ; SIZE 67.2 BY 42 ; SYMMETRY X Y ; SITE
    CORE1 ;
    PIN Z DIRECTION OUTPUT ;
        PORT LAYER M1; PATH 42 33; END END Z
    PIN A DIRECTION INPUT ;
        PORT LAYER M1; PATH 25.2 15; END END A
    PIN B DIRECTION INPUT ;
        PORT LAYER M1; PATH 36.49; END END B
    PIN VDD DIRECTION INOUT; SHAPE FEEDTHRU;
        PORT LAYER M1; WIDTH 5.6; PATH 50.4 4.6 50.4 37.4; END
    END VDD
    PIN VSS DIRECTION INOUT; SHAPE FEEDTHRU;
        PORT LAYER M1; WIDTH 5.6; PATH 16.8 4.6 16.8 37.4; END
    END VSS
    OBS LAYER M1 ; RECT 24.1 1.5 43.5 40.5 ; END END NOR2
MACRO AND2J EEQ AND2 ; FOREIGN AND2SJ ; SIZE 67.2 BY 48 ;
    SYMMETRY X Y ; ORIGIN 0 6 ; SITE CORE1 ;
    PIN Z DIRECTION OUTPUT ;
        PORT LAYER M2; PATH 25.2 33 42 33; END END Z
    PIN A DIRECTION INPUT ;
        PORT LAYER M1; PATH 42 15; END END A
    PIN B DIRECTION INPUT ;
        PORT LAYER M1; PATH 42 3; END END B
    PIN VDD DIRECTION INOUT; SHAPE FEEDTHRU;
        PORT LAYER M1; WIDTH 5.6; PATH 50.4 -1.4 50.4 37.4;
    END END VDD
    PIN VSS DIRECTION INOUT; SHAPE FEEDTHRU;
        PORT LAYER M1; WIDTH 5.6; PATH 16.8 -1.4 16.8 37.4;
    END END VSS
    OBS LAYER M1 ; RECT 24.1 1.5 43.5 34.5 ; END END AND2J
MACRO SOUAREBLOCK FOREIGN SOUAREBLOCKS; CLASS RING; SIZE 268.8
    BY 252; SITE SQUAREBLOCK;
    PIN Z DIRECTION OUTPUT ;
        PORT LAYER M2 ; PATH 22.8 21 246.0 21 ; END END Z
    PIN A DIRECTION OUTPUT ;
        PORT LAYER M2 ; PATH 64.4 33 137.2 33 ;
        PATH 137.2 33 137.2 69 ; PATH 137.2 69 204.4 69 ; END
    END A
    PIN B DIRECTION INPUT ;
        PORT LAYER M2 ; PATH 22.8 129 246.0 129 ; END END B
    PIN C DIRECTION INPUT ;
        PORT LAYER M2; PATH 70 165 70 153; PATH 70 153 126 153;
        END END C
    PIN D DIRECTION INPUT ;
        PORT LAYER M2; PATH 22.8 75 64.4 75; END END D
    PIN E DIRECTION INPUT ;
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PORT LAYER M2 ; PATH 22.8 87 64.4 87 ; END END E
    PIN F DIRECTION INPUT ;
        PORT LAYER M2; PATH 22.8 99 64.4 99; END END F
    PIN G DIRECTION INPUT ;
        PORT LAYER M2 ; PATH 22.8 111 64.4 111 ; END END G
    PIN VDD DIRECTION INOUT; SHAPE RING;
        PORT LAYER M1 ; WIDTH 3.6 ; PATH 4.0 3.5 4.0 248 ;
        PATH 264.8 100 264.8 248 ; PATH 150 3.5 150 100 ;
        LAYER M2; WIDTH 3.6; PATH 4.0 3.5 150 3.5;
        PATH 150 100 264.8 100 ; PATH 4.0 248 264.8 248 ; END
        END VDD
    PIN VSS DIRECTION INOUT; SHAPE RING;
        PORT LAYER M1; WIDTH 3.6; PATH 10 10 10 150;
        PATH 100 150 100 200 ; PATH 50 200 50 242 ;
        PATH 258.8 10 258.8 242 ; LAYER M2 ; WIDTH 3.6 ;
        PATH 10 150 100 150 ; PATH 100 200 50 200 ;
        PATH 10 10 258.8 10 ; PATH 50 242 258.8 242 ; END END VSS
    OBS LAYER M1 ; RECT 13.8 14.0 255.0 237.2 ; END
        END SQUAREBLOCK
MACRO I2BLOCK FOREIGN I2BLOCKS; CLASS RING; SIZE 672 BY 504;
    SITE I2BLOCK;
    PIN Z DIRECTION OUTPUT ;
        PORT LAYER M2; PATH 22.8 21 649.2 21; END END Z
    PIN A DIRECTION OUTPUT ;
        PORT LAYER M2 ; PATH 22.8 63 154.0 63 ; PATH 154.0 63 154.0
    129;
        PATH 154.0 129 447.6 129; END END A
    PIN B DIRECTION INPUT ;
        PORT LAYER M2 ; PATH 137.2 423 447.6 423 ; END END B
    PIN C DIRECTION INPUT ;
        PORT LAYER M2 ; PATH 204.4 165 271.6 165 ; END END C
    PIN D DIRECTION INPUT ;
        PORT LAYER M2; PATH 204.4 171 271.6 171; END END D
    PIN E DIRECTION INPUT ;
        PORT LAYER M1 ; PATH 204.4 213 204.4 213 ; END END E
    PIN F DIRECTION INPUT ;
        PORT LAYER M1 ; PATH 406 249 406 273 ; END END F
    PIN G DIRECTION INPUT ;
        PORT LAYER M1; PATH 338.8 249 338.8 273; END END G
    PIN H DIRECTION INPUT ;
        PORT LAYER M1 ; PATH 372.4 357 372.4 381 ; END END H
    PIN VDD DIRECTION INOUT; SHAPE RING;
        PORT LAYER M1; WIDTH 3.6; PATH 668 3.5 668 80.5;
        PATH 467 80.5 467 465.5; PATH 668 465.5 668 500.5;
        PATH 4 500.5 4 465.5; PATH 138 465.5 138 80.5;
        PATH 4 80.5 4 3.5 ; LAYER M2 ; WIDTH 3.6 ; PATH 4 3.5 668 3.5;
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PATH 668 80.5 467 80.5 ; PATH 467 465.5 668 465.5 ;
        PATH 668 500.5 4 500.5 ; PATH 4 465.5 138 465.5 ;
        PATH 138 80.5 4 80.5 ; END END VDD
    PIN VSS DIRECTION INOUT; SHAPE RING;
        PORT LAYER M1; WIDTH 3.6; PATH 662 10 662 74;
        PATH 461 74 461 472 ; PATH 662 472 662 494 ; PATH 10 494 10
        PATH 144 472 144 74 ; PATH 10 74 10 10 ; LAYER M2 ; WIDTH
        PATH 10 10 662 10 ; PATH 662 74 461 74 ; PATH 461 472 662
             472 ;
        PATH 662 494 10 494 ; PATH 10 472 144 472 ; PATH 144 74 10
             74;
        END END VSS
    OBS LAYER M1; RECT 14 14 658 70; RECT 14 476 658 490;
        RECT 148 14 457 490 ; # rectilinear shape description
        LAYER OVERLAP; RECT 0 0 672 84; RECT 134.4 84 470.4 462;
        RECT 0 462 672 504; END END I2BLOCK
MACRO LBLOCK FOREIGN LBLOCKS; CLASS RING; SIZE 201.6 BY 168; SITE
    LBLOCK ;
    PIN Z DIRECTION OUTPUT ;
        PORT LAYER M2; PATH 2.8 15 198.8 15; END END Z
    PIN A DIRECTION OUTPUT ;
        PORT LAYER M2 ; PATH 2.8 81 137.2 81 ; PATH 137.2 81 137.2
             69 i
        PATH 137.2 69 198.8 69; END END A
    PIN B DIRECTION INPUT ;
        PORT LAYER M2; PATH 2.8 165 64.4 165; END END B
    PIN C DIRECTION INPUT ;
        PORT LAYER M1 ; PATH 2.8 93 2.8 105 ; END END C
    PIN D DIRECTION INPUT ;
        PORT LAYER M1 ; PATH 64.4 93 64.4 105 ; END END D
    PIN E DIRECTION INPUT ;
        PORT LAYER M1 ; PATH 198.8 39 198.8 39 ; END END E
    PIN F DIRECTION INPUT ;
        PORT LAYER M1; PATH 198.8 45 198.8 45; END END F
    PIN G DIRECTION INPUT ;
        PORT LAYER M1; PATH 2.8 111 2.8 111; END END G
        PORT LAYER M2; WIDTH 3.6; PATH 1.8 27 199.8 27; END END VDD
    PIN VSS DIRECTION INOUT ;
        PORT LAYER M2; WIDTH 3.6; PATH 1.8 57 199.8 57; END END VSS
    OBS LAYER M2; RECT 1.0 80 66.2 166.5; RECT 1.0 1.5 200.6 23;
        RECT 1.0 31 200.6 53 ; RECT 1.0 61 200.6 82.5 ;
         # rectilinear shape description
        LAYER OVERLAP ; RECT 0 0 201.6 84 ; RECT 0 84 67.2 168 ;
        END END LBLOCK
```

Examples

END LIBRARY

DEF

The following example shows a design netlist.

```
DESIGN DEMO4CHIP ;
TECHNOLOGY DEMO4CHIP ;
ARRAY DEMO4 ;
UNITS DISTANCE MICRONS 100;
COMPONENTS 243 ;
- CORNER1 CORNER; - CORNER2 CORNER; - CORNER3 CORNER;
- CORNER4 CORNER; - C01 IN1X; - C02 IN1Y; - C04 IN1X;
- C05 IN1X ; - C06 IN1Y ;
- C07 IN1Y; - C08 IN1Y; - C09 IN1Y; - C10 IN1X; - C11 IN1X;
- C13 BIDIR1Y ; - C14 INV ; - C15 BUF ; - C16 BUF ; - C17 BUF ;
- C19 BIDIR1Y ; - C20 INV ; - C21 BUF ; - C22 BUF ; - C23 BUF ;
- C25 BIDIR1Y ; - C26 INV ; - C27 BUF ; - C28 BUF ; - C29 BUF ;
- C31 BIDIR1Y ; - C32 INV ; - C33 BUF ; - C34 BUF ; - C35 BUF ;
- C37 BIDIR1X ; - C39 INV ; - C40 BUF ; - C41 BUF ; - C42 BUF ;
- C44 BIDIR1X ; - C45 INV ; - C46 BUF ; - C47 BUF ; - C48 BUF ;
- C50 BIDIR1Y ; - C51 INV ; - C52 BUF ; - C53 BUF ; - C54 BUF ;
- C56 BIDIR1X ; - C57 INV ; - C58 BUF ; - C59 BUF ; - C60 BUF ;
- D02 BIDIR1X ; - D03 INV ; - D04 BUF ; - D05 BUF ; - D06 BUF ;
- D08 BIDIR1X ; - D09 INV ; - D10 BUF ; - D11 BUF ; - D12 BUF ;
- D14 BIDIR1X ; - D15 INV ; - D16 BUF ; - D17 BUF ; - D19 BUF ;
- D33 BIDIR1Y ; - D34 INV ; - D35 BUF ; - D36 BUF ; - D37 BUF ;
- D39 BIDIR1Y ; - D40 INV ; - D41 BUF ; - D42 BUF ; - D43 BUF ;
- D45 BIDIR1Y ; - D46 INV ; - D47 BUF ; - D48 BUF ; - D49 BUF ;
- D82 OR2 ; - D83 OR2 ; - D84 OR2 ; - D85 OR2 ; - D86 OR2 ;
- D87 OR2 ; - D88 OR2 ; - D89 OR2 ; - D90 OR2 ; - D91 OR2 ;
- D92 OR2 ; - D93 OR2 ;
- E01 AND3 ; - E02 AND3 ; - E03 AND3 ; - E04 AND3 ; - E05 AND3 ;
- E06 AND3 ; - E07 AND3 ; - E08 AND3 ; - E09 AND3 ; - E10 AND3 ;
- E11 AND3 ; - E12 AND3 ; - E13 AND3 ; - E14 AND3 ; - E15 AND3 ;
- E16 AND3 ;
- EE16 IN1X ; - E17 IN1X ; - E18 IN1X ; - E19 IN1X ; - E20 IN1X ;
- E21 IN1X ; - E22 IN1X ; - E23 IN1Y ; - E24 IN1Y ; - E25 IN1Y ;
- E26 INV ; - E27 AND2 ; - E28 AND2 ; - E29 AND2 ; - E30 AND2 ;
- E31 AND2 ; - E32 AND2 ; - E33 OR2 ; - E34 OR2 ; - E35 OR2 ;
- E36 OR2 ; - E37 IN1Y ; - E38A01 DFF3 ; - E38A02 DFF3 ;
- E38A03 DFF3 ;- E38A04 DFF3 ; - E38A05 DFF3 ; - F01 I2BLOCK ;
- F04 OR2 ; - F06 OR2 ; - F07 OR2 ; - F08 OR2 ; - F09 SQUAREBLOCK ;
- F12 LBLOCK;
- Z14 INV ; - Z15 BUF ; - Z16 BUF ; - Z17 BUF ; - Z20 INV ;
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- Z21 BUF ; - Z22 BUF ; - Z23 BUF ; - Z26 INV ; - Z27 BUF ;
- Z28 BUF ; - Z29 BUF ; - Z32 INV ; - Z33 BUF ; - Z34 BUF ;
- Z35 BUF; - Z39 INV; - Z40 BUF; - Z41 BUF; - Z42 BUF;
- Z45 INV ; - Z46 BUF ; - Z47 BUF ; - Z48 BUF ; - Z51 INV ;
- Z52 BUF ; - Z53 BUF ; - Z54 BUF ; - Z57 INV ; - Z58 BUF ; - Z59 BUF ;
- Z60 BUF; - Z103 INV; - Z104 BUF; - Z105 BUF; - Z106 BUF;
- Z109 INV ; - Z110 BUF ; - Z111 BUF ; - Z112 BUF ; - Z115 INV ;
- Z116 BUF ; - Z117 BUF ; - Z119 BUF ; - Z134 INV ; - Z135 BUF ;
- Z136 BUF; - Z137 BUF; - Z140 INV; - Z141 BUF; - Z142 BUF;
- Z143 BUF ; - Z146 INV ; - Z147 BUF ; - Z148 BUF ; - Z149 BUF ;
- Z182 OR2 ; - Z183 OR2 ; - Z184 OR2 ; - Z185 OR2 ; - Z186 OR2 ;
- Z187 OR2; - Z188 OR2; - Z189 OR2; - Z190 OR2; - Z191 OR2;
- Z192 OR2 ; - Z193 OR2 ; - Z201 AND3 ; - Z202 AND3 ; - Z203 AND3 ;
- Z204 AND3 ; - Z205 AND3 ; - Z206 AND3 ; - Z207 AND3 ; - Z208 AND3 ;
- Z209 AND3 ; - Z210 AND3 ; - Z211 AND3 ; - Z212 AND3 ; - Z213 AND3 ;
- Z214 AND3 ; - Z215 AND3 ; - Z216 AND3 ; - Z226 INV ; - Z227 AND2 ;
- Z228 AND2 ; - Z229 AND2 ; - Z230 AND2 ; - Z231 AND2 ; - Z232 AND2 ;
- Z233 OR2 ; - Z234 OR2 ; - Z235 OR2 ; - Z236 OR2 ; - Z38A01 DFF3 ;
- Z38A02 DFF3 ; - Z38A03 DFF3 ; - Z38A04 DFF3 ; - Z38A05 DFF3 ;
END COMPONENTS
NETS 222 ;
- VDD ( Z216 B ) ( Z215 B ) ( Z214 C ) ( Z214 B )
( Z213 C ) ( Z213 B ) ( Z212 C ) ( Z212 B ) ( Z211 C ) ( Z211 B )
( Z210 C ) ( E23 Z ) ( Z143 Z ) ( Z142 Z ) ( Z141 Z ) ( Z119 Z )
( Z117 Z ) ( Z116 Z ) ( Z106 Z ) ( Z105 Z ) ( Z104 Z ) ( Z34 Z )
( Z33 Z ) ( Z28 Z ) ( Z27 Z ) ( Z22 Z ) ( Z21 Z ) ( Z16 Z )
( Z15 Z ) ( D45 PO ) ( D14 PO ) ( C01 PI ) ( D45 TN ) ( D39 TN )
( D33 TN ) ( D14 TN ) ( D08 TN ) ( D02 TN ) ( C56 TN ) ( C50 TN )
(C44 TN) (C37 TN) (C31 TN) (C25 TN) (C19 TN) (C13 TN);
- VSS ( Z209 C ) ( Z208 C ) ( Z207 C ) ( Z206 C ) ( Z205 C )
( Z204 C ) ( Z203 C ) ( Z202 C ) ( Z201 C ) ( Z149 Z ) ( Z148 Z )
( Z147 Z ) ( Z137 Z ) ( Z136 Z ) ( Z135 Z ) ( Z112 Z ) ( Z111 Z )
( Z110 Z ) ( Z60 Z ) ( Z59 Z ) ( Z58 Z ) ( Z54 Z ) ( Z53 Z )
( Z52 Z ) ( Z47 Z ) ( Z46 Z ) ( Z41 Z ) ( Z40 Z ) ( E18 Z )
( D49 Z ) ( D43 Z ) ( D45 A ) ( D39 A ) ( D33 A ) ( D14 A )
( D08 A ) ( D02 A ) ( C56 A ) ( C50 A ) ( C44 A ) ( C37 A )
(C31 A) (C25 A) (C19 A) (C13 A); - XX1001 (Z38A04 G)
( Z38A02 G ); - XX100 ( Z38A05 G ) ( Z38A03 G ) ( Z38A01 G );
- XX907 ( Z236 B ) ( Z235 B ) ; - XX906 ( Z234 B ) ( Z233 B ) ;
- XX904 ( Z232 B ) ( Z231 B ) ; - XX903 ( Z230 B ) ( Z229 B ) ;
- XX902 ( Z228 B ) ( Z227 B ) ;
- XX900 ( Z235 A ) ( Z233 A ) ( Z232 A ) ( Z230 A ) ( Z228 A ) ( Z226 A ) ;
- Z38QN4 ( Z38A04 QN ) ( Z210 B ) ; - COZ131 ( Z38A04 Q ) ( Z210 A ) ;
- Z38QN3 ( Z38A03 QN ) ( Z209 B ) ; - COZ121 ( Z38A03 Q ) ( Z209 A ) ;
- Z38QN2 ( Z38A02 QN ) ( Z208 B ) ; - COZ111 ( Z38A02 Q ) ( Z208 A ) ;
- Z38QN1 ( Z38A01 QN ) ( Z207 B ) ; - COZ101 ( Z38A01 Q ) ( Z207 A ) ;
```

```
- XX901 ( Z236 A ) ( Z234 A ) ( Z231 A ) ( Z229 A ) ( Z227 A ) ( Z226 Z )
    (Z193 A);
- X415 ( Z149 A ) ( Z148 A ) ( Z147 A ) ( Z146 Z ) ; - X413 ( Z143 A )
    (Z142 A) (Z141 A) (Z140 Z);
- X411 ( Z137 A ) ( Z136 A ) ( Z135 A ) ( Z134 Z ) ;
- X405 ( Z119 A ) ( Z117 A ) ( Z116 A ) ( Z115 Z ) ;
- X403 ( Z112 A ) ( Z111 A ) ( Z110 A ) ( Z109 Z ) ;
- X401 ( Z106 A ) ( Z105 A ) ( Z104 A ) ( Z103 Z ) ;
- X315 ( Z60 A ) ( Z59 A ) ( Z58 A ) ( Z57 Z ) ;
- X313 ( Z54 A ) ( Z53 A ) ( Z52 A ) ( Z51 Z ) ;
- DIS051 ( Z216 A ) ( Z48 Z ) ;
- X311 ( Z48 A ) ( Z47 A ) ( Z46 A ) ( Z45 Z ) ;
- DISO41 ( Z215 A ) ( Z42 Z ) ; - X309 ( Z42 A ) ( Z41 A ) ( Z40 A )
    ( Z39 Z ) ;
- X307 ( Z35 A ) ( Z34 A ) ( Z33 A ) ( Z32 Z ) ;
- DIS031 ( Z214 A ) ( Z35 Z ) ; - DIS021 ( Z213 A ) ( Z29 Z ) ;
- X305 ( Z29 A ) ( Z28 A ) ( Z27 A ) ( Z26 Z ) ;
- DIS011 ( Z212 A ) ( Z23 Z ) ;
- X303 ( Z23 A ) ( Z22 A ) ( Z21 A ) ( Z20 Z ) ;
- DISO01 ( Z211 A ) ( Z17 Z ) ;
- X301 ( Z17 A ) ( Z16 A ) ( Z15 A ) ( Z14 Z ) ;
- X1000 ( E38A05 G ) ( E38A03 G ) ( E38A01 G ) ( E37 Z ) ;
- CNTEN ( Z38A05 Q ) ( E38A05 Q ) ( E25 A ) ;
- VIH20 ( E37 PI ) ( E25 PO ) ; - X0907 ( E36 B ) ( E35 B ) ( E25 Z ) ;
- CCLKO ( F09 A ) ( E24 A ) ; - VIH19 ( E25 PI ) ( E24 PO ) ;
- X0906 ( E34 B ) ( E33 B ) ( E24 Z ) ; - CATH1 ( F09 Z ) ( E23 A ) ;
- VIH18 ( E24 PI ) ( E23 PO ) ; - CRLIN ( F08 Z ) ( E22 A ) ;
- VIH17 ( E23 PI ) ( E22 PO ) ; - X0904 ( E32 B ) ( E31 B ) ( E22 Z ) ;
- NXLIN ( F07 Z ) ( E21 A ) ; - VIH16 ( E22 PI ) ( E21 PO ) ;
- X0903 ( E30 B ) ( E29 B ) ( E21 Z ) ; - RPT1 ( F06 Z ) ( E20 A ) ;
- VIH15 ( E21 PI ) ( E20 PO ) ; - X0902 ( E28 B ) ( E27 B ) ( E20 Z ) ;
- AGISL ( F04 Z ) ( E19 A ) ; - VIH14 ( E20 PI ) ( E19 PO ) ;
- X0900 ( E35 A ) ( E33 A ) ( E32 A ) ( E30 A ) ( E28 A ) ( E26 A )
    (E19 Z);
- TSTCN ( Z38A05 QN ) ( E38A05 QN ) ( E18 A ) ;
- VIH13 ( E19 PI ) ( E18 PO ) ; - BCLK1 ( F01 A ) ( E17 A ) ;
- VIH12 ( E18 PI ) ( E17 PO ) ; - CLR0 ( F01 Z ) ( EE16 A ) ;
- VIH11 ( E17 PI ) ( EE16 PO ) ; - BCLKX1 ( Z216 C ) ( E17 Z )
    (E16 C); - CLRXO (Z38A05 CD) (Z38A03 CD) (Z38A01 CD)
    ( Z215 C ) ( E38A05 CD ) ( E38A03 CD ) ( E38A01 CD ) ( EE16 Z )
    ( E15 C ); - E38QN4 ( E38A04 QN ) ( E10 B );
- CAX131 ( E38A04 Q ) ( E10 A ) ; - E38QN3 ( E38A03 QN ) ( E09 B ) ;
- CAX121 ( E38A03 Q ) ( E09 A ) ; - E38QN2 ( E38A02 QN ) ( E08 B ) ;
- CAX111 ( E38A02 Q ) ( E08 A ) ; - E38QN1 ( E38A01 QN ) ( E07 B ) ;
- CAX101 ( E38A01 Q ) ( E07 A );
- SDD111 ( Z38A05 D ) ( Z205 Z ) ( E38A05 D ) ( E05 Z ) ;
- SDD121 ( Z38A04 D ) ( Z204 Z ) ( E38A04 D ) ( E04 Z ) ;
```

```
- X0901 ( E36 A ) ( E34 A ) ( E31 A ) ( E29 A ) ( E27 A ) ( E26 Z )
    ( D93 A );
- VIH21 ( Z192 A ) ( E37 PO ) ( D92 A ) ;
- STRDENBO ( Z206 B ) ( Z202 B ) ( Z201 B ) ( Z189 B ) ( Z188 B )
    (F12 A) (E06 B) (E02 B) (E01 B) (D89 B) (D88 B);
- STRDENAO ( Z202 A ) ( Z201 A ) ( Z183 B ) ( Z182 B ) ( F12 Z )
    (F01 H) (E02 A) (E01 A) (D83 B) (D82 B);
- DAB151 ( F12 H ) ( D48 Z ) ; - DAA151 ( F08 B ) ( D47 Z ) ;
- X0415 ( D49 A ) ( D48 A ) ( D47 A ) ( D46 Z ) ;
- SDD151 ( Z38A01 D ) ( Z201 Z ) ( E38A01 D ) ( E01 Z ) ( D45 EN ) ;
- X0414 ( Z146 A ) ( D46 A ) ( D45 ZI ) ; - D151 ( E14 C ) ( D45 IO ) ;
- DAB141 ( F12 G ) ( D42 Z ) ; - DAA141 ( F08 A ) ( D41 Z ) ;
- X0413 ( D43 A ) ( D42 A ) ( D41 A ) ( D40 Z ) ;
- SDD141 ( Z38A02 D ) ( Z202 Z ) ( E38A02 D ) ( E02 Z ) ( D39 EN ) ;
- VIH60 ( D45 PI ) ( D39 PO ) ; - X0412 ( Z140 A ) ( D40 A ) ( D39 ZI ) ;
- D141 ( E13 C ) ( D39 IO ) ; - SDI131 ( E16 B ) ( D37 Z ) ;
- DAB131 ( F12 F ) ( D36 Z ) ; - DAA131 ( F07 B ) ( D35 Z ) ;
- X0411 ( D37 A ) ( D36 A ) ( D35 A ) ( D34 Z ) ;
- VIH58 ( Z193 Z ) ( D93 Z ) ( D33 PI ) ;
- SDD131 ( Z38A03 D ) ( Z203 Z ) ( E38A03 D ) ( E03 Z ) ( D33 EN ) ;
- VIH59 ( D39 PI ) ( D33 PO ) ; - X0410 ( Z134 A ) ( D34 A ) ( D33 ZI ) ;
- D131 ( E12 C ) ( D33 IO ) ; - SDI101 ( E15 B ) ( D19 Z ) ; ...
- X0315 ( C60 A ) ( C59 A ) ( C58 A ) ( C57 Z ) ;
- SDD071 ( Z211 Z ) ( E11 Z ) ( C56 EN ) ;
- VIH53 ( Z190 Z ) ( D90 Z ) ( D02 PI ) ( C56 PO ) ;
- X0314 ( Z57 A ) ( C57 A ) ( C56 ZI );
- D071 ( E08 C ) ( C56 IO ) ; - SDI061 ( E11 B ) ( C54 Z ) ;
- DAB061 ( F09 H ) ( C53 Z ) ; - DAA061 ( F04 A ) ( C52 Z ) ;
- X0313 ( C54 A ) ( C53 A ) ( C52 A ) ( C51 Z ) ;
- SDD061 ( Z212 Z ) ( E12 Z ) ( C50 EN ) ;
- VIH52 ( Z189 Z ) ( D89 Z ) ( C56 PI ) ( C50 PO ) ;
- X0312 ( Z51 A ) ( C51 A ) ( C50 ZI ) ;
- D061 ( E07 C ) ( C50 IO ) ; - SDI051 ( E16 A ) ( C48 Z ) ;
- DAB051 ( F09 G ) ( C47 Z ) ; - DAA051 ( F01 G ) ( C46 Z ) ;
- X0311 ( C48 A ) ( C47 A ) ( C46 A ) ( C45 Z ) ;
- SDD051 ( Z213 Z ) ( E13 Z ) ( C44 EN ) ;
- VIH51 ( Z188 Z ) ( D88 Z ) ( C50 PI ) ( C44 PO ) ;
- X0310 ( Z45 A ) ( C45 A ) ( C44 ZI ) ;
- D051 ( E06 C ) ( C44 IO ) ; - SDI041 ( E15 A ) ( C42 Z ) ;
- DAB041 ( F09 F ) ( C41 Z ) ; - DAA041 ( F01 F ) ( C40 Z ) ;
- X0309 ( C42 A ) ( C41 A ) ( C40 A ) ( C39 Z ) ;
- SDD041 ( Z214 Z ) ( E14 Z ) ( C37 EN ) ;
- VIH50 ( Z187 Z ) ( D87 Z ) ( C44 PI ) ( C37 PO ) ;
- X0308 ( Z39 A ) ( C39 A ) ( C37 ZI ) ;
- D041 ( E05 C ) ( C37 IO ) ; - SDI031 ( E14 A ) ( C35 Z ) ;
- DAB031 ( F09 E ) ( C34 Z ) ; - DAA031 ( F01 E ) ( C33 Z ) ;
- X0307 ( C35 A ) ( C34 A ) ( C33 A ) ( C32 Z ) ;
```

```
- SDD031 ( Z215 Z ) ( E15 Z ) ( C31 EN ) ;
- VIH49 ( Z186 Z ) ( D86 Z ) ( C37 PI ) ( C31 PO ) ;
- X0306 ( Z32 A ) ( C32 A ) ( C31 ZI ) ;
- D031 ( E04 C ) ( C31 IO ) ; - SDI021 ( E13 A ) ( C29 Z ) ;
- DAB021 ( F09 D ) ( C28 Z ) ; - DAA021 ( F01 D ) ( C27 Z ) ;
- X0305 ( C29 A ) ( C28 A ) ( C27 A ) ( C26 Z ) ;
- SDD021 ( Z216 Z ) ( E16 Z ) ( C25 EN ) ;
- VIH48 ( Z185 Z ) ( D85 Z ) ( C31 PI ) ( C25 PO ) ;
- X0304 ( Z26 A ) ( C26 A ) ( C25 ZI ) ;
- D021 ( E03 C ) ( C25 IO ) ; - SDI011 ( E12 A ) ( C23 Z ) ;
- DAB011 ( F09 C ) ( C22 Z ) ; - DAA011 ( F01 C ) ( C21 Z ) ;
- X0303 ( C23 A ) ( C22 A ) ( C21 A ) ( C20 Z ) ;
- SDD011 ( Z209 Z ) ( E09 Z ) ( C19 EN ) ;
- VIH47 ( Z184 Z ) ( D84 Z ) ( C25 PI ) ( C19 PO ) ;
- X0302 ( Z20 A ) ( C20 A ) ( C19 ZI ) ;
- D011 ( E02 C ) ( C19 IO ) ; - SDI001 ( E11 A ) ( C17 Z ) ;
- DAB001 ( F09 B ) ( C16 Z ) ; - DAA001 ( F01 B ) ( C15 Z ) ;
- X0301 ( Z14 A ) ( C17 A ) ( C16 A ) ( C15 A ) ( C14 Z ) ;
- VIH45 ( Z182 Z ) ( D82 Z ) ( C13 PI ) ;
- SDD001 ( Z210 Z ) ( E10 Z ) ( C13 EN ) ;
- VIH46 ( Z183 Z ) ( D83 Z ) ( C19 PI ) ( C13 PO ) ;
- X0300 ( C14 A ) ( C13 ZI ) ; - D001 ( E01 C ) ( C13 IO ) ;
- CCLKBO ( Z234 Z ) ( Z189 A ) ( E34 Z ) ( D89 A ) ( C11 A ) ;
- VIH10 ( EE16 PI ) ( C11 PO ) ;
- STRAAA ( Z206 A ) ( E06 A ) ( C11 Z ) ;
- CCLKAO ( Z233 Z ) ( Z188 A ) ( E33 Z ) ( D88 A ) ( C10 A ) ;
- VIH9 ( C11 PI ) ( C10 PO );
- STRB00 ( Z192 B ) ( D92 B ) ( C10 Z ) ;
- CRLINB1 ( Z232 Z ) ( Z187 A ) ( E32 Z ) ( D87 A ) ( C09 A ) ;
- VIH8 ( C10 PI ) ( C09 PO ) ;
- STRA00 ( Z187 B ) ( D87 B ) ( C09 Z ) ;
- CRLINA1 ( Z231 Z ) ( Z186 A ) ( E31 Z ) ( D86 A ) ( C08 A ) ;
- VIH7 ( C09 PI ) ( C08 PO ) ;
- X10001 ( E38A04 G ) ( E38A02 G ) ( C08 Z ) ;
- NXLINB1 ( Z230\ Z ) ( Z185\ A ) ( E30\ Z ) ( D85\ A ) ( C07\ A ) ;
- VIH6 ( CO8 PI ) ( CO7 PO );
- CLRX00 ( Z38A04 CD ) ( Z38A02 CD ) ( E38A04 CD ) ( E38A02 CD )
    (C07Z);
- NXLINA1 ( Z229 Z ) ( Z184 A ) ( E29 Z ) ( D84 A ) ( C06 A ) ;
- VIH5 ( C07 PI ) ( C06 PO );
- STRBBO ( Z205 B ) ( Z193 B ) ( E05 B ) ( D93 B ) ( C06 Z ) ;
- RPTB1 ( Z228 Z ) ( Z183 A ) ( E28 Z ) ( D83 A ) ( C05 A ) ;
- VIH4 ( C06 PI ) ( C05 PO );
- STRAAO ( Z205 A ) ( Z186 B ) ( E05 A ) ( D86 B ) ( C05 Z ) ;
- RPTA1 ( Z227 Z ) ( Z182 A ) ( E27 Z ) ( D82 A ) ( C04 A ) ;
- VIH3 ( C05 PI ) ( C04 PO ) ;
- STRBO ( Z204 B ) ( Z203 B ) ( Z191 B ) ( Z190 B ) ( E04 B )
```

Examples

Scan Chain Synthesis Example

You define the scan chain in the COMPONENTS and SCANCHAINS sections in your DEF file.

```
COMPONENTS 100;
- SIN MUX;
- SOUT PAD;
- C1 SDFF;
- C2 SDFF;
- C3 SDFF;
- C4 SDFF;
- B1 BUF;
- A1 AND; ...
END COMPONENTS

NETS 150;
- N1 (C1 SO) (C3 SI);
- N2 (C3 SO) (A1 A); ...
END NETS
```

You do not need to define any scan nets in the NETS section. This portion of the NETS section shows the effect of the scan chain process on existing nets that use components you specify in the SCANCHAINS section.

```
SCANCHAINS 1;
- SC
+ COMMONSCANPINS (IN SI) (OUT SO)
+ START SIN Z2
+ FLOATING C1 C2 C3
+ ORDERED C4 B1 (IN A) (OUT Q);
+ STOP SOUT A;
END SCANCHAINS
```

Because components C1, C2, and C3 are floating, TROUTE SCANCHAIN can synthesize them in any order in the chain. TROUTE synthesizes ordered components (C4 and B1) in the order you specify.

В

Via Pattern Encoding Convention

This appendix contains information about the following topics.

- Overview on page 201
- Bitmapped Via Pattern Encoding Convention on page 201
- Compressed Via Pattern Encoding Convention on page 202

Overview

This appendix explains

- The bitmapped pattern encoding convention for generated vias
- The compressed via pattern encoding convention
- How the compressed pattern encoding convention maps to the bitmapped pattern encoding convention

You can choose the naming convention you want with the following environmental variable:

```
Synthesis.ViaName.Convention
string [bitmapped, compressed]
Default: compressed
expert
```

Specifies the encoding convention to use for generated vias.

The compressed option creates much shorter via pattern entries in the DEF file. Use the bitmapped option only if you need to maintain compatibility to versions 4.3 and earlier.

Bitmapped Via Pattern Encoding Convention

The bitmapped via pattern encoding represents the cut pattern as hexadecimal digits.

Via Pattern Encoding Convention

Name Form

A symmetric via has equal metal on both sides of the center in both directions. You can use Synthesis. Delimiter to set the separator (default value is " - "). Generated symmetric vias have the following form:

```
viaRuleName-viaSizeX-viaSizeY-cutPattern
```

An asymmetric via has unequal metal in either direction. You can use Synthesis. Asymmetric. Delimiter to set the separator (default value is "|"). Generated asymmetric vias have the following form:

```
viaRuleName | minX | minY | maxX | maxY | offsetX | offsetY | cutPattern
```

The offsetX and offsetY values express the offset between the via center and the origin.

Cut Representation

The following example shows the cut pattern, the binary bits, and the hexadecimal representation of a bitmapped via.

```
000000 111111 = 3F
0 000 100111 = 27
000000 111111 = 3F
00 110000 = 30
```

Compressed Via Pattern Encoding Convention

The compressed via pattern encoding convention uses both hexadecimal (base 16) and double-decimal (base 20) digits to represent the cut patterns. The compressed via pattern encoding convention generates much shorter pattern name entries because it uses the double-decimal digits to reduce repetitive patterns and characters.

Bitmapped:

```
viaRuleName-viaSizeX-viaSizeY-cutPattern
```

Compressed:

```
viaRuleName-viaSizeX-viaSizeY-Rp_cutPattern_Rh
```

Rp Number of times the following cut pattern is repeated

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Via Pattern Encoding Convention

Rh

Number of times the preceding hexadecimal character is repeated

Rp and Rh are expressed as double-decimal (base 20) digits.

Character Sets

The following shows the hexadecimal and double-decimal digit character sets. The hexadecimal character set uses alpha characters A to F. The double-decimal character set uses the remaining alpha characters, G to Z.

Hexadecimal Digit Character Set

Number	0	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
Character	0	1	2	3	4	5	6	7	8	9	Α	В	С	D	Е	F

Double-Decimal Digit Character Set (Base 20)

Number	0	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15	16	17	18	19
Character	G	Н	ı	J	K	L	М	N	0	Р	Q	R	S	Т	U	٧	W	Χ	Υ	Ζ

Rules for Double-Decimal Digit Character Set

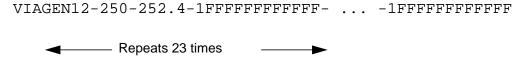
The double-decimal digit character set follows these rules:

- The cut pattern repetition count, *Rp*, is in front of the repeated cut pattern. The compressed convention uses *Rp* encoding if the cut pattern repeats two or more times.
- The hexadecimal character repetition count, *Rh*, follows the repeated hexadecimal character. The compressed convention uses *Rh* encoding if the preceding hexadecimal character repeats three or more times.

Example 1

The following shows how a bitmapped via pattern name maps to the same name in compressed form.

■ Bitmapped via pattern (340 characters):



Via Pattern Encoding Convention

Compressed via pattern (24 characters):

VIAGEN12_250_252.4_IJ1FS

Number of times the following pattern—repeats itself. IJ means that the following cut pattern, 1F, repeats 23 times.

The number of times the preceding character repeats. S means that the preceding character, F, repeats 12 times.

Example 2

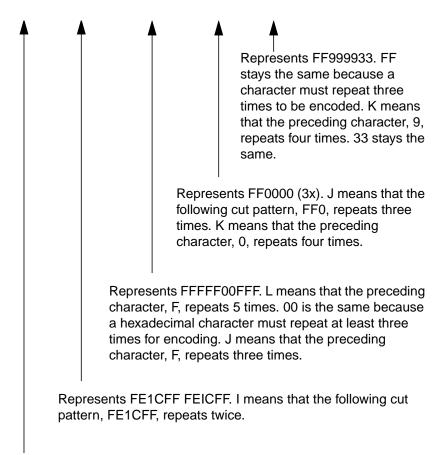
Bitmapped via pattern name (86 characters):

VIAGEN12-250-252.4-FFFFFFF0000-FE1CFF-FE1CFF-FFFF00FFF-FF0000-FF0000-FF999933

Compressed via name (51 characters):

Via Pattern Encoding Convention

VIAGEN12_250_252.4_FO0K_IFE1CFF_FL00FJ_JFF0K_FF9K33



Represents FFFFFFF0000. O means that the preceding character, F, repeats 8 times. K means that the preceding character, 0, repeats 4 times.

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Via Pattern Encoding Convention

C

Optimizing LEF Technology for Place and Route

This appendix contains the following information.

- Overview
- Guidelines for No Wire Extension at Pin on page 208
- Guidelines for Routing Pitch on page 208
- Guidelines for Wide Metal Spacing on page 211
- Guidelines for Wire Extension at Vias on page 212
- Guidelines for Default Vias on page 214
- Guidelines for Stack Vias (MAR Vias) and Samenet Spacing on page 216
- Example of an Optimized LEF Technology File on page 220

Overview

This appendix provides guidelines for defining the optimized technology section in the LEF file to get the best performance using Cadence[®] place-and-route tools, especially Cadence Ultra Router. The LEF syntax shown is based on Silicon Ensemble[®] Place-and-Route 5.2 or newer.

For the following guidelines, the preferred routing direction for metal1 and all other odd metal layers is horizontal. The preferred routing direction for metal2 and all other even metal layers is vertical. Standard cells are arranged in horizontal rows.

This appendix discusses the following LEF statements.

```
NOWIREEXTENSIONATPIN { ON | OFF }

LAYER layerName
   TYPE ROUTING ;
   PITCH distance ;
```

Optimizing LEF Technology for Place and Route

```
WIDTH defWidth;
SPACING minSpacing [RANGE minwidth maxwidth];
WIREEXTENSION value;

END layerName

VIA viaName DEFAULT
[TOPSTACKONLY]
LAYER layerName RECT pt pt; ...

END viaName

SPACING
SAMENET
layerName layerName minSpace [STACK];

END SPACING
```

Guidelines for No Wire Extension at Pin

By default, wires extend one half of the default routing width at pins. To prevent this wire extension at pins when the pin width is narrower than the wire width, use the following statement in the LEF file.

```
NOWIREEXTENSIONATPIN ON ;
```

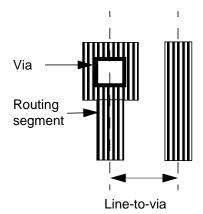
To control the wire extension at vias, double-check the via size and metal enclosure rule. Then use the WIREEXTENSION statement in the appropriate LAYER section.

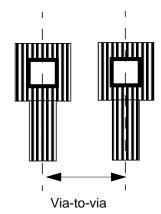
Guidelines for Routing Pitch

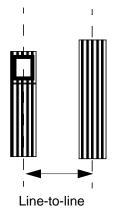
The following is a summary for choosing the right pitch for an existing design library. For detailed information on determining routing pitch, refer to the <u>Cadence Abstract Generator</u> User Guide.

Optimizing LEF Technology for Place and Route

Pitch Measurement

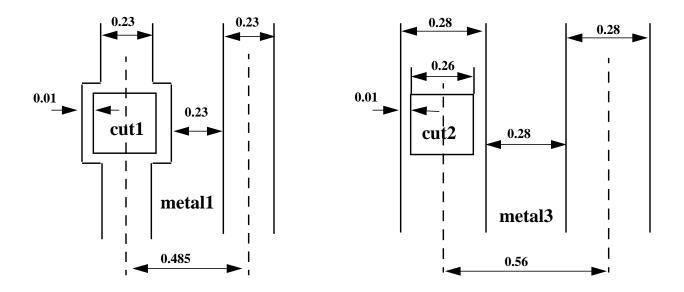






DESIGN RULE No. 1

W.1	Minimum width of metal1 = 0.23 um
S.1	Minimum space between two $metall$ regions = 0.23 um
W.2	Minimum and maximum width of cut1 = 0.26 um
E.1	Minimum extension of $metall$ beyond $cutl = 0.01$ um
W.3	Minimum width of metal3 = 0.28 um
S.2	Minimum space between two $metal3$ regions = 0.28 um
W.4	Minimum and maximum width of cut2 = 0.26 um
E.2	Minimum extension of metal1 beyond $cut2 = 0.01$ um



Although the minimum metall routing pitch is 0.485um from the design rule, you should use 0.56um instead, to match the metall routing pitch in the same preferred direction.

LEF Construct No. 1

```
LAYER metal1

TYPE ROUTING;

WIDTH 0.23;
```

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```
SPACING 0.23;
PITCH 0.56;
DIRECTION HORIZONTAL;

END metal1

LAYER metal3
TYPE ROUTING;
WIDTH 0.28;
SPACING 0.28;
PITCH 0.56;
DIRECTION HORIZONTAL;

END metal3
```

Recommendations

- Use line-to-via spacing for both the horizontal and vertical direction.
- Allow diagonal vias with the routing pitch.
- Align the routing pitch for metal1 and metal2, with the pins inside the standard cells.
- Have uniform routing pitch in the same preferred direction. The pitch ratio should be 2 3 or 1 2. It is better to define the metall pitch larger than necessary in order to achieve a 1 1 ratio because the metall width is usually smaller the metall and metall widths.

Pitch Recommendations for Library Development

- All pins should be on the grid, and only those portions of the pins that are accessible to the router should be modeled as pins. For example, 45 degree pin geometry.
- The height of the cell should be the even multiple of the metal1 pitch, and the width of the cell should be the even multiple of the metal2 pitch.
- The blockage modeling, especially for metal1, should be simplified as much as possible. For example, it is very common for the entire area within the cell boundary to be obstructed in metal1, so use a single rectangular blockage instead of many small blockages.

Guidelines for Wide Metal Spacing

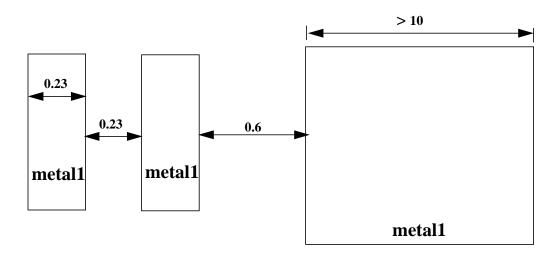
The SPACING statement in the LEF LAYER section is applied to both regular and special wires. You can use the Cadence® ultra router option frouteUseRangeRule to determine

Optimizing LEF Technology for Place and Route

which objects to check against the SPACING RANGE statement. The default checks both pin and obstruction.

DESIGN RULE No. 2

- S.1 Minimum space between two metal1 regions = 0.23 um
- S.2 Minimum space between metal lines with one or both metal line width and length are greater than 10um = 0.6 um



LEF CONSTRUCT No. 2

```
LAYER metal1
WIDTH 0.23;
SPACING 0.23;
SPACING 0.6 RANGE 10.002 1000;
END metal1
```

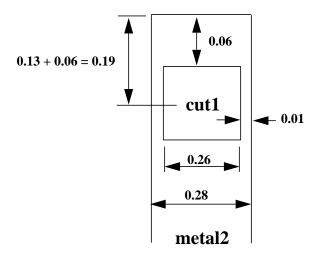
Guidelines for Wire Extension at Vias

The following guidelines are for wire extension at vias.

Optimizing LEF Technology for Place and Route

DESIGN RULE No. 3

W.1	Minimum and maximum width of cut1 = 0.26 um
W.2	Minimum width of metal2 = 0.28 um
E.1	Minimum extension of metal2 beyond cut1 = 0.01 um
E.2	Minimum extension of metal2 end-of-line region beyond cut1 = 0.06 um



LEF CONSTRUCT No. 3

```
LAYER metal2

TYPE ROUTING;

WIDTH 0.28;

SPACING 0.28;

PITCH 0.56;

WIREEXTENSION 0.19;

DIRECTION VERTICAL;

END metal2

VIA via23 DEFAULT

LAYER metal2;

RECT -0.14 -0.14 0.14 0.14;  # Use square via LAYER cut2;
```

Optimizing LEF Technology for Place and Route

```
RECT -0.13 -0.13 0.13 0.13 ;

LAYER metal3 ;

RECT -0.14 -0.14 0.14 0.14 ; # Use square via

END via23
```

Recommendations

- Use the WIREEXTENSION statement instead of defining multiple vias because the width of the metal2 in cut1 is the same as the default routing width of the metal2 layer.
- Define the DEFAULT VIA as a square via.

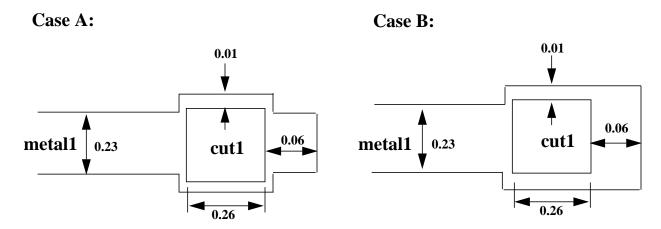
Guidelines for Default Vias

The following guidelines are for default vias.

Optimizing LEF Technology for Place and Route

DESIGN RULE No. 4

W.1	Minimum width of metal1 = 0.23 um
W.2	Minimum and maximum width of cut1 = 0.26 um
E.1	Minimum extension of metal1 beyond cut1 = 0.01 um
E.2	Minimum extension of metal1 end-of-line region beyond cut1 = 0.06 um



Use WIREEXTENSION and square DEFAULT VIA

Use Horizontal and Vertical DEFAULT VIAS

LEF CONSTRUCT No. 4 (Case B)

```
LAYER metal1

TYPE ROUTING;

WIDTH 0.23;

SPACING 0.23;

PITCH 0.56;

DIRECTION HORIZONTAL;

END metal1

VIA via12_H DEFAULT

LAYER metal1;

RECT -0.19 -0.14 0.19 0.14; # metal1 end-of-line
```

Optimizing LEF Technology for Place and Route

```
extension 0.6 in both directions
    LAYER cut1;
         RECT -0.13 -0.13 0.13 0.13;
    LAYER metal2 ;
         RECT -0.14 -0.14 0.14 0.14;
END via12 H
VIA via12_V DEFAULT
    LAYER metal1 ;
         RECT -0.14 -0.19 0.14 0.19 ;
                                       # metall end-of-line
         extension 0.6 in both directions
    LAYER cut1 ;
         RECT -0.13 -0.13 0.13 0.13;
    LAYER metal2 ;
         RECT -0.14 -0.14 0.14 0.14;
END via12_V
```

Recommendations

- If the width of the end-of-line metal extension is the same as the default metal routing width, as in Case A, use the WIREEXTENSION statement in the LEF LAYER section, and define a square via in the DEFAULT VIA section.
- If the width of the end-of-line metal extension is the same as the width of the via metal, as in Case B, define one horizontal DEFAULT VIA and one vertical DEFAULT VIA to cover the required metal extension area in both pregerred and non-preferred routing directions. Do not use the WIREEXTENSION statement in the LEF LAYER section.

Guidelines for Stack Vias (MAR Vias) and Samenet Spacing

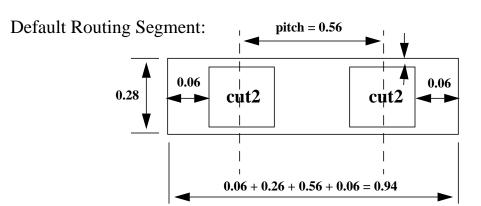
The following guidelines are for stack vias (minimum area rule) and SAMENET SPACING.

LEF/DEF 5.5 Language ReferenceOptimizing LEF Technology for Place and Route

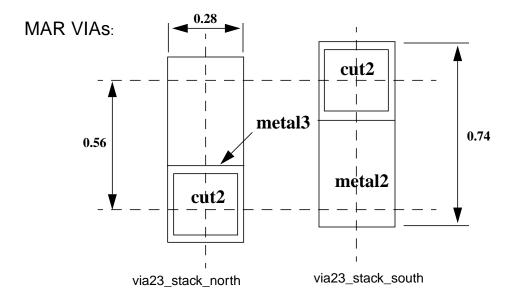
DESIGN RULE No. 5

W.1	Minimum width of metal2 = 0.28 um
W.2	Minimum and maximum width of cut2 = 0.26 um
E.1	Minimum extension of metal2 beyond cut2 = 0.01 um
A.1	Minimum area of metal2 = 0.2025 um
C.1	Cut2 can be fully or partially stacked on cut1, contact or any combination
W.1	Minimum width of metal3 = 0.28 um
W.2	Minimum and maximum width of cut3 = 0.26 um
E.1	Minimum extension of metal2 beyond cut3 = 0.01 um
A.1	Minimum area of metal3 = 0.2025 um
C.1	Cut3 can be fully or partially stacked on cut2, cut1, contact or any combination

Optimizing LEF Technology for Place and Route



Minimum routing area of metal3 = $0.28 \times 0.94 = 0.2632 > 0.2.25$ (MAR)



LEF CONSTRUCT No. 5

```
VIA via23_stack_north DEFAULT TOPOFSTACKONLY
     LAYER metal2 ;
          RECT -0.14 - 0.14 \ 0.14 \ 0.6; # MAR = 0.28 \times 0.74
     LAYER cut2 ;
```

```
RECT -0.13 -0.13 0.13 0.13;
     LAYER metal3 ;
          RECT -0.14 -0.14 0.14 0.14;
END via23_stack_north
VIA via23_stack_south DEFAULT TOPOFSTACKONLY
     LAYER metal2 ;
         RECT -0.14 - 0.6 \ 0.14 \ 0.14; # MAR = 0.28 \times 0.74
     LAYER cut2 ;
         RECT -0.13 -0.13 0.13 0.13;
     LAYER metal3 ;
         RECT -0.14 -0.14 0.14 0.14;
END via23 stack south
VIA via34_stack_east DEFAULT TOPOFSTACKONLY
     LAYER metal3 ;
          RECT -0.14 -0.14 0.6 0.14; # MAR = 0.28 x 0.74
     LAYER cut3 ;
         RECT -0.13 -0.13 0.13 0.13;
     LAYER metal4 ;
         RECT -0.14 -0.14 0.14 0.14;
END via34_stack_east
VIA via34_stack_west DEFAULT TOPOFSTACKONLY
     LAYER metal3 ;
         RECT -0.6 -0.14 \ 0.14 \ 0.14; # MAR = 0.28 \ x \ 0.74
     LAYER cut3 ;
         RECT -0.13 -0.13 0.13 0.13;
     LAYER metal4 ;
         RECT -0.14 -0.14 0.14 0.14;
END via34 stack west
SPACING
     SAMENET metal2 metal2 0.28 STACK;
     SAMENET metal3 metal3 0.28 STACK;
     SAMENET cut2 cut2 0.26;
     SAMENET cut3 cut3 0.26;
     SAMENET cut1 cut2 0.0 STACK;
     SAMENET cut2 cut3 0.0 STACK;
END SPACING
```

Optimizing LEF Technology for Place and Route

Recommendations

- The minimum metal routing segment (two vias between one pitch grid) with or without end-of-line metal extension should automatically satisfy the minimum area rule.
- If vias are stackable, create the TOPSTACKONLY vias with a rectangular shape blocking only one neighboring grid for both sides of the preferred routing direction. In other words, one north oriented and one south oriented for vertical-preferred routing layers, and one east oriented and one west oriented for horizontal-preferred routing layers.
- Use slightly larger dimensions for the via size to make them an even number, so they snap to the manufacturing grids.
- The STACK keyword in the SAMENETSPACING statements only allows vias to be fully overlapped (stacked) by SROUTE commands. To allow vias to be partially overlapped, set the environment variable SROUTE.ALLOWOVERLAPINSTACKVIA to TRUE.
- The metal1 layer does not require a MAR via because all metal1 pins should satisfy the minimum area rules.

Example of an Optimized LEF Technology File

```
VERSION 5.2;
NAMESCASESENSITIVE ON ;
BUSBITCHARS "[]";
UNITS
     DATABASE MICRONS 100 ;
END UNITS
LAYER metal1
     TYPE ROUTING ;
     WIDTH 0.23 ;
     SPACING 0.23;
     SPACING 0.6 RANGE 10.02 1000 ;
     PITCH 0.56;
     DIRECTION HORIZONTAL ;
END metal1
LAYER cut1
     TYPE CUT ;
END cut1
```

```
LAYER metal2
    TYPE ROUTING ;
    WIDTH 0.28 ;
     SPACING 0.28;
     SPACING 0.6 RANGE 10.02 1000 ;
     PITCH 0.56 ;
    WIREEXTENSION 0.19;
     DIRECTION VERTICAL ;
END metal2
LAYER cut2
    TYPE CUT ;
END cut2
LAYER metal3
    TYPE ROUTING ;
     WIDTH 0.28 ;
     SPACING 0.28 ;
     SPACING 0.6 RANGE 10.02 1000 ;
    PITCH 0.56 ;
     WIREEXTENSION 0.19;
     DIRECTION HORIZONTAL ;
END metal3
LAYER cut3
    TYPE CUT ;
END cut3
LAYER metal4
     TYPE ROUTING ;
     WIDTH 0.28 ;
     SPACING 0.28;
     SPACING 0.6 RANGE 10.02 1000 ;
     PITCH 0.56 ;
     WIREEXTENSION 0.19;
    DIRECTION VERTICAL ;
END metal4
```

```
LAYER cut4
    TYPE CUT ;
END cut4
LAYER metal5
    TYPE ROUTING ;
     WIDTH 0.28 ;
     SPACING 0.28;
     SPACING 0.6 RANGE 10.02 1000 ;
     PITCH 0.56 ;
     WIREEXTENSION 0.19;
     DIRECTION HORIZONTAL ;
END metal5
LAYER cut5
    TYPE CUT ;
END cut5
LAYER metal6
     TYPE ROUTING ;
     WIDTH 0.44;
     SPACING 0.46 ;
     SPACING 0.6 RANGE 10.02 1000 ;
     PITCH 1.12 ;
     DIRECTION VERTICAL ;
END metal6
### start DEFAULT VIA ###
VIA via12_H DEFAULT
     LAYER metal1 ;
         RECT -0.19 -0.14 0.19 0.14; # metall end-of-line ext 0.6
     LAYER cut1 ;
         RECT -0.13 -0.13 0.13 0.13;
     LAYER metal2 ;
         RECT -0.14 -0.14 0.14 0.14;
END via12_H
VIA via12_V DEFAULT
     LAYER metal1 ;
         RECT -0.14 -0.19 0.14 0.19; # metall end-of-line ext 0.6
     LAYER cut1 ;
```

```
RECT -0.13 -0.13 0.13 0.13;
     LAYER metal2 ;
          RECT -0.14 -0.14 0.14 0.14;
END via12_V
VIA via23 DEFAULT
     LAYER metal2 ;
         RECT -0.14 -0.14 0.14 0.14;
     LAYER cut2 ;
         RECT -0.13 -0.13 0.13 0.13;
     LAYER metal3 ;
         RECT -0.14 -0.14 0.14 0.14;
END via23
VIA via34 DEFAULT
     LAYER metal3 ;
         RECT -0.14 -0.14 0.14 0.14;
     LAYER cut3 ;
         RECT -0.13 -0.13 0.13 0.13;
     LAYER metal4 ;
         RECT -0.14 -0.14 0.14 0.14;
END via34
VIA via45 DEFAULT
     LAYER metal4 ;
         RECT -0.14 -0.14 0.14 0.14;
     LAYER cut4 ;
         RECT -0.13 -0.13 0.13 0.13;
     LAYER metal5 ;
         RECT -0.14 -0.14 0.14 0.14;
END via45
VIA via56_H DEFAULT
     LAYER metal5 ;
         RECT -0.24 -0.19 0.24 0.19 ;
     LAYER cut5 ;
         RECT -0.18 -0.18 0.18 0.18;
     LAYER metal6 ;
         RECT -0.27 -0.27 0.27 0.27;
END via56 H
```

```
VIA via56_V DEFAULT
     LAYER metal5 ;
          RECT -0.19 -0.24 0.19 0.24;
     LAYER cut5 ;
          RECT -0.18 -0.18 0.18 0.18;
     LAYER metal6 ;
          RECT -0.27 -0.27 0.27 0.27;
END via56_V
### end DEFAULT VIA ###
### start STACK VIA ###
VIA via23_stack_north DEFAULT TOPOFSTACKONLY
     LAYER metal2 ;
          RECT -0.14 - 0.14 \ 0.14 \ 0.6; # MAR = 0.28 \times 0.74
     LAYER cut2 ;
          RECT -0.13 -0.13 0.13 0.13;
     LAYER metal3 ;
          RECT -0.14 -0.14 0.14 0.14;
END via23 stack north
VIA via23 stack south DEFAULT TOPOFSTACKONLY
     LAYER metal2 ;
          RECT -0.14 - 0.6 \ 0.14 \ 0.14; # MAR = 0.28 \ x \ 0.74
     LAYER cut2 ;
          RECT -0.13 -0.13 0.13 0.13;
     LAYER metal3 ;
          RECT -0.14 -0.14 0.14 0.14;
END via23_stack_south
VIA via34_stack_east DEFAULT TOPOFSTACKONLY
     LAYER metal3 ;
          RECT -0.14 - 0.14 \ 0.6 \ 0.14; # MAR = 0.28 \times 0.74
     LAYER cut3 ;
          RECT -0.13 -0.13 0.13 0.13;
     LAYER metal4 ;
          RECT -0.14 -0.14 0.14 0.14;
END via34_stack_east
VIA via34_stack_west DEFAULT TOPOFSTACKONLY
     LAYER metal3 ;
          RECT -0.6 -0.14 \ 0.14 \ 0.14; # MAR = 0.28 \times 0.74
```

Optimizing LEF Technology for Place and Route

```
LAYER cut3 ;
          RECT -0.13 -0.13 0.13 0.13;
     LAYER metal4 ;
          RECT -0.14 -0.14 0.14 0.14;
END via34 stack west
VIA via45_stack_north DEFAULT TOPOFSTACKONLY
     LAYER metal4 ;
          RECT -0.14 - 0.14 \ 0.14 \ 0.6; # MAR = 0.28 \times 0.74
     LAYER cut4;
          RECT -0.13 -0.13 0.13 0.13;
     LAYER metal5 ;
          RECT -0.14 -0.14 0.14 0.14;
END via45_stack_north
VIA via45_stack_south DEFAULT TOPOFSTACKONLY
     LAYER metal4 ;
          RECT -0.14 - 0.6 \ 0.14 \ 0.14; # MAR = 0.28 \times 0.74
     LAYER cut4;
          RECT -0.13 -0.13 0.13 0.13;
     LAYER metal5 ;
          RECT -0.14 -0.14 0.14 0.14;
END via45_stack_south
VIA via56_stack_east DEFAULT TOPOFSTACKONLY
     LAYER metal5 ;
          RECT -0.19 -0.19 0.35 0.19; # MAR = 0.38 \times 0.54
     LAYER cut5 ;
          RECT -0.18 -0.18 0.18 0.18;
     LAYER metal6 ;
          RECT -0.27 -0.27 0.27 0.27;
END via56_stack_east
VIA via56 stack west DEFAULT TOPOFSTACKONLY
     LAYER metal5 ;
          RECT -0.35 -0.19 \ 0.19 \ 0.19; # MAR = 0.38 \times 0.54
     LAYER cut5 ;
          RECT -0.18 -0.18 0.18 0.18;
     LAYER metal6 ;
          RECT -0.27 -0.27 0.27 0.27;
END via56_stack_west
```

end STACK VIA

```
SPACING
    SAMENET metal1 metal1 0.23 STACK;
    SAMENET metal2 metal2 0.28 STACK;
    SAMENET metal3 metal3 0.28 STACK;
    SAMENET metal4 metal4 0.28 STACK;
    SAMENET metal5 metal5 0.28 STACK;
    SAMENET metal6 metal6 0.46 STACK;
    SAMENET cut1 cut1 0.26;
    SAMENET cut2 cut2 0.26;
    SAMENET cut3 cut3 0.26;
    SAMENET cut4 cut4 0.26;
    SAMENET cut5 cut5 0.35;
    SAMENET cut1 cut2 0.0 STACK;
    SAMENET cut2 cut3 0.0 STACK;
    SAMENET cut3 cut4 0.0 STACK;
    SAMENET cut4 cut5 0.0 STACK;
END SPACING
```

D

Calculating and Fixing Process Antenna Violations

This appendix describes process antenna violations and how you can use the router to fix them. It includes the following sections:

- Overview on page 228
- Using Process Antenna Keywords in the LEF and DEF Files on page 232
- Calculating Antenna Ratios on page 233
- Checking for Antenna Violations on page 248
- <u>Using Antenna Diode Cells</u> on page 253
- <u>Using DiffUseOnly</u> on page 254
- Calculations for Hierarchical Designs on page 255

Calculating and Fixing Process Antenna Violations

Overview

During deep submicron wafer fabrication, gate damage can occur when excessive static charges accumulate and discharge, passing current through a gate. If the area of the layer connected directly to the gate or connected to the gate through lower layers is large relative to the area of the gate and the static charges are discharged through the gate, the discharge can damage the oxide that insulates the gate and cause the chip to fail. This phenomenon is called the *process antenna effect* (PAE).

To determine the extent of the PAE, the router calculates the area of the layer relative to the area of the gates connected to it, or connected to it through lower layers. The number it calculates is called the *antenna ratio*. Each foundry sets a maximum allowable antenna ratio for the chips it fabricates.

For example, assume a foundry sets a maximum allowable antenna ratio of 500. If a net has two input gates that each have an area of 1 square micron, any metal layers that connect to the gates and have an area larger than 1,000 square microns have process antenna violations because they would cause the antenna ratio to be higher than 500:

Antenna Ratio =
$$\frac{\text{Area of metal layer}}{\text{Area of gates}}$$
 500 = $\frac{1000}{1+1}$

To tell the router the values to use when it calculates the antenna ratio, you set antenna keywords in the LEF and DEF files. The router measures potential damage caused by PAE by checking the ratio it calculates against the values specified by the antenna keywords. When it finds a net whose antenna ratio for a specified layer exceeds the maximum allowed value for that layer, it finds a *process antenna violation* and attempts to fix it using one or both of the following methods:

- Changing the routing so the routing layers connected to a gate or connected to a gate through lower layers are not so large that they build enough static charge to damage the gate
- Inserting diodes that protect the gate by providing an alternate path to discharge the static charge

LEF can specify several types of antenna ratios, including ratios for PAE damage on one layer only and ratios calculated by adding accumulated damage on several layers. In addition, LEF can specify ratios based on the area of the metal wires or the cut area of vias.

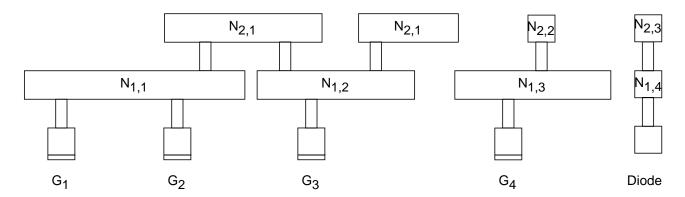
What Are Process Antennas?

In a chip manufacturing process, metal layers are built up, layer by layer, starting with the firstlevel metal layer (usually referred to as metal1). Next, the metal1-metal2 vias are created, then the second-level metal layer, then metal2-metal3 vias, and so on.

On each metal layer, metal is initially deposited so it covers the entire chip. Then, the unneeded portions of the metal are removed by etching, typically in plasma (charged particles).

Figure D-1 on page 229 shows a section of an imaginary chip after the unneeded metal from metal2 is removed.

Figure D-1



In the figure,

- Gate areas for transistors are labelled G_k , where k is a sequential number starting with 1.
- Wire segments are labelled $N_{i,j}$
 - N signifies that the wire segment is an electrically connected node
 - i specifies the metal layer to which the node belongs
 - j is a sequential number for the node on that metal layer
- Nodes are labelled so that all pieces of the metal geometry on layer $metal_i$ that are electrically connected by conductors at layers below *metal*; belong to the same node. For example, the two *metal2* wire segments that belong to node $N_{2,1}$ are electrically connected to gates G_1 , G_2 , and G_3 by a piece of wire on *metal1* (labelled $N_{1,2}$).

Thick oxide insulates the already-fabricated structures below *metal2*, preventing them from direct contact with the plasma. The *metal2* geometries, however, are exposed to the plasma,

Calculating and Fixing Process Antenna Violations

and collect charge from it. As the metal geometries collect charge, they build up voltage potential.

Because the metal geometries collect charge during the metallization process, they are referred to as process antennas. In general, the more area covered by the metal geometries that are exposed to the plasma (that is, the larger the process antennas), the more charge they can collect.

In <u>Figure D-1</u> on page 229, note the following:

- Node $N_{1,1}$ is electrically connected to gates G_1 and G_2 .
- Node $N_{1,2}$ is electrically connected to gate G_3 .
- Node $N_{2,1}$ (node $N_{2,1}$ has two pieces of metal) is electrically connected to gates G_1 , G_2 , and G_3 .
- Node $N_{1,3}$ and node $N_{2,2}$ are electrically connected to gate G_4 .
- Node $N_{1,4}$ and node $N_{2,3}$ are electrically connected to the diffusion (diode).

What Is the Process Antenna Effect (PAE)?

If the voltage potential across the gate oxide becomes large enough to cause current to flow across the gate oxide, from the process antennas to the gates to which the process antennas are electrically connected, the current can damage the gate oxide. The process antenna effect (PAE) is the term used to describe the build-up of charge and increase in voltage potential. The larger the total gate area that is electrically connected to the process antennas on a specific layer, the more charge the connected gates can withstand.

In the imaginary chip in <u>Figure D-1</u> on page 229, if the current were to flow, the following would happen, as a result of the node-gate connections:

- The charge collected by process antennas on nodes $N_{1,1}$, $N_{1,2}$, and $N_{2,1}$ would be discharged through one or more of gates G_1 , G_2 , and G_3 .
- The charge collected by process antennas on nodes $N_{1,3}$ and $N_{2,2}$ would be discharged through gate G_4 .
- The charge collected by process antennas on node $N_{1,4}$ and $N_{2,3}$ would be discharged through the diode.

What Is the Antenna Ratio?

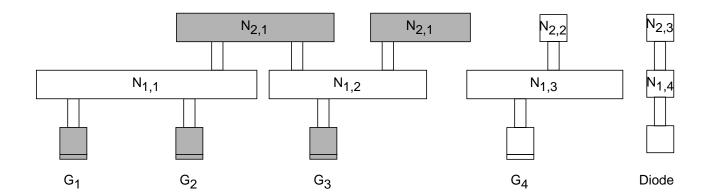
Because the total gate area that is electrically connected to a node (and therefore connected to the process antennas) determines the amount of charge from the process antennas the electrically connected gates can withstand, and because the size of the process antennas connected to the node determines how much charge the antennas collect, it is useful to calculate the ratio of the size of the process antennas on a node to the size of the gate area that is electrically connected to the node. This is the antenna ratio. The greater the antenna ratio, the greater the potential for damage to the gate oxide.

If you check a chip and obtain an antenna ratio greater than the threshold specified by the foundry, gate damage is likely to occur.

Figure D-2 on page 231 shows the same section of the imaginary chip as the previous figure. The shaded areas in this figure represent the process antennas on node $N_{2,1}$ and the gates to which they connect: gates G1, G2, and G3. The shaded gates discharge the electricity collected by the process antennas on node $N_{2,1}$.

Figure D-2

Area of process antennas on a node Antenna Ratio = Area of gates electrically connected to the node



What Can Be Done to Improve the Antenna Ratio?

If there is an alternate path for the current to flow, the charge on the node can be discharged through the alternate path before the voltage potential reaches a level that damages the gate. For example, a Zener diode, which allows current to flow in the reverse direction when the reverse bias reaches a specified breakdown voltage, provides an alternate path, and helps avoid building up so much charge at the node that the charge is discharged through the gate

Calculating and Fixing Process Antenna Violations

oxide. Diffusion features that form the output of a logic gate (source and drain of transistors) can provide such an alternate discharge path.

Routers typically use two methods to decrease the antenna ratio:

- Changing the routing by breaking the metal layers into smaller pieces
- Inserting antenna diode cells to discharge the current

Both of these methods supply alternate paths for the current. For details about how to specify antenna diode cells, see "Using Antenna Diode Cells" on page 253.

Using Process Antenna Keywords in the LEF and DEF Files

You tell the router the values to use for the gate, diffusion, and metal areas by setting values for process antenna keywords in the LEF and DEF files for your design. You also tell the router the values to use for the threshold process antenna ratios by setting the keywords.

The following table lists LEF version 5.5 antenna keywords.

If the keyword ends with	It refers to	Examples
area	Area of the gates or diffusion	ANTENNADIFFAREA ANTENNAGATEAREA
	Measured in square microns	
factor	Area multiplier used for the metal nodes	ANTENNAAREAFACTOR ANTENNASIDEAREAFACTOR
		Note: Use DIFFUSEONLY if you want the multiplier to apply only when connecting to diffusion. For more information, see "Using DiffUseOnly" on page 254.

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If the keyword ends with	It refers to	Examples
ratio	Relationship the	ANTENNAAREARATIO
	router is calculating	ANTENNASIDEAREARATIO
	Cum is used in	ANTENNADIFFAREARATIO
	keywords for cumulative antenna ratio.	ANTENNADIFFSIDEAREARATIO
		ANTENNACUMAREARATIO
		ANTENNACUMSIDEAREARATIO
	iano.	ANTENNACUMDIFFAREARATIO
		ANTENNACUMDIFFSIDEAREARATIO

Calculating Antenna Ratios

Tools should calculate antenna ratios using one of the following models:

The partial checking model

Using this model, you calculate damage to gates by process antennas on one layer. For example, if you use the partial checking model to calculate the PAE referred to a gate from *metal3*, you do not consider any potential damages referred to that gate from metallization steps on *metal1* or *metal2*.

You use this model to calculate a partial antenna ratio (PAR). A PAR tells you if any single metallization step is likely to inflict damage to a gate.

The cumulative checking model

This model is more conservative than the partial checking model. It adds damage to a gate caused by the PAE referred to the gate from each metallization step, starting from *metal1* up to the layer that is being checked. For example, if you use the cumulative checking model to calculate the PAE referred to a gate from *metal3*, you add the PAR from the relevant antenna areas on *metal1*, *metal2*, and *metal3*.

You use this model to calculate a cumulative antenna ratio (CAR). A CAR adds the damages on successive layers together to accumulate them as the layers are built up.

Calculating the Antenna Area

The area used to model the charge-collecting ability of a node is called the *antenna area*. The router calculates the antenna area for one of the following areas:

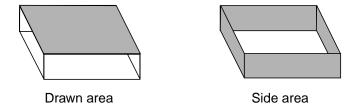
■ The drawn area (the top surface area of the process antenna)

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The side area (the area of the sides of the process antenna)

Figure D-3 on page 234 shows drawn and side areas.

Figure D-3



Antenna Area Factor

You can increase or decrease the calculated antenna area by specifying an antenna area factor in the LEF file.

- Use ANTENNAAREAFACTOR to adjust the calculation of the drawn area.
- Use ANTENNASIDEAREAFACTOR to adjust the calculation of the side area.

The default value of both factors is 1.

Calculating a PAR

The formula to calculate a PAR is

$$PAR(N_{i,j},G_k) = \frac{Area(N_{i,j}) \times F}{G_k \in C(N_{i,j})}$$

$$\sum_{G_k} Area(G_k)$$

 $\texttt{PAR} \, (\, \mathtt{N}_{i,\,j}, \, \mathtt{G}_k \,) \text{ is the partial antenna ratio for node } \underline{\jmath} \text{ on } \underline{\textit{metal}}_i \text{ with respect to gate } \mathtt{G}_k, \text{ where } \mathtt{G}_k \text{ is electrically connected to node } \mathtt{N}_{\underline{\imath}\,,\,\underline{\jmath}} \text{ by layer } \underline{\imath} \text{ or below.}$

 $Area(N_{i,j})$ is the drawn or side area of node $N_{i,j}$.

F is an optional scaling factor (AntennaAreaFactor or AntennaSideAreaFactor).

Calculating and Fixing Process Antenna Violations

 $C(N_{i,j})$ is the set of gates G_k that are electrically connected to $N_{i,j}$ through the layers below $metal_i$.

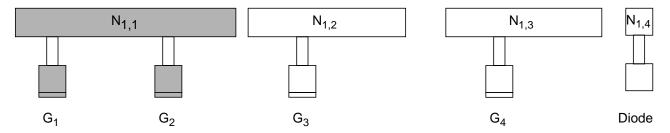
 $Area(G_k)$ is the drawn or side area of gate G_k . (The reason to include the G_k parameter for PAR is to maintain uniformity with the notation for CAR.)

Note: For a specified node $N_{i,j}$, the PAR $(N_{i,j}, G_k)$ for all gates G_k that are connected to the node $N_{i,j}$ using $metal_i$ or below are identical.

Calculations for PAR on the First Metal Layer

<u>Figure D-4</u> on page 235 shows a section of an imaginary chip after the first metal layer is processed.

Figure D-4



The shaded areas in the figure represent the wire segment and the gates whose areas you must compute to evaluate the formula below.

To calculate PAR ($N_{i,j}$, G_k) for node $N_{1,1}$, a node on the first metal layer, with respect to gate G_1 , use the following formula:

$$PAR (N_{1,1},G_1) = \frac{Area(N_{1,1}) \times F}{Area(G_1) + Area(G_2)}$$

Because gates g_1 and g_2 both connect to node n_1 , the following statement is true:

$$PAR(N_{1,1},G_1) = PAR(N_{1,1},G_2)$$

To calculate PAR for node $N_{1,2}$, another node on the first metal layer, with respect to gate G_3 , use the following formula:

PAR
$$(N_{1,2},G_3) = \frac{Area(N_{1,2}) \times F}{Area(G_3)}$$

Calculating and Fixing Process Antenna Violations

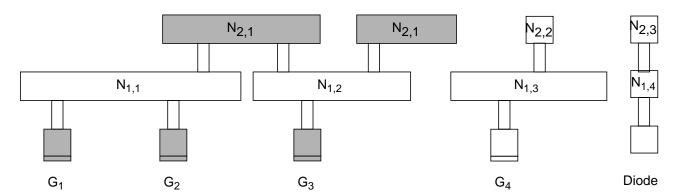
To calculate PAR ($N_{i,j}$, G_k) for node $N_{1,3}$, another node on the first metal layer, with respect to gate G_4 , use the following formula:

PAR
$$(N_{1,3},G_4) = \frac{Area(N_{1,3}) \times F}{Area(G_4)}$$

Calculations for PAR on the Second Metal Layer

Figure D-5 on page 236 shows the chip after the second metal layer is processed.

Figure D-5



The shaded areas in the figure represent the wire segments and the gates whose areas you must compute to evaluate the formula below.

 $N_{2,1}$ consists of two pieces of metal on the second layer that are electrically connected at this step in the fabrication process. Therefore, to calculate PAR ($N_{2,1}$, G_1), you must add the area of both pieces together.

To calculate PAR ($N_{i,j}$, G_k) for node $N_{2,1}$, a node on the second metal layer, with respect to gate G_1 , use the following formula:

PAR
$$(N_{2,1},G_1) = \frac{Area(N_{2,1}) \times F}{Area(G_1) + Area(G_2) + Area(G_3)}$$

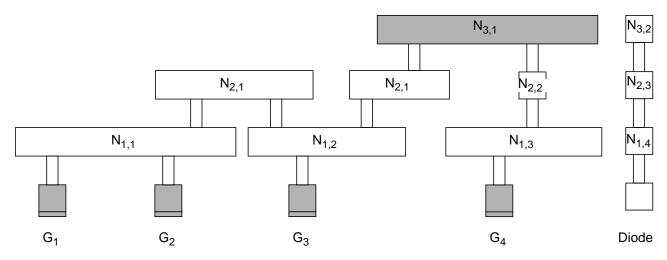
As on the first layer,

$$PAR(N_{2,1},G_1) = PAR(N_{2,1},G_2) = PAR(N_{2,1},G_3)$$

Calculations for PAR on the Third Metal Layer

Figure D-6 on page 237 shows the chip after the third metal layer is processed.

Figure D-6



The shaded areas in the figure represent the wire segment and the gates whose areas you must compute to evaluate the formula below.

To calculate PAR $(N_{i,j}, G_k)$ for node $N_{3,1}$, a node on the third metal layer, with respect to gate G_1 , use the following formula:

$$PAR (N_{3,1},G_1) = \frac{Area(N_{3,1}) \times F}{Area(G_1) + Area(G_2) + Area(G_3) + Area(G_4)}$$

As on the prior layers,

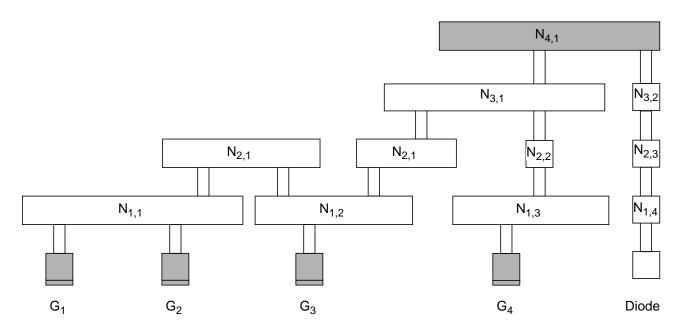
$$PAR(N_{3,1},G_1) = PAR(N_{3,1},G_2) = PAR(N_{3,1},G_3) = PAR(N_{3,1},G_4)$$

Calculations for PAR on the Fourth Metal Layer

Figure D-7 on page 238 shows the chip after the fourth metal layer is processed.

Calculating and Fixing Process Antenna Violations

Figure D-7



The shaded areas in the figure represent the wire segment and the gates whose areas you must compute to evaluate the formula below.

To calculate PAR (N_i , j, G_k) for the fourth metal layer, use the following formula:

$$PAR (N_{4,1},G_1) = \frac{Area(N_{4,1}) \times F}{Area(G_1) + Area(G_2) + Area(G_3) + Area(G_4)}$$

As on the prior layers,

$$PAR(N_{4,1},G_1) = PAR(N_{4,1},G_2) = PAR(N_{4,1},G_3) = PAR(N_{4,1},G_4)$$

Note: Node $N_{4,1}$ is connected to the diffusion layer through the output diode. After the router calculates the antenna ratio, it compares its calculations to the area of the diffusion, instead of the area of the gates.

Calculating a CAR

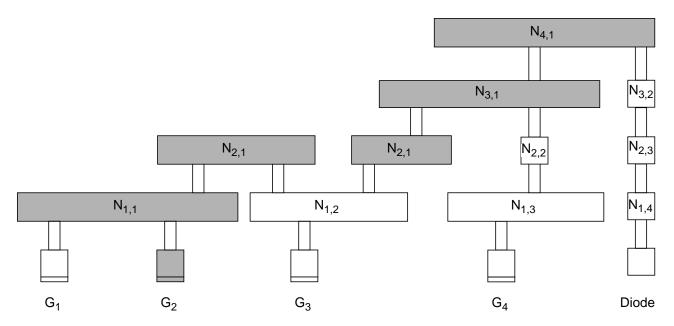
To calculate a CAR, the router adds the PARs for all the relevant nodes on the specified or lower metal layers that are electrically connected to a gate. Therefore, CAR (N_i , $_j$, G_k) designates the cumulative damage to gate \mathbf{G}_k by metallization steps up to the current level of metal, i.

Note: In practice, the router only needs to keep track of the worst-case CAR; however, the CARs for all of the gates shown in Figure D-8 on page 239 are described here.

Calculating and Fixing Process Antenna Violations

The router calculates an antenna ratio with respect to a node-gate pair. To find the CAR for the node N_i , j - gate G_k pair, you trace the path of the current between gate G_k and node N_i , j and add the PAR with respect to gate G_k for the all nodes in the path between the first metal layer and layer i that you can trace back to G_k .

Figure D-8



The path of the current between gate G_2 and node $N_{4,1}$ is shaded.

/Important

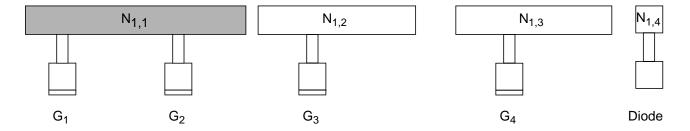
In <u>Figure D-8</u> on page 239, node $\mathbb{N}_{1,2}$ is not shaded because it was not electrically connected to \mathbb{G}_2 when metal1 was processed. That is, because the charge accumulated on $\mathbb{N}_{1,2}$ when metal1 was processed cannot damage gate \mathbb{G}_1 , the router does not include it in the calculations for $CAR(\mathbb{N}_{2,1},\mathbb{G}_1)$.

Another way to explain this is to say that the PAE from node $\mathbb{N}_{1,2}$ with respect to gate \mathbb{G}_2 is 0.

Calculations for CAR on the First Metal Layer

<u>Figure D-9</u> on page 240 shows the chip after the first metal layer is processed.

Figure D-9



In the figure above,

$$CAR(N_{1,1},G_1) = PAR(N_{1,1},G_1)$$

 $CAR(N_{1,1},G_2) = PAR(N_{1,1},G_2)$

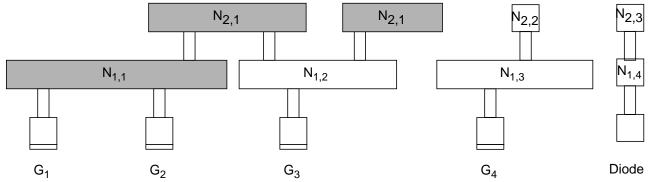
Because PAR($N_{1,1}$, G_1) equals PAR($N_{1,1}$, G_2), CAR($N_{1,1}$, G_1) equals CAR($N_{1,1}$, G_2).

Note: In general, $CAR(N_{i,j},G_k)$ equals $CAR(N_{i,j},G_{k'})$ if the two gates G_k and $G_{k'}$ are electrically connected to the same node on metal1, the lowest layer that is subject to the process antenna effect.

Calculations for CAR on the Second Metal Layer

Figure D-10 on page 240 shows the chip after the second metal layer is processed.

Figure D-10



The path of the current between gate G_1 and node $N_{2,1}$ is shaded. Note that node N_{2,1} comprises two pieces of metal.

Calculating and Fixing Process Antenna Violations



In the figure above, $\mathrm{N}_{1,2}$ is not included in the calculations for $\mathrm{CAR}\left(\mathrm{N}_{2,1},\mathrm{G}_{1}\right)$ because it was not electrically connected to G_{1} when metal1 was processed. That is, because the charge accumulated on $\mathrm{N}_{1,2}$ when metal1 was processed cannot damage gate G_{1} , the router does not include it in the calculations for $\mathrm{CAR}\left(\mathrm{N}_{2,1},\mathrm{G}_{1}\right)$.

In the figure above,

$$CAR(N_{2,1},G_1) = PAR(N_{1,1},G_1) + PAR(N_{2,1},G_1)$$

 $CAR(N_{2,1},G_2) = PAR(N_{1,1},G_2) + PAR(N_{2,1},G_2)$

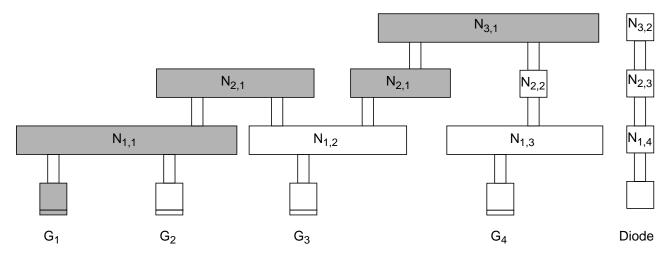
Gates G_1 and G_2 have the same history with regard to PAE because they are connected to the same piece of *metal1*, so they have the same CAR for any node on a specified layer:

$$CAR(N_{2,1},G_1) = CAR(N_{2,1},G_2)$$

Calculations for CAR on the Third Metal Layer

<u>Figure D-11</u> on page 241 shows the chip after the third metal layer is processed.

Figure D-11



The path of the current between gate G_1 and node $N_{3,1}$ is shaded.

Calculating and Fixing Process Antenna Violations

Gate G₁

In the figure above,

$$CAR(N_{3,1},G_1) = PAR(N_{1,1},G_1) + PAR(N_{2,1},G_1) + PAR(N_{3,1},G_1)$$

Gate G₂

In the figure above,

$$CAR(N_{3,1},G_2) = PAR(N_{1,1},G_2) + PAR(N_{2,1},G_2) + PAR(N_{3,1},G_2)$$

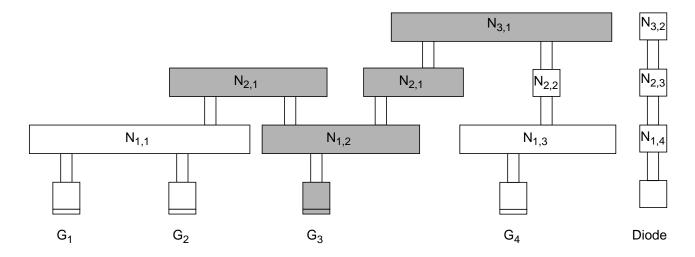
 $\begin{array}{l} {\rm CAR}\,({\rm N_{3\,,\,1}\,,G_1}) \ \ \text{equals} \ \ {\rm CAR}\,({\rm N_{3\,,\,1}\,,G_2}) \ \ \text{because gates} \ {\rm G_1} \ \ \text{and} \ {\rm G_2} \ \ \text{are both electrically} \\ {\rm connected} \ \ \text{to the same node,} \ {\rm N_{1\,,1}}, \ \ \text{on} \ \ \textit{metal1} \ \ \text{and therefore have the same history with} \\ {\rm regard} \ \ \text{to PAE}. \ \ \text{Therefore, the formula for} \ \ {\rm CAR}\,({\rm N_{3\,,\,2}\,,G_2}) \ \ \text{is} \ \ {\rm CAR}\,({\rm N_{3\,,\,1}\,,G_1}) \ \ = \ \ {\rm CAR}\,({\rm N_{3\,,\,1}\,,G_2}) \\ \end{array}$

Gates G₃ and G₄

Gates G_3 and G_4 are not connected to the same node on *metal1* and therefore do not have the same history with regard to PAE. Therefore, the $CAR(N_{3,1},G_3)$ and $CAR(N_{3,1},G_4)$ do not necessarily equal $CAR(N_{3,1},G_1)$ or $CAR(N_{3,1},G_2)$.

In Figure D-12 on page 242, the relevant areas for calculating CAR for gate G_3 are shaded.

Figure D-12



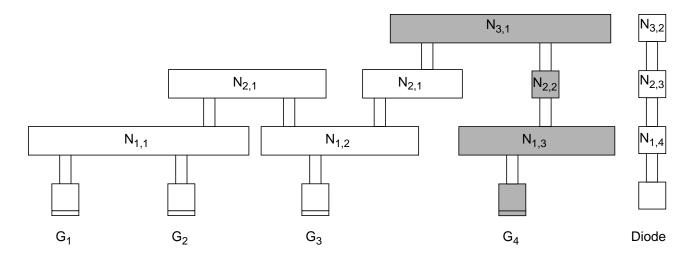
In the figure above,

Calculating and Fixing Process Antenna Violations

$$CAR(N_{3,1},G_3) = PAR(N_{1,2},G_3) + PAR(N_{2,1},G_3) + PAR(N_{3,1},G_3)$$

In Figure D-13 on page 243, the relevant areas for calculating CAR for gate G_4 are shaded.

Figure D-13



In the figure above,

$$CAR(N_{3,1},G_4) = PAR(N_{1,3},G_4) + PAR(N_{2,2},G_4) + PAR(N_{3,1},G_4)$$

Calculations for CAR on the Fourth Metal Layer

The following figure shows the chip after the fourth metal layer is processed.

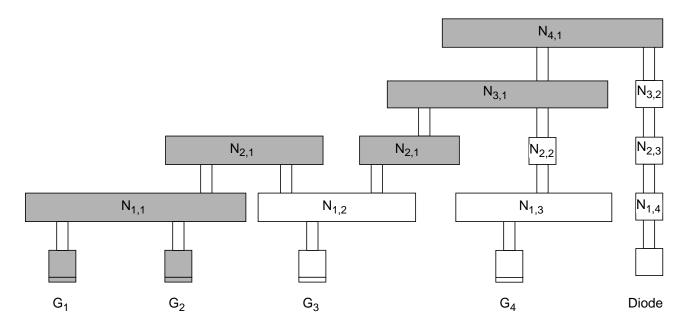
Note: Node $\mathbb{N}_{4,1}$ is connected to the diffusion layer through the output diode. After the router calculates the antenna ratio, it compares its calculations to the area of the diffusion, instead of the area of the gates.

Gates G₁ and G₂

In <u>Figure D-14</u> on page 244, the relevant areas for calculating $CAR(N_{4,1}, G_1)$ and $CAR(N_{4,1}, G_2)$ are shaded.

Calculating and Fixing Process Antenna Violations

Figure D-14



In the figure above,

$$\begin{aligned} & \text{CAR}(N_{4,1}, G_1) &= \text{PAR}(N_{1,1}, G_1) + \text{PAR}(N_{2,1}, G_1) \\ &+ \text{PAR}(N_{3,1}, G_1) + \text{PAR}(N_{4,1}, G_1) \end{aligned}$$

$$& \text{CAR}(N_{4,1}, G_2) &= \text{PAR}(N_{1,1}, G_2) + \text{PAR}(N_{2,1}, G_2) \\ &+ \text{PAR}(N_{3,1}, G_2) + \text{PAR}(N_{4,1}, G_2) \end{aligned}$$

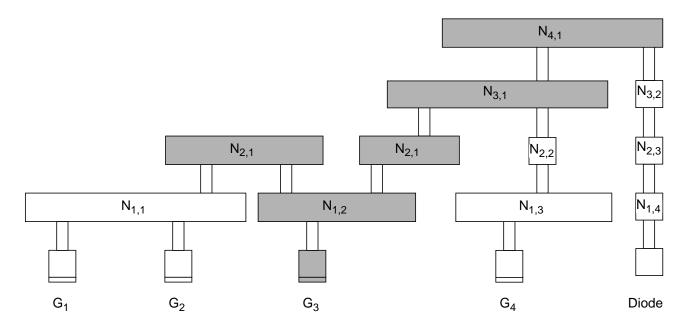
$$& \text{CAR}(N_{4,1}, G_1) &= \text{CAR}(N_{4,1}, G_2)$$

Gate G₃

In Figure D-15 on page 245, the relevant areas for calculating CAR ($N_{4,1}$, G_3) are shaded.

Calculating and Fixing Process Antenna Violations

Figure D-15



In the figure above,

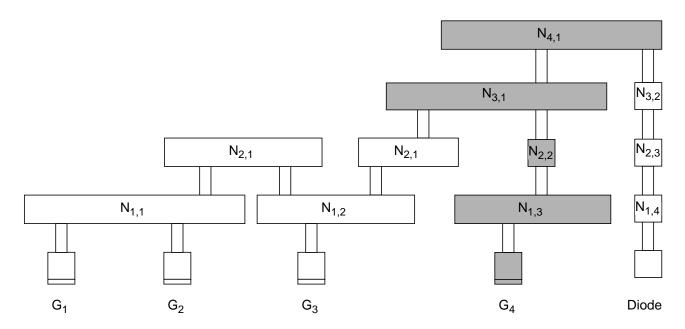
$$\begin{array}{lll} \text{CAR}(\text{N}_{4,1},\text{G}_3) &=& \text{PAR}(\text{N}_{1,2},\text{G}_3) &+& \text{PAR}(\text{N}_{2,1},\text{G}_3) \\ &+& \text{PAR}(\text{N}_{3,1},\text{G}_3) &+& \text{PAR}(\text{N}_{4,1},\text{G}_3) \end{array}$$

 ${\tt CAR}\,(\,{\rm N}_{4\,,\,1}\,,\,{\rm G}_3\,)\,\,\text{does not equal CAR}\,(\,{\rm N}_{4\,,\,1}\,,\,{\rm G}_1\,)\,\,\text{or CAR}\,(\,{\rm N}_{4\,,\,1}\,,\,{\rm G}_2\,)\,\,\text{because it is not connected to the same node on }\textit{metal1}\,.$

Gate G₄

In <u>Figure D-16</u> on page 246, the relevant areas for calculating CAR ($N_{4,1}$, G_4) are shaded.

Figure D-16



In the figure above,

$$\begin{array}{lll} \text{CAR}\left(N_{4,1}, G_{4}\right) &=& \text{PAR}\left(N_{1,3}, G_{4}\right) &+& \text{PAR}\left(N_{2,2}, G_{4}\right) \\ &+& \text{PAR}\left(N_{3,1}, G_{4}\right) &+& \text{PAR}\left(N_{4,1}, G_{4}\right) \end{array}$$

 $\mathtt{CAR}\left(\mathtt{N_{4,1}},\mathtt{G_4}\right) \text{ does not equal } \mathtt{CAR}\left(\mathtt{N_{4,1}},\mathtt{G_1}\right), \mathtt{CAR}\left(\mathtt{N_{4,1}},\mathtt{G_2}\right), \text{ or } \mathtt{CAR}\left(\mathtt{N_{4,1}},\mathtt{G_3}\right) \text{ because }$ it is not connected to the same node on metal1.

Calculating Ratios for a Cut Layer

The router calculates damage from a cut layer separately from damage from a metal layer. Calculations for the cut layers do not use side area modelling.

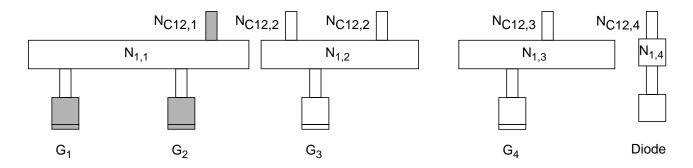
In the figures and text that follow,

- Cij is the cut layer between $metal_i$ and $metal_i$.
- $N_{Cij,k}$ specifies an electrically connected node on Cij.
- The nodes are numbered sequentially, from left to right.

Calculating a PAR on a Cut Layer

Figure D-17 on page 247 shows the chip after the C12 process step.

Figure D-17



In the figure above,

$$PAR(N_{C12,1},G_1) = \frac{Area(N_{C12,1},G_1) \times F}{Area(G_1) + Area(G_2)}$$

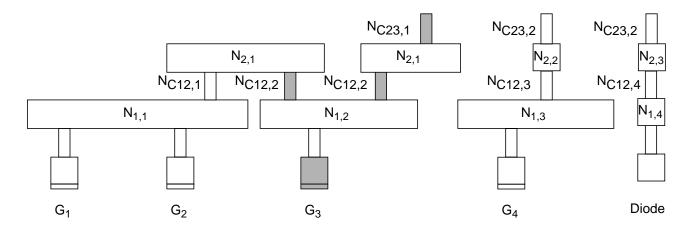
As in calculations on the metal layers,

$$PAR(N_{C12,1},G_1) = PAR(N_{C12,2},G_2)$$

Calculating a CAR on a Cut Layer

Figure D-18 on page 247 shows the chip after the C23 process step.

Figure D-18

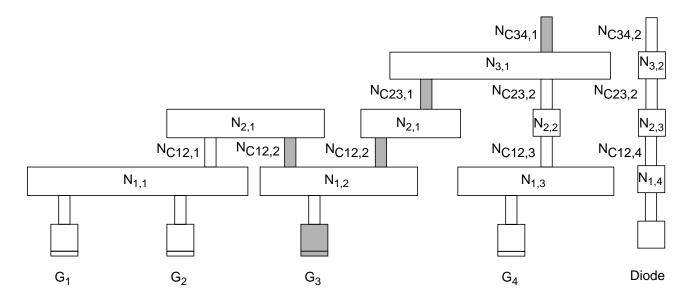


The router calculates the CAR with respect to gate G3 after the cut C23 process step as follows:

$$\mathsf{CAR}(\mathsf{N}_{\mathsf{C23},1},\mathsf{G}_3) = \ \frac{\mathsf{Area}(\mathsf{N}_{\mathsf{C23},1},\mathsf{G}_3) \times \mathsf{F}}{\mathsf{Area}(\mathsf{G}_3)} \ + \ \frac{\mathsf{Area}(\mathsf{N}_{\mathsf{C12},2},\mathsf{G}_3) \times \mathsf{F}}{\mathsf{Area}(\mathsf{G}_3)}$$

Figure D-19 on page 248 shows the chip after the C34 process step.

Figure D-19



The router calculates the CAR with respect to gate G3 after the cut C34 process step as follows:

$$\mathsf{CAR}(\mathsf{N}_{\mathsf{C34},1},\mathsf{G_3}) = \frac{\mathsf{Area}(\mathsf{N}_{\mathsf{C34},1},\mathsf{G_3}) \times \mathsf{F}}{\mathsf{Area}(\mathsf{G_3})} \ + \ \frac{\mathsf{Area}(\mathsf{N}_{\mathsf{C23},1},\mathsf{G_3}) \times \mathsf{F}}{\mathsf{Area}(\mathsf{G_3})} \ + \ \frac{\mathsf{Area}(\mathsf{N}_{\mathsf{C12},2},\mathsf{G_3}) \times \mathsf{F}}{\mathsf{Area}(\mathsf{G_3})}$$

Checking for Antenna Violations

For each metal layer, the router performs several antenna checks, using the keywords and values specified in the LEF or DEF file. The router can perform the following four types of antenna checks, depending on the keywords you set in the LEF file:

- **Area Ratio Check**
- Side Area Ratio Check

Calculating and Fixing Process Antenna Violations

- Cumulative Area Ratio Check
- Cumulative Side Area Ratio Check

Area Ratio Check

The area ratio check compares the PAR for each layer to the value of the ANTENNAAREARATIO or ANTENNADIFFAREARATIO.

The router calculates the PAR as follows:

PAR
$$(N_i, j, G_k) = \frac{\text{Drawn area of } N_i, j \times \text{AntennaAreaFactor}}{\Sigma \text{ Area of gates connected below } N_i, j}$$

Note: The ANTENNAAREAFACTOR has a default value of 1.

According to the formula above, the area ratio check finds the PAR for node $N_{i,j}$ with respect to gate G_k by dividing the drawn area of the node by the area of the gates that are electrically connected to it. If the PAR is greater than the ANTENNAREARATIO or ANTENNADIFFAREARATIO specified in the LEF file, the router finds a process antenna violation and attempts to fix it.

The link between PAR ($N_{i,j}$, G_k) and a PAE violation at node $N_{i,j}$ depends on whether node $N_{i,j}$ is connected to a piece of diffusion, as follows:

- If there is no connection from node $N_{i,j}$ to a diffusion area through the current and lower layers, a violation occurs when the PAR is greater than the ANTENNAAREARATIO.
- If there is a connection from node $N_{i,j}$ to a diffusion area through current and lower layers, a violation occurs when the PAR is greater than the ANTENNADIFFAREARATIO.
- If there is a connection from node $N_{i,j}$ to a diffusion area through current and lower layers, and ANTENNADIFFAREA is not specified for an output or inout pin, the value is 0.

Side Area Ratio Check

The side area ratio check compares the PAR computed based on the side area of the nodes for each layer to the value of the ANTENNASIDEAREARATIO or ANTENNADIFFSIDEAREARATIO.

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The router calculates the PAR as follows:

PAR
$$(N_{i,j}, G_{k}) = \frac{\text{Side area of } N_{i,j} \times \text{AntennaSideAreaFactor}}{\Sigma \text{ Area of gates connected below } N_{i,j}}$$

Note: The ANTENNASIDEAREAFACTOR has a default value of 1.

According to the formula above, the area ratio check finds the PAR for node $\mathtt{N}_{i,j}$ with respect to gate \mathtt{G}_k by dividing the side area of the node by the area of the gates that are electrically connected to $\mathtt{N}_{i,j}$. If the PAR is greater than the ANTENNASIDEAREARATIO or ANTENNADIFFSIDEAREARATIO specified in the LEF file, the router finds a process antenna violation and attempts to fix it.

The link between PAR $(N_{i,j},G_k)$ and a PAE violation at node $N_{i,j}$ depends on whether node $N_{i,j}$ is connected to a piece of diffusion, as follows:

- If there is no connection to the diffusion area through the current and lower layers, a violation occurs when the PAR is greater than the ANTENNASIDEAREARATIO.
- If there is a connection to the diffusion area through current and lower layers, a violation occurs when the PAR is greater than the ANTENNADIFFSIDEAREARATIO.
- If there is a connection to the diffusion area through current and lower layers, and ANTENNADIFFAREA is not specified for an output or inout pin, the value is 0.

Cumulative Area Ratio Check

The cumulative area ratio check compares the CAR to the value of ANTENNACUMAREARATIO or ANTENNACUMDIFFAREARATIO. The CAR is equal to the sum of the PARs of all nodes on the same or lower layers that are electrically connected to the gate.

Note: When you use CARs, you can ignore metal layers by not specifying the CAR keywords for those layers. For example, if you want to check *metal1* using a PAR and the remaining metal layers using a CAR, you can define ANTENNAAREARATIO or ANTENNASIDEAREARATIO for *metal1*, and ANTENNACUMAREARATIO or ANTENNACUMSIDEAREARATIO for the remaining metal layers.

The cumulative area ratio check finds the CAR for node $\mathrm{N}_{i,j}$ with respect to gate G_k by adding the PARs for all layers of metal, from the current layer down to metal1, for all nodes that are electrically connected G_k . If the CAR is greater than the ANTENNACUMAREARATIO or ANTENNACUMDIFFAREARATIO specified in the LEF file, the router finds a process antenna violation and attempts to fix it.

Calculating and Fixing Process Antenna Violations

The link between CAR ($N_{i,j}$, G_k) and a PAE violation at node $N_{i,j}$ depends on whether node $N_{i,j}$ is connected to a piece of diffusion, as follows:

- If there is no connection to a diffusion area through the current and lower layers, a violation occurs when the CAR is greater than the ANTENNACUMAREARATIO.
- If there is a connection to a diffusion area through current and lower layers, a violation occurs when the CAR is greater than the ANTENNACUMDIFFAREARATIO.
- If there is a connection to a diffusion area through current and lower layers, and ANTENNADIFFAREA is not specified for an output or inout pin, the value is 0.

Cumulative Side Area Ratio Check

The cumulative side area ratio check compares the CAR to the value of the ANTENNACUMSIDEAREARATIO or ANTENNACUMDIFFAREARATIO.

Note: When you use CARs, you can ignore metal layers by not specifying the CAR keywords for those layers. For example, if you want to check *metal1* using a PAR and the remaining metal layers using a CAR, you can define ANTENNAAREARATIO or ANTENNASIDEAREARATIO for *metal1*, and ANTENNACUMAREARATIO or ANTENNACUMSIDEAREARATIO for the remaining metal layers.

The formula for this check is the same as for the ANTENNACUMAREARATIO check, except that the router uses the ANTENNASIDEAREAFACTOR instead of the ANTENNAAREAFACTOR in the calculations.

The cumulative side area ratio check finds the CAR for node $N_{i,j}$ with respect to gate G_k by adding the PARs for all layers of metal, from the current layer down to metal1, for all nodes that are electrically connected G_k . If the CAR is greater than the ANTENNACUMSIDEAREARATIO or ANTENNACUMDIFFAREARATIO specified in the LEF file, the router finds a process antenna violation and attempts to fix it.

- If there is no connection to a diffusion area through the current and lower layers, a violation occurs when the CAR is greater than the ANTENNACUMSIDEAREARATIO.
- If there is a connection to a diffusion area through current and lower layers, a violation occurs when the CAR is greater than the ANTENNACUMSIDEAREARATIO.
- If there is a connection to a diffusion area through current and lower layers, and ANTENNACUMDIFFAREA is not specified for an output or inout pin, the value is 0.

Example Using the Antenna Keywords

The following example is a portion of a LEF file that shows the antenna keywords for a process that has cumulative area ratio damage for metal and cut layers.

Assume you have the following antenna rules for your process:

- 1. A maximum cumulative metal to gate area ratio of 1000
- 2. If a diode of greater than .1 microns is connected to the metal, the maximum metal ratio is: ratio = diode_area x 2000 + 5000
- 3. A maximum cumulative via to gate area ratio of 20
- 4. If a diode of greater than .1 microns is connected to the via, the maximum via ratio is: ratio = diode_area x 200 + 100

The corresponding LEF file would include:

```
LAYER M1
 TYPE ROUTING ;
 ANTENNACUMAREARATIO 1000;
 ANTENNACUMDIFFAREARATIO
       PWL ( ( 0 1000 ) ( 0.099 1000 ) ( 0.1 5200 ) ( 100 205000 ) ) ;
END M1
LAYER VIA1
 TYPE CUT ;
 ANTENNACUMAREARATIO 20 ;
  ANTENNACUMDIFFAREARATIO
       PWL ( ( 0 20 ) ( 0.099 20 ) ( 0.1 120 ) ( 100 20100 ) );
END VIA1
```

A typical standard cell that has only *M1* pins and routing inside of it would have:

```
MACRO INV1X
 CLASS CORE ;
 PIN IN
    DIRECTION INPUT ;
    ANTENNAGATEAREA .5 LAYER M1 ; \# connects to 0.5 \mum^2 poly gate
    ANTENNAPARTIALMETALAREA 1.0 LAYER M1; \# has 1.0 \mum^2 M1 area.
           # Note that it should not include the M1 pin area, just the M1 routing
```

Calculating and Fixing Process Antenna Violations

```
# area that is not included in the PIN shapes. In many cases, all of the
           \# M1 routing is included in the PIN, so this value is 0, and not in the
           # LEF at all.
   ANTENNAMAXAREACAR 10.0 LAYER M1; # has 10.0 cumulative ratio so far.
           # This value can include area from internal poly routing if poly routing
           # damage is accumulated with the metal layers. It does not include
           \# the area of the M1 pin area, just the M1 routing area that is not
           # included in the PIN shapes. If poly damage is not included, and all
           \# of the M1 routing is included in the PIN, this value will be 0, and
           # not in the LEF at all.
 END IN
 PIN OUT
   DIRECTION OUTPUT ;
   ANTENNADIFFAREA .2 LAYER M1 ; \# connects to 0.2 \mum^2 difusion area
   ANTENNAPARTIALMETALAREA 1.0 LAYER M1 ; \# has 1.0 \mum^2 M1 area
    # No ANTENNAMAXAREACAR value because no internal poly gate is connected
 END OUT
END INV1X
```

Using Antenna Diode Cells

Routers generally use one of two methods to fix process antenna violations:

- Change the routing by breaking the metal layers into smaller pieces
- Insert antenna diode cells to discharge the current

Changing the Routing

One method routers use to fix antenna violations is to limit the charge that is collected through the metal nodes exposed to the plasma. To do this, it goes up one layer or pushes the routing down one layer whenever the process antenna ratio exceeds the ratio set in the LEF file.

The router changes the routing by disconnecting nets with antenna violations and making the connections to higher metal layers instead. It does not make the connections to lower layers. This method works because the top metal layer always completes the connection from the gate to the output drain area of the driver, which is a diode that provides a discharge path.

Calculating and Fixing Process Antenna Violations

Inserting Antenna Diode Cells

The second method routers use to repair antenna violations is to insert antenna diode cells in the design. The electrical charges on the metal that connects to the diodes is then discharged through the diode diffusion layer and substrate. The router inserts the diode cells automatically.

The following example shows a LEF definition of an antenna diode cell, with the CLASS CORE ANTENNACELL and ANTENNADIFFAREA defined:

```
MACRO antennal
CLASS CORE ANTENNACELL;
...
PIN ANT1
AntennaDiffArea 1.0;
PORT
LAYER metall;
RECT 0.190 2.380 0.470 2.660;
END
END ANT1
END antennal
```

Using DiffUseOnly

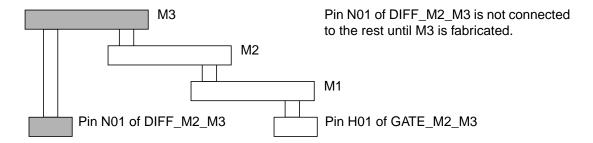
LEF defines only one value for ANTENNAAREAFACTOR and one value for ANTENNASIDEAREAFACTOR, with or without DIFFUSEONLY, per layer. If you specify more than one antenna area or side area factor for a layer, only the last one is used. The AREAFACTOR value lets you scale the value of the metal area. If you use the DIFFUSEONLY keyword, only metal attached to diffusion is scaled.

Calculating and Fixing Process Antenna Violations

Suppose you have the following LEF file:

```
Antenna.lef
LAYER M3
TYPE ROUTING ;
PITCH 0.56 ;
DIRECTION HORIZONTAL ;
WIDTH 0.28; SPACING 0.28;
SPACING 0.36 RANGE 1.0 250.0;
CAPACITANCE CPERSQDIST 0.0009762;
RESISTANCE RPERSO 0.129 ;
THICKNESS 0.60;
AntennaAreaRatio 10000 ;
AntennaDiffAreaRatio 10000 ;
AntennaAreaFactor 1.2 DiffUseOnly;
AntennaSideAreaRatio 5000;
AntennaDiffSideAreaRatio 5000 ;
AntennaSideAreaFactor 1.4 DiffUseOnly;
END M3
```

Figure D-20



In the figure,

- The input pin H01 of GATE_M2_M3 connects the metal wires to metal1, metal2, and metal3 in sequence.
- The ANTENNAAREAFACTOR 1.2 DIFFUSEONLY and ANTENNASIDEAREAFACTOR 1.4 DIFFUSEONLY apply to *metal3* routing.
- Prior to metal3 fabrication, there is no path to the diffusion diode. This causes the default factor of 1.0 to apply to the metal1 and metal2 segments shown when calculating PARs.

Calculations for Hierarchical Designs

The following section illustrates computation of antenna ratios for hierarchical designs.

Calculating and Fixing Process Antenna Violations

LEF and DEF Keywords for Hierarchical Designs

If the keyword ends with	It refers to	Examples
area sideArea	Drawn area or side area of the metal wires. Measured in square microns.	ANTENNAPARTIALCUTAREA ANTENNAPARTIALMETALAREA ANTENNAPARTIALMETALSIDEAREA ANTENNAPINDIFFAREA ANTENNAPINGATEAREA ANTENNAPINPARTIALCUTAREA
CAR	Relationship the router is calculating CAR is used in keywords for cumulative antenna ratio.	ANTENNAMAXAREACAR ANTENNAMAXCUTCAR ANTENNAMAXSIDEAREACAR ANTENNAPINMAXAREACAR ANTENNAPINMAXCUTCAR ANTENNAPINMAXSIDEAREACAR

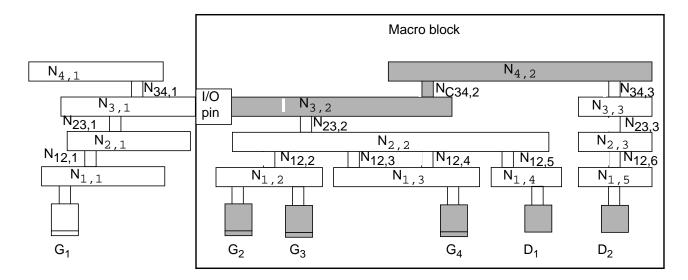
Design Example

<u>Figure D-21</u> on page 257 represents a macro block. This block can be a custom hard block or part of a bottom-up hierarchical flow. The resulting PAE values will be the same in either case. In the example,

- Gates G_1 , G_2 , G_3 , and G_4 are the same size.
- Node $N_{1,3}$ is larger than node $N_{1,2}$.
- Vias (cuts) are all the same size.
- The I/O pin is on metal3.
- The area of diffusion for D_1 is $area(Diff_1)$.
- The area of diffusion for D_2 is $area(Diff_2)$.
- The area of the cut layer that connects node $N_{3,1}$ and node $N_{4,2}$ is $area(N_{C34,1})$.
- Any damage from the poly layer or poly-to-metal1 via is ignored.

LEF/DEF 5.5 Language Reference Calculating and Fixing Process Antenna Violations

Figure D-21



Relevant Metal Areas

- The relevant metal area for PAE calculations is the partial metal drawn area and side area connected directly to the I/O pin on the inside of the macro on the specified layer.
- Only the same metal layer as the I/O pin or above is needed for PAR calculations in hierarchical designs.

Important

Do not include the drawn area or side area of the I/O pin in the area calculations for the block, because the router includes these areas in the calculations for the upper level. Only the internal routing area that is not part of the I/O pin should be included.

For the design in the figure above, you must specify values for the following metal areas in the LEF file:

```
ANTENNAPARTIALMETALAREA area(N_{3.1},) LAYER Metal3;
ANTENNAPARTIALMETALAREA area(N_{4,2}) LAYER Metal4;
ANTENNAPARTIALMETALSIDEAREA sideArea(N3.2) LAYER Metal3;
ANTENNAPARTIALMETALSIDEAREA sideArea(N_{4,2}) LAYER Metal4;
```

You do not need to specify an ANTENNAPARTIALMETALAREA or ANTENNAPARTIALSIDEMETALAREA for any layer lower than metal3 because the I/O pin is on *metal3*; that is, there is no connection outside the block until *metal3* is processed.

Calculating and Fixing Process Antenna Violations

Relevant Gate, Diffusion, and Cut Areas

- The relevant gate and diffusion areas are the gate and diffusion areas that connect directly to the I/O pin on the specified layer or are electrically connected to the pin through lower layers.
- The relevant partial cut area is above the current pin layer and inside the macro on the specified layer.

For the design in the figure above, you must specify values for the following gate, diffusion, and cut areas in the LEF file:

```
ANTENNAGATEAREA area(G_2+G_3+G_4) LAYER Metal3; ANTENNADIFFAREA area(Diff_1) LAYER Metal3; ANTENNADIFFAREA area(Diff_1+Diff_2) LAYER Metal4; ANTENNAPARTIALCUTAREA area(N_{34,2}) LAYER via34;
```

Calculating the CAR

Use the following keywords to calculate the actual CAR on the I/O pin layer or above.

- The relevant maximum CAR value of the drawn and side areas are from the metal layer that is on or below the I/O pin layer.
- The relevant maximum CAR value of the cut layer is from the cut layer that is immediately above the I/O pin layer.

Use the following keywords to calculate the maximum CAR values:

$$\begin{split} & \text{ANTENNAMAXAREACAR} \, \left(\frac{N_{1,3}}{G_4} + \frac{N_{2,2}}{G_2 + G_3 + G_4} + \frac{N_{3,1}}{G_2 + G_3 + G_4} \right) \, \, \, \text{Layer Metab} \, ; \\ & \text{ANTENNAMAXSIDEAREACAR} \, \left(\frac{N_{1,3}}{G_4} + \frac{N_{2,2}}{G_2 + G_3 + G_4} + \frac{N_{3,1}}{G_2 + G_3 + G_4} \right) \, \, \, \text{Layer Metab} \, ; \\ & \text{ANTENNAMAXCUTCAR} \, \left(\frac{N_{12,3} + N_{12,4}}{G_4} + \frac{N_{23,2}}{G_2 + G_3 + G_4} + \frac{N_{34,2}}{G_2 + G_3 + G_4} \right) \, \, \, \text{Layer Metab} \, ; \end{split}$$

Sample LEF File for a Bottom-Up Hierarchical Design

For a macro block like that shown in <u>Figure D-21</u> on page 257, you should have the following pin information in your LEF file, ignoring SIDEAREA values:

PIN example

Calculating and Fixing Process Antenna Violations

```
ANTENNAGATEAREA 0.3 LAYER METAL3 ; # area of G_2 + G_3 + G_4 ANTENNADIFFAREA 1.0 LAYER METAL3 ; # area of D_1 ANTENNAPARTIALMETALAREA 10.0 LAYER METAL3 ; # area of N_{3,1} ANTENNAMAXAREACAR 100.0 LAYER METAL3 ; # max CAR of N_{3,1} ANTENNAPARTIALCUTAREA 0.1 LAYER VIA34 ; # area of N_{34,2} ANTENNAMAXCUTCAR 5.0 LAYER VIA34 ; # max cut CAR of N_{34,2} ANTENNAGATEAREA 0.3 LAYER METAL4 ; # area of G_2 + G_3 + G_4 ANTENNADIFFAREA 2.0 LAYER METAL4 ; # area of D_1 + D_2 ANTENNAPARTIALMETALAREA 12.0 LAYER METAL4 ; # area of N_{4,2} ANTENNAMAXAREACAR 130.0 LAYER METAL4 ; # max CAR of N_{4,2} END example
```

Top-Down Hierarchical Design Example

In a top-down design, the router uses the top-level antenna values to check for process antennas inside the block. If the top level is routed first, the top-level routing CAR and PAR values can be passed down into the DEF for the sub-block. This method can also be used to pass down estimated "budgets" for PAR and CAR values.

Set the following keywords in the DEF file for the design. In a top-down design you assign a value to the I/O pin that indicates how much routing, CAR, and PAR occurred outside the block already.

```
MACRO macroName

CLASS BLOCK;

PIN pinName

DIRECTION OUTPUT;

[ANTENNAPINPARTIALMETALAREA value [LAYER layerName];]...

[ANTENNAPINPARTIALMETALSIDEAREA value [LAYER layerName];]...

[ANTENNAPINGATEAREA value [LAYER layerName];]...

[ANTENNAPINDIFFAREA value [LAYER layerName];]...

[ANTENNAPINMAXAREACAR value [LAYER layerName];]...

[ANTENNAPINMAXSIDEAREACAR value [LAYER layerName];]...

[ANTENNAPINPARTIALCUTAREA value [LAYER cutlayerName];]...

END Z

END macroName
```

Calculating and Fixing Process Antenna Violations

Sample DEF File for a Top-Down Hierarchical Design

An example of the DEF keywords for Figure D-21 on page 257 would be:

```
PINS 100 ;

- example + NET example1

+ ANTENNAPINPARTIALMETALAREA (N_{3,1}) LAYER Metal3 ;

+ ANTENNAPINPARTIALMETALSIDEAREA (N_{3,1}) LAYER Metal3 ;

+ ANTENNAPINGATEAREA (G_1) LAYER Metal3 ;

# NO ANTENNAPINDIFFAREA for this example

+ ANTENNAPINMAXAREACAR \left(\frac{N_{1,1}+N_{2,1}+N_{3,1}}{G_1}\right) LAYER Metal3;

+ ANTENNAPINMAXSIDEAREACAR \left(\frac{N_{1,1}+N_{2,1}+N_{3,1}}{G_1}\right) LAYER Metal3;

+ ANTENNAPINPARTIALCUTAREA (N_{34,1}) LAYER via34 ;

+ ANTENNAPINMAXCUTCAR \left(\frac{N_{34,1}+N_{23,1}+N_{12,1}}{G_1}\right) LAYER Metal3;

+ ANTENNAPINGATEAREA (G_1) LAYER Metal4 ;

+ ANTENNAPINGATEAREA (G_1) LAYER Metal4 ;

+ ANTENNAPINPARTIALMETALAREA (N_{4,1}) LAYER Metal4 ;

+ ANTENNAPINPARTIALMETALAREA (N_{4,1}) LAYER Metal4 ;

+ ANTENNAPINPARTIALMETALSIDEAREA (N_{4,1}) LAYER Metal4 ;
```

END PINS

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